

STRUCTURE SEARCH

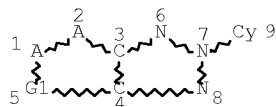
=> d his l31

(FILE 'HCAPLUS' ENTERED AT 13:44:57 ON 18 MAY 2009)

L31 29 S L27 OR L30
SAV TEMP L31 FAN775HCP/A

=> d que stat l31

L3 STR



REP G1=(0-20) A

NODE ATTRIBUTES:

DEFAULT MLEVEL IS ATOM

GGCAT IS UNS AT 9

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 9

STEREO ATTRIBUTES: NONE

L4 SCR 2043

L6 2975 SEA FILE=REGISTRY SSS FUL L3 AND L4

L9 1424 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L6

L10 1225078 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON OPTIC?

L11 153 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L9 AND L10

L12 QUE SPE=ON ABB=ON PLU=ON DEVICE? OR CONTRIVANCE? OR
INVENTION? OR APPARAT? OR APP## OR IMPLEMENT? OR INSTR
UMENT? OR TOOL? OR UTENSIL? OR EQUIP?

L13 149242 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L10(2A)L12

L14 41 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L13 AND L11

L15 86 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L9 AND
?LUMIN?

L16 7 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L14 AND L15

L19 57 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L9 AND
(REFLECT? OR TRANSMIS?)

L20 18 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L9 AND (ANOD?
OR CATHOD? OR ELECTROD?)

L21 3 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L19 AND L20

L22 QUE SPE=ON ABB=ON PLU=ON (CHARG? OR HOLE# OR ELECT
RON# OR E) (2A) (TRANSPORT? OR MIGRAT? OR TRANSFER? OR MO
VE# OR MOVING# OR MOVEMENT? OR CARR?)

L23 5 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L9 AND L22

L24 28 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L16 OR L20 OR
L21 OR L23

L25 QUE SPE=ON ABB=ON PLU=ON PY=<2004 NOT P/DT

L26 QUE SPE=ON ABB=ON PLU=ON (PY=<2004 OR PRY=<2004 OR
AY=<2004 OR MY=<2004 OR REVIEW/DT) AND P/DT

L27 24 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L24 AND (L25
OR L26)

L28 QUE SPE=ON ABB=ON PLU=ON PHOTOELECTR? OR PHOTO?(A)E
LECTR?

L29 7 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L9 AND L28

L30 7 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L29 AND (L25
OR L26)

L31 29 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L27 OR L30

STRUCTURE SEARCH RESULTS

=> d l31 1-29 ibib ed abs hitstr hitind

L31 ANSWER 1 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2006:367294 HCAPLUS Full-text

DOCUMENT NUMBER: 144:413585

TITLE: Production of high quantum yield
luminescent monomers, oligomers and
polymers and their usesINVENTOR(S): Morishita, Yoshii; Nomura, Satoyuki; Tsuda,
Yoshihiro; Tai, Seiji; Marrocco, Matthew, L.,
III; Motamedi, Farshad, J.; Wang, Li-Sheng;
Liang, YongchaoPATENT ASSIGNEE(S): Hitachi Chemical Co., Ltd., Japan; Maxdem
Incorporated

SOURCE: PCT Int. Appl., 168 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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WO 2006041221	A1	20060420	WO 2005-JP19352	2005 1014

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W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ,
CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG,
ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP,
KE, KG, KM, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, LY,
MA, MD, MG, MK, MN, MW, MX, MZ, NA, NG, NI, NO, NZ, OM,
PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY,
TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA,
ZM, ZW

RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR,
HU, IE, IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI,
SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR,
NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL,
SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM

US 20060083945	A1	20060420	US 2004-966370	2004 1015
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JP 2008516008	T	20080515	JP 2007-516129	2005 1014
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CN 101203538	A	20080618	CN 2005-80035298	2007 0416
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KR 2007118582	A	20071217	KR 2007-710893	2007 0514
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PRIORITY APPLN. INFO.:	US 2004-966370	A	2004 1015
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WO 2005-JP19352	W	2005 1014
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10/553,775-294324-EIC SEARCH

OTHER SOURCE(S): MARPAT 144:413585

ED Entered STN: 21 Apr 2006

AB The invention relates generally to novel high quantum yield ~~luminescent~~ monomers, oligomers, and polymers, comprising benzotriazole repeating units and derivs. thereof have been discovered and utilized in ~~optical devices~~ and components therefor, including ~~electroluminescent devices~~, light emitting devices, ~~photoluminescent devices~~, organic light emitting diodes (OLEDs), OLED displays, lights, as sensors, UV stabilizers, and the like. Thus, a 1,4-dibromo-2,5-bis(hexyloxy)benzene-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer with PL peak at 495 nm (green color) was prepared and coated on a Paytron P-coated ITO glass and followed by vapor deposited an Al film to give an EL device with high quantum yield.

IT 883741-20-8P, 1,4-Dibromo-2,5-bis(hexyloxy)benzene-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-21-7P, 2,5-Bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-22-8P, 2,5-Bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer, SRU 883741-23-9P, 2,5-Di(hexyloxy)-1,4-dibromobenzene-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole copolymer 883741-28-4P, 2-(4,7-Bis(chloromethyl)-2H-benzotriazol-2-yl)-4,6-di-tert-butylphenol-1,4-bis(chloromethyl)-2,5-dimethoxybenzene copolymer 883741-29-5P, 1,4-Dibromo-2,5-dihexylbenzene-2,5-dihexyl-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-30-8P, 1,4-Dibromo-2,5-bis(hexyloxy)benzene-2,5-dihexyl-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-31-9P, 2,5-Bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-1,4-dibromo-2,5-bis(hexyloxy)benzene-2,5-dihexyl-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-32-0P, 2,5-Bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-1,4-dibromo-2,5-dihexylbenzene-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-33-1P, 2,6-Dibromonaphthalene-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-34-2P, 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-35-3P, 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-dihexyl-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-36-4P, 3,6-Dibromo-9-phenyl-9H-carbazole-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-37-5P, 2,4-Di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluorene-7-yl)-1,3,2-dioxaborolane copolymer 883741-38-6P, 2,4-Di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluorene-7-yl)-1,3,2-dioxaborolane copolymer, SRU 883741-39-7P, 2,7-Dibromo-9,9-dioctyl-9H-fluorene-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-

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tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer 883741-43-3F,
 2,5-Bis(4-bromophenyl)-1,3,4-oxadiazole-2-(4,7-bis(5-bromothiophen-2-yl)-2H-benzo[d][1,2,3]triazol-2-yl)-4,6-di-tert-butylphenol-4-bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester copolymer 883741-41-3F,
 1,4-Dibromo-2,5-bis(hexyloxy)benzene-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzo[d][1,2,3]triazole copolymer 883741-42-2F,
 1,4-Dibromo-2,5-dihexylbenzene-2,5-dihexyl-1,4-benzenebisboronic ethylene glycol ester-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzo[d][1,2,3]triazole copolymer 883741-43-3F,
 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer 883741-44-4F,
 2,7-Dibromo-9,9-dioctyl-9H-fluorene-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer
 RL: DEV (Device component use); IMF (Industrial manufacture); PRP (Properties); PREP (Preparation); USES (Uses)
 (production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)

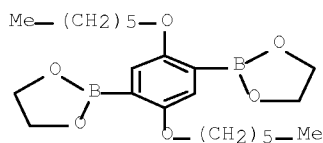
RN 883741-20-6 HCAPLUS

CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with
 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and
 1,4-dibromo-2,5-bis(hexyloxy)benzene (9CI) (CA INDEX NAME)

CM 1

CRN 849691-48-1

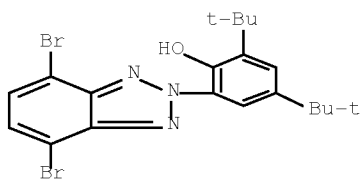
CMF C22 H36 B2 O6



CM 2

CRN 784163-33-3

CMF C20 H23 Br2 N3 O

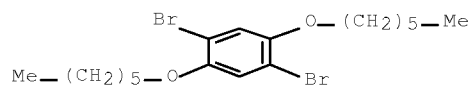


10/553,775-294324-EIC SEARCH

CM 3

CRN 128424-36-2

CMF C18 H28 Br2 O2



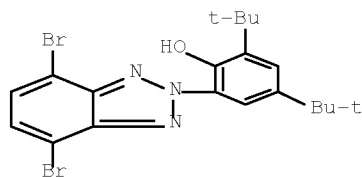
RN 883741-21-7 HCAPLUS

CN Boronic acid, [2,5-bis(hexyloxy)-1,4-phenylene]bis-, polymer with 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)phenol (9CI) (CA INDEX NAME)

CM 1

CRN 784163-33-3

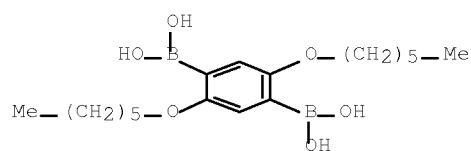
CMF C20 H23 Br2 N3 O



CM 2

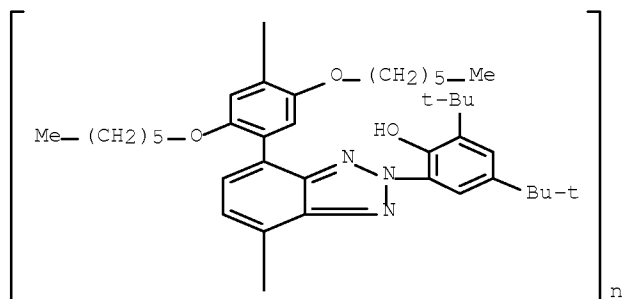
CRN 171089-85-3

CMF C18 H32 B2 O6



RN 883741-22-8 HCAPLUS

CN Poly[[2-[3,5-bis(1,1-dimethylethyl)-2-hydroxyphenyl]-2H-benzotriazole-4,7-diyl][2,5-bis(hexyloxy)-1,4-phenylene]] (9CI) (CA INDEX NAME)



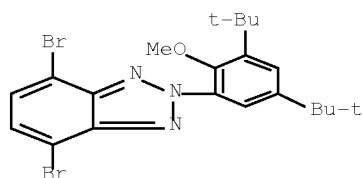
RN 883741-23-9 HCAPLUS

CN 2H-Benzotriazole, 2-[3,5-bis(1,1-dimethylethyl)-2-methoxyphenyl]-4,7-dibromo-, polymer with 1,4-dibromo-2,5-bis(hexyloxy)benzene (9CI) (CA INDEX NAME)

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CRN 883741-16-0

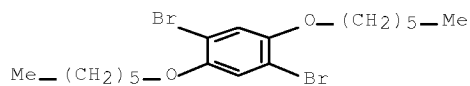
CMF C21 H25 Br2 N3 O



CM 2

CRN 128424-36-2

CMF C18 H28 Br2 O2



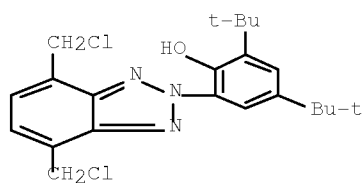
RN 883741-28-4 HCAPLUS

CN Phenol, 2-[4,7-bis(chloromethyl)-2H-benzotriazol-2-yl]-4,6-bis(1,1-dimethylethyl)-, polymer with 1,4-bis(chloromethyl)-2,5-dimethoxybenzene (9CI) (CA INDEX NAME)

CM 1

CRN 883741-27-3

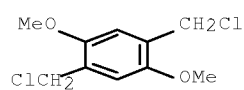
CMF C22 H27 Cl2 N3 O



CM 2

CRN 3752-97-4

CMF C10 H12 Cl2 O2



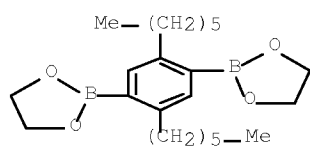
RN 883741-29-5 HCAPLUS

CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 1,4-dibromo-2,5-dihexylbenzene and 2,2'-(2,5-dihexyl-1,4-phenylene)bis[1,3,2-dioxaborolane] (9CI)
(CA INDEX NAME)

CM 1

CRN 883741-17-1

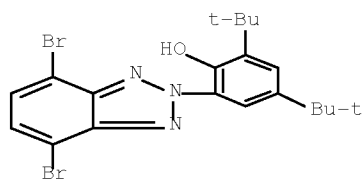
CMF C22 H36 Br2 O4



CM 2

CRN 784163-33-3

CMF C20 H23 Br2 N3 O

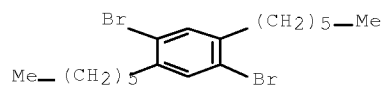


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CM 3

CRN 117635-21-9

CMF C18 H28 Br2



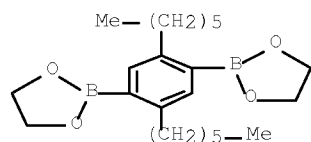
RN 883741-30-8 HCAPLUS

CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 1,4-dibromo-2,5-bis(hexyloxy)benzene and 1,4-dibromo-2,5-bis(hexyloxy)-1,3,2-dioxaborolane (9CI) (CA INDEX NAME)

CM 1

CRN 883741-17-1

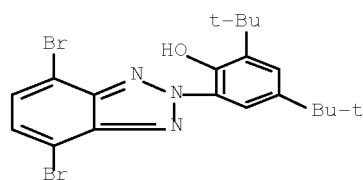
CMF C22 H36 B2 O4



CM 2

CRN 784163-33-3

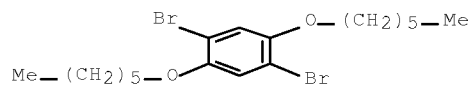
CMF C20 H23 Br2 N3 O



CM 3

CRN 128424-36-2

CMF C18 H28 Br2 O2



10/553,775-294324-EIC SEARCH

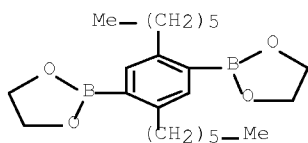
RN 883741-31-9 HCAPLUS

CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with
2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane],
1,4-dibromo-2,5-bis(hexyloxy)benzene and
2,2'-(2,5-dihexyl-1,4-phenylene)bis[1,3,2-dioxaborolane] (9CI)
(CA INDEX NAME)

CM 1

CRN 883741-17-1

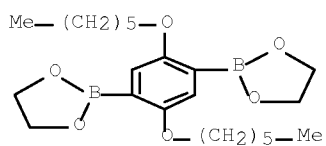
CMF C22 H36 B2 O4



CM 2

CRN 849691-48-1

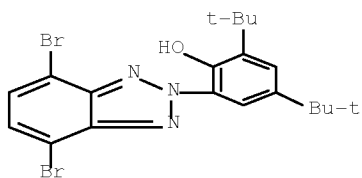
CMF C22 H36 B2 O6



CM 3

CRN 784163-33-3

CMF C20 H23 Br2 N3 O

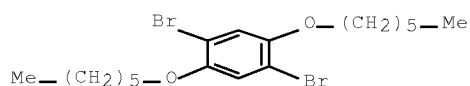


CM 4

CRN 128424-36-2

CMF C18 H28 Br2 O2

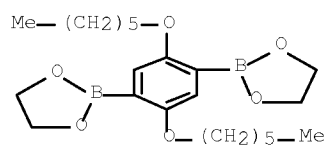
10/553,775-294324-EIC SEARCH



RN 883741-32-0 HCAPLUS
 CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with
 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and
 1,4-dibromo-2,5-dihexylbenzene (9CI) (CA INDEX NAME)

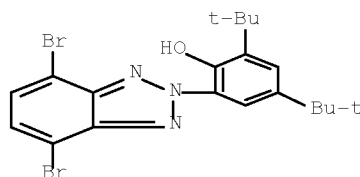
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CRN 849691-48-1
 CMF C22 H36 B2 O6



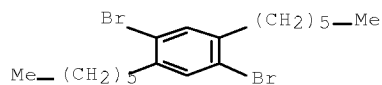
CM 2

CRN 784163-33-3
 CMF C20 H23 Br2 N3 O



CM 3

CRN 117635-21-9
 CMF C18 H28 Br2

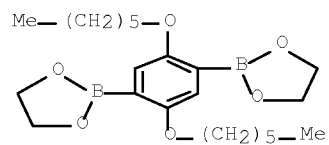


RN 883741-33-1 HCAPLUS
 CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with
 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and
 2,6-dibromonaphthalene (9CI) (CA INDEX NAME)

10/553,775-294324-EIC SEARCH

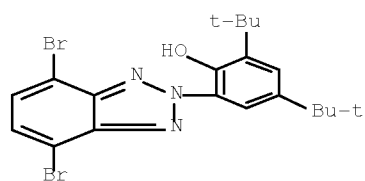
CM 1

CRN 849691-48-1
CMF C22 H36 B2 O6



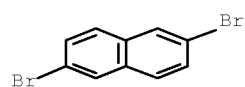
CM 2

CRN 784163-33-3
CMF C20 H23 Br2 N3 O



CM 3

CRN 13720-06-4
CMF C10 H6 Br2

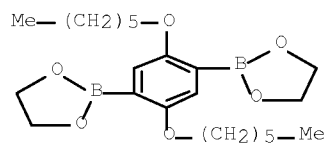


RN 883741-34-2 HCAPLUS
CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with
2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and
4-bromo-N-(4-bromophenyl)-N-phenylbenzenamine (9CI) (CA INDEX
NAME)

CM 1

CRN 849691-48-1
CMF C22 H36 B2 O6

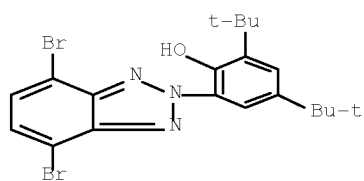
10/553,775-294324-EIC SEARCH



CM 2

CRN 784163-33-3

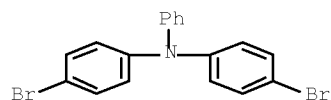
CMF C20 H23 Br2 N3 O



CM 3

CRN 81090-53-1

CMF C18 H13 Br2 N



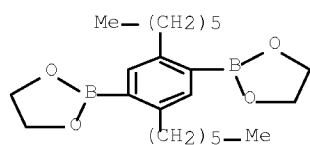
RN 883741-35-3 HCAPLUS

CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 4-bromo-N-(4-bromophenyl)-N-phenylbenzenamine and 2,2'-(2,5-dihexyl-1,4-phenylene)bis[1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

CM 1

CRN 883741-17-1

CMF C22 H36 B2 O4

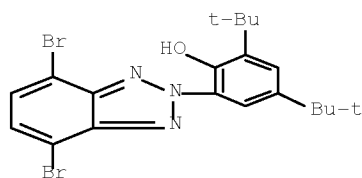


10/553,775-294324-EIC SEARCH

CM 2

CRN 784163-33-3

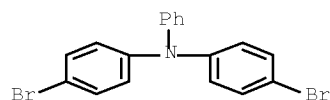
CMF C20 H23 Br2 N3 O



CM 3

CRN 81090-53-1

CMF C18 H13 Br2 N



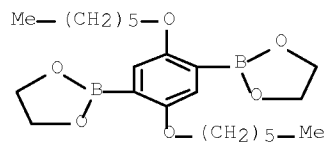
RN 883741-36-4 HCAPLUS

CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with
2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and
3,6-dibromo-9-phenyl-9H-carbazole (9CI) (CA INDEX NAME)

CM 1

CRN 849691-48-1

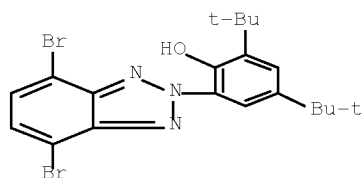
CMF C22 H36 B2 O6



CM 2

CRN 784163-33-3

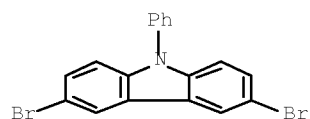
CMF C20 H23 Br2 N3 O



CM 3

CRN 57103-20-5

CMF C18 H11 Br2 N



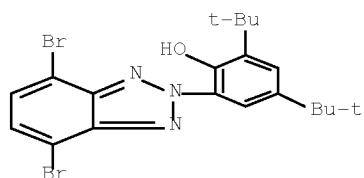
RN 883741-37-5 HCAPLUS

CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with
2,2'-(9,9-dioctyl-9H-fluorene-2,7-diyl)bis[4,4,5,5-tetramethyl-1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

CM 1

CRN 784163-33-3

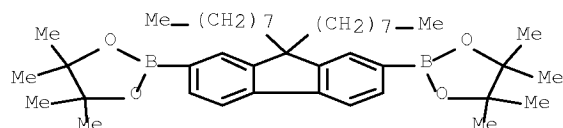
CMF C20 H23 Br2 N3 O



CM 2

CRN 196207-58-6

CMF C41 H64 B2 O4

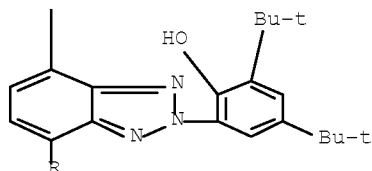
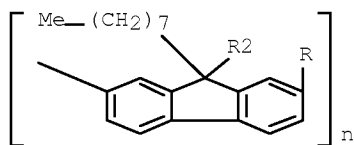


RN 883741-38-6 HCAPLUS

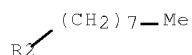
10/553,775-294324-EIC SEARCH

CN Poly[[2-[3,5-bis(1,1-dimethylethyl)-2-hydroxyphenyl]-2H-benzotriazole-4,7-diyl](9,9-dioctyl-9H-fluorene-2,7-diyl)] (9CI)
(CA INDEX NAME)

PAGE 1-A



PAGE 2-A

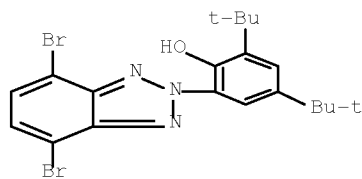


RN 883741-39-7 HCAPLUS
CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 2,7-dibromo-9,9-dioctyl-9H-fluorene and 2,2'-(9,9-dioctyl-9H-fluorene-2,7-diyl)bis[4,4,5,5-tetramethyl-1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

CM 1

CRN 784163-33-3

CMF C20 H23 Br2 N3 O

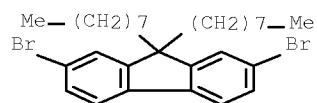


CM 2

CRN 198964-46-4

CMF C29 H40 Br2

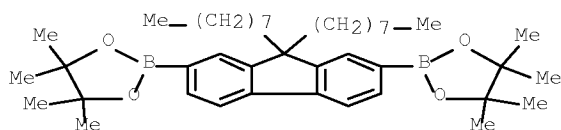
10/553,775-294324-EIC SEARCH



CM 3

CRN 196207-58-6

CMF C41 H64 B2 O4



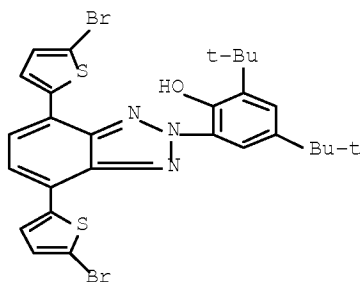
RN 883741-40-0 HCAPLUS

CN Phenol, 2-[4,7-bis(5-bromo-2-thienyl)-2H-benzotriazol-2-yl]-4,6-bis(1,1-dimethylethyl)-, polymer with 2,5-bis(4-bromophenyl)-1,3,4-oxadiazole, 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and 4-bromo-N-(4-bromophenyl)-N-phenylbenzenamine (9CI) (CA INDEX NAME)

CM 1

CRN 883741-19-3

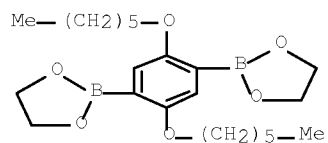
CMF C28 H27 Br2 N3 O S2



CM 2

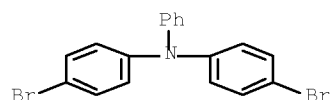
CRN 849691-48-1

CMF C22 H36 B2 O6



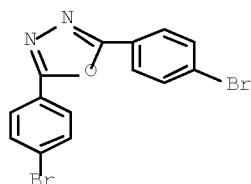
CM 3

CRN 81090-53-1
 CMF C18 H13 Br2 N



CM 4

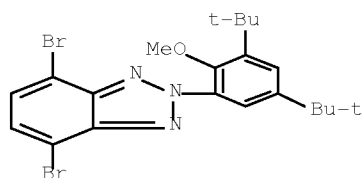
CRN 19542-05-3
 CMF C14 H8 Br2 N2 O



RN 883741-41-1 HCAPLUS
 CN 2H-Benzotriazole, 2-[3,5-bis(1,1-dimethylethyl)-2-methoxyphenyl]-
 4,7-dibromo-, polymer with
 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and
 1,4-dibromo-2,5-bis(hexyloxy)benzene (9CI) (CA INDEX NAME)

CM 1

CRN 883741-16-0
 CMF C21 H25 Br2 N3 O

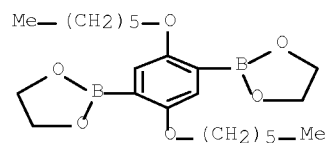


10/553,775-294324-EIC SEARCH

CM 2

CRN 849691-48-1

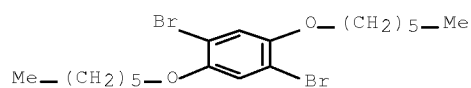
CMF C22 H36 B2 O6



CM 3

CRN 128424-36-2

CMF C18 H28 Br2 O2



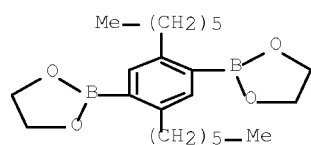
RN 883741-42-2 HCAPLUS

CN 2H-Benzotriazole, 2-[3,5-bis(1,1-dimethylethyl)-2-methoxyphenyl]-4,7-dibromo-, polymer with 1,4-dibromo-2,5-dihexylbenzene and (2,5-dihexyl-1,4-phenylene)-1,3,2-dioxaborolane (9CI) (CA INDEX NAME)

CM 1

CRN 883741-17-1

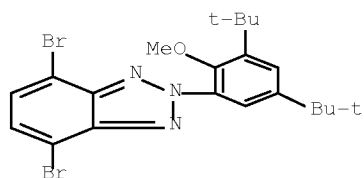
CMF C22 H36 B2 O4



CM 2

CRN 883741-16-0

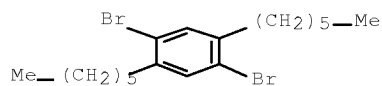
CMF C21 H25 Br2 N3 O



CM 3

CRN 117635-21-9

CMF C18 H28 Br2



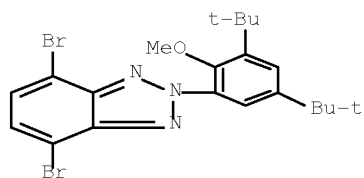
RN 883741-43-3 HCAPLUS

CN Benzenamine, 4-bromo-N-(4-bromophenyl)-N-phenyl-, polymer with
 2-[3,5-bis(1,1-dimethylethyl)-2-methoxyphenyl]-4,7-dibromo-2H-
 benzotriazole and 2,2'-(9,9-dioctyl-9H-fluorene-2,7-
 diyl)bis[4,4,5,5-tetramethyl-1,3,2-dioxaborolane] (9CI) (CA INDEX
 NAME)

CM 1

CRN 883741-16-0

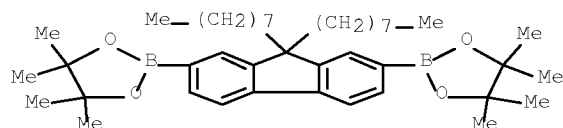
CMF C21 H25 Br2 N3 O



CM 2

CRN 196207-58-6

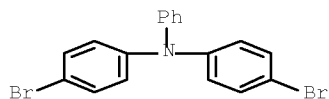
CMF C41 H64 B2 O4



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CM 3

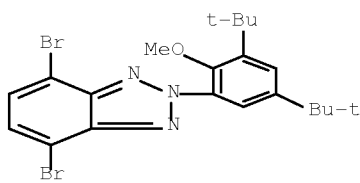
CRN 81090-53-1
CMF C18 H13 Br2 N



RN 883741-44-4 HCAPLUS
CN 2H-Benzotriazole, 2-[3,5-bis(1,1-dimethylethyl)-2-methoxyphenyl]-4,7-dibromo-, polymer with 2,7-dibromo-9,9-dioctyl-9H-fluorene and 2,2'-(9,9-dioctyl-9H-fluorene-2,7-diyl)bis[4,4,5,5-tetramethyl-1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

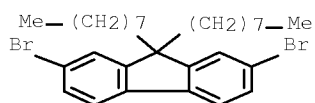
CM 1

CRN 883741-16-0
CMF C21 H25 Br2 N3 O



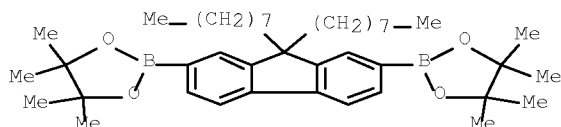
CM 2

CRN 198964-46-4
CMF C29 H40 Br2



CM 3

CRN 196207-58-6
CMF C41 H64 B2 O4



CC 37-3 (Plastics Manufacture and Processing)
 Section cross-reference(s): 35, 74

ST benzotriazole luminescent monomer oligomer polymer
 electroluminescent device

IT Electroluminescent devices
 luminescent substances
 Sensors
 (production of high quantum yield luminescent monomers,
 oligomers and polymers for electroluminescent
 devices)

IT 883741-48-8P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered
 material use); PREP (Preparation); USES (Uses)
 (chemical sensor; production of high quantum yield luminescent
 monomers, oligomers and polymers for electroluminescent
 devices)

IT 9003-53-6D, sulfonated
 RL: DEV (Device component use); USES (Uses)
 (dopant for PEDOT; production of high quantum yield
 luminescent monomers, oligomers and polymers for
 electroluminescent devices)

IT 126213-51-2
 RL: DEV (Device component use); USES (Uses)
 (doped with PSS; production of high quantum yield
 luminescent monomers, oligomers and polymers for
 electroluminescent devices)

IT 2835-58-7P, 2-Phenylazoaniline 69272-50-0P,
 3,6-Dibromo-1,2-phenylenediamine 883741-18-2P,
 2,4-Di-tert-butyl-6-(4,7-di(thiophen-2-yl)-2H-benzotriazol-2-
 yl)phenol
 RL: IMF (Industrial manufacture); RCT (Reactant); PREP
 (Preparation); RACT (Reactant or reagent)
 (intermediate; production of high quantum yield luminescent
 monomers, oligomers and polymers for electroluminescent
 devices)

IT 1916-72-9P, 2-Phenyl-2H-benzotriazole
 RL: IMF (Industrial manufacture); TEM (Technical or engineered
 material use); PREP (Preparation); USES (Uses)
 (intermediate; production of high quantum yield luminescent
 monomers, oligomers and polymers for electroluminescent
 devices)

IT 57103-20-5P, 3,6-Dibromo-9-phenylcarbazole 81090-53-1P,
 4,4'-Dibromotriphenylamine 128424-36-2P,
 2,5-Dihexyloxy-1,4-dibromobenzene 784163-33-3P,
 2,4-Di-tert-butyl-6-(4,7-dibromo-2H-benzo[d][1,2,3]triazol-2-
 yl)phenol 849691-48-1P 851106-87-1P 883741-16-0P,
 2-(3,5-Di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole
 883741-17-1P 883741-19-3P,
 2-(4,7-Bis(5-bromothiophen-2-yl)-2H-benzotriazol-2-yl)-4,6-di-tert-
 butylphenol 883741-55-7P,
 2-(3,5-Di-tert-butyl-2-methoxyphenyl)-4,6-dibromo-2H-benzotriazole
 883741-56-8P, 2-(3,5-Di-tert-butyl-2-methoxyphenyl)-5,6-dibromo-2H-
 benzotriazole
 RL: IMF (Industrial manufacture); RCT (Reactant); PREP
 (Preparation); RACT (Reactant or reagent)
 (monomer; production of high quantum yield luminescent
 monomers, oligomers and polymers for electroluminescent
 devices)

IT 883741-51-3, 4,6-Dibromo-2-hexyl-2H-benzotriazole 883741-52-4,
 5,6-Dibromo-2-hexyl-2H-benzotriazole 883741-53-5,
 2,4-Di-tert-butyl-6-(4,6-dibromo-2H-benzo[d][1,2,3]triazol-2-
 yl)phenol 883741-54-6, 2,4-Di-tert-butyl-6-(5,6-dibromo-2H-
 benzo[d][1,2,3]triazol-2-yl)phenol
 RL: RCT (Reactant); RACT (Reactant or reagent)

10/553,775-294324-EIC SEARCH

(monomer; production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)

IT 1044764-63-7, Baytron P

RL: DEV (Device component use); USES (Uses)

(production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)

IT 883741-20-6P, 1,4-Dibromo-2,5-bis(hexyloxy)benzene-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-31-7P, 2,5-Bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-32-8P, 2,5-Bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer, SRU 883741-33-9P, 2,5-Di(hexyloxy)-1,4-dibromobenzene-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole copolymer 883741-28-4P, 2-(4,7-Bis(chloromethyl)-2H-benzotriazol-2-yl)-4,6-di-tert-butylphenol-1,4-bis(chloromethyl)-2,5-dimethoxybenzene copolymer 883741-29-5P, 1,4-Dibromo-2,5-di(hexyl)benzene-2,5-di(hexy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-30-8P, 1,4-Dibromo-2,5-bis(hexyloxy)benzene-2,5-di(hexy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-31-9P, 2,5-Bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-1,4-dibromo-2,5-bis(hexyloxy)benzene-2,5-di(hexyl)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-32-0P, 2,5-Bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-1,4-dibromo-2,5-di(hexyl)benzene-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-33-1P, 2,6-Dibromonaphthalene-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-34-2P, 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-35-3P, 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-di(hexyl)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-36-4P, 3,6-Dibromo-9-phenyl-9H-carbazole-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-37-5P, 2,4-Di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer 883741-38-6P, 2,4-Di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer, SRU 883741-39-7P, 2,7-Dibromo-9,9-dioctyl-9H-fluorene-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer 883741-40-0P, 2,5-Bis(4-bromophenyl)-1,3,4-oxadiazole-2-(4,7-bis(5-bromothiophen-2-yl)-2H-benzo[d][1,2,3]triazol-2-yl)-4,6-di-tert-butylphenol-4-bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-bis(hexyloxy)-1,4-

10/553,775-294324-EIC SEARCH

benzenebisboronic ethylene glycol ester copolymer
 883741-41-1P, 1,4-Dibromo-2,5-bis(hexyloxy)benzene-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzo[d][1,2,3]triazole copolymer 883741-42-2P,
 1,4-Dibromo-2,5-dihexylbenzene-2,5-dihexyl-1,4-benzenebisboronic ethylene glycol ester-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzo[d][1,2,3]triazole copolymer 883741-43-3P,
 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluorene-7-yl)-1,3,2-dioxaborolane copolymer 883741-44-4P,
 2,7-Dibromo-9,9-dioctyl-9H-fluorene-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluorene-7-yl)-1,3,2-dioxaborolane copolymer 883741-45-5P,
 1,4-Dibromo-2,5-bis(hexyloxy)benzene-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-4,7-dibromo-2-hexyl-2H-benzotriazole copolymer 883741-46-6P,
 1,4-Dibromo-2,5-bis(hexyloxy)benzene-2,5-dihexyl-1,4-benzenebisboronic ethylene glycol ester-4,7-dibromo-2-hexyl-2H-benzotriazole copolymer 883741-47-7P,
 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-bis(hexyloxy)-1,4-benzenebisboronic ethylene glycol ester-4,7-dibromo-2-hexyl-2H-benzotriazole copolymer
 RL: DEV (Device component use); IMF (Industrial manufacture); PRP (Properties); PREP (Preparation); USES (Uses)
 (production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)

IT 16292-17-4P, 4,4'-Dibromodiphenylamine 67399-93-3P,
 1,4-Dihexyloxybenzene 171089-85-3P 883741-24-0P,
 2-(4,7-Bis(4-(dimethylamino)phenyl)-2H-benzotriazol-2-yl)-4,6-di-tert-butylphenol 883741-25-1P 883741-27-3P,
 2-(4,7-Bis(chloromethyl)-2H-benzotriazol-2-yl)-4,6-di-tert-butylphenol 883741-49-9P 883741-50-2P
 RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
 (production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)

IT 74-88-4, reactions 95-14-7, 1H-Benzotriazole 95-54-5,
 1,2-Phenylenediamine, reactions 98-80-6, Phenylboronic acid 98-95-3, Nitrobenzene, reactions 107-21-1, Ethylene glycol, reactions 111-25-1, 1-Bromohexane 121-43-7, Trimethyl borate 122-39-4, reactions 123-31-9, p-Hydroquinone, reactions 128-08-5, N-Bromosuccinimide 542-88-1, Bis(chloromethyl)ether 591-50-4, Iodobenzene 814-49-3, Diethyl phosphochloridate 1150-62-5, 9-Phenylcarbazole 2440-22-4, Tinuvin P 3240-34-4, Iodobenzene diacetate 3846-71-7 7726-95-6, Bromine, reactions 10035-10-6, Hydrogenbromide, reactions 15155-41-6,
 4,7-Dibromobenzo[1,2,5]thiadiazole 28611-39-4,
 4-(Dimethylamino)phenylboronic acid 54663-78-4,
 Tributyl(thiophen-2-yl)stannate 131117-66-3,
 2,5-Dihexyl-1,4-benzenediboronic acid
 RL: RCT (Reactant); RACT (Reactant or reagent)
 (production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)

REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L31 ANSWER 2 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2006:50852 HCAPLUS Full-text
 DOCUMENT NUMBER: 144:138888
 TITLE: Manufacture of aromatic polycarbonates as

10/553,775-294324-EIC SEARCH

binders for electrophotographic photoconductors showing good abrasion resistance and low surface energy

INVENTOR(S): Li, Hung Guo; Nagai, Kazukiyo; Okuda, Harukazu; Hatanaka, Masahide

PATENT ASSIGNEE(S): Ricoh Co., Ltd., Japan; Nisshin Chemical Industry Co., Ltd.

SOURCE: Jpn. Kokai Tokkyo Koho, 35 pp.
CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
JP 2006016566	A	20060119	JP 2004-197925	2004 0705

PRIORITY APPLN. INFO.: <-- JP 2004-197925

2004
0705

ED Entered STN: 19 Jan 2006

AB The polycarbonates are manufactured by solution polymerization of HOXOH (X = bivalent aliphatic group, bivalent alicyclic group, bivalent aromatic group, etc.) with OH-containing acrylic polyorganosiloxanes and carbonyl halides. Preferably, the polyorganosiloxanes are manufactured by grafting acrylic monomers containing 3-(N-benzotriazole)-4-hydroxyphenethyl methacrylate onto silicones. Electrophotog. process and apparatus, and process cartridges are also claimed.

IT 873545-93-88

RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)

(manufacture of aromatic polycarbonates as binders for electrophotog. photoconductors showing good abrasion resistance and low surface energy by solution polymerization of dihydroxy compds. with OH-containing acrylic polyorganosiloxanes and carbonyl halides)

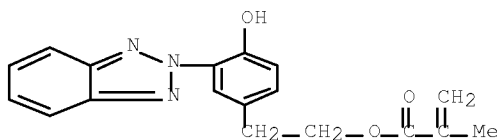
RN 873545-93-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with 4,4'-cyclohexylidenebis[phenol], ethenyldimethoxymethylsilane, 1,1,1,3,3,3-hexachloro-2-propanone, methyl 2-methyl-2-propenoate, octamethylcyclotetrasiloxane and (2,4,6-trioxo-1,3,5-triazine-1,3,5(2H,4H,6H)-triyl)tri-2,1-ethanediyl tri-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 96478-09-0

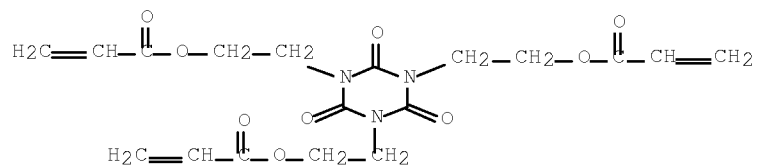
CMF C18 H17 N3 O3



CM 2

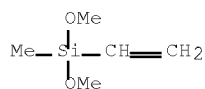
10/553,775-294324-EIC SEARCH

CRN 40220-08-4
CMF C18 H21 N3 O9



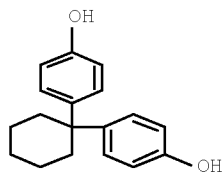
CM 3

CRN 16753-62-1
CMF C5 H12 O2 Si



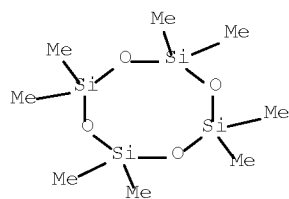
CM 4

CRN 843-55-0
CMF C18 H20 O2



CM 5

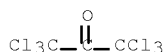
CRN 556-67-2
CMF C8 H24 O4 Si4



CM 6

CRN 116-16-5

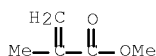
CMF C3 Cl6 O



CM 7

CRN 80-62-6

CMF C5 H8 O2



- CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38
- ST acrylic polysiloxane arom polycarbonate ~~electrophotog~~
~~photoconductor~~ abrasion resistance; benzotriazole
hydroxyphenethyl methacrylate polysiloxane polycarbonate
~~electrophotog photoconductor~~; soln polymn graft
acrylic polysiloxane carbonyl halide
- IT Abrasion-resistant materials
Electrophotographic photoconductors
(photoreceptors)
(manufacture of aromatic polycarbonates as binders for
~~electrophotog. photoconductors~~ showing good
abrasion resistance and low surface energy by solution polymerization of
dihydroxy compds. with OH-containing acrylic polyorganosiloxanes
and carbonyl halides)
- IT Polysiloxanes, preparation
RL: DEV (Device component use); IMF (Industrial manufacture); PREP
(Preparation); USES (Uses)
(polycarbonate-polyisocyanurate-, acrylic; manufacture of aromatic
polycarbonates as binders for ~~electrophotog.~~
~~photoconductors~~ showing good abrasion resistance and
low surface energy)
- IT Polyisocyanurates
RL: DEV (Device component use); IMF (Industrial manufacture); PREP
(Preparation); USES (Uses)
(polycarbonate-polysiloxane-, acrylic; manufacture of aromatic
polycarbonates as binders for ~~electrophotog.~~
~~photoconductors~~ showing good abrasion resistance and
low surface energy)
- IT Polycarbonates, preparation
RL: DEV (Device component use); IMF (Industrial manufacture); PREP
(Preparation); USES (Uses)
(polyisocyanurate-polysiloxane-, acrylic; manufacture of aromatic
polycarbonates as binders for ~~electrophotog.~~
~~photoconductors~~ showing good abrasion resistance and
low surface energy)
- IT Polymerization
(solution; manufacture of aromatic polycarbonates as binders for
~~electrophotog. photoconductors~~ showing good

10/553,775-294324-EIC SEARCH

abrasion resistance and low surface energy by solution polymerization of dihydroxy compds. with OH-containing acrylic polyorganosiloxanes and carbonyl halides)

IT 873545-93-88

RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)

(manufacture of aromatic polycarbonates as binders for electrophotog. photoconductors showing good abrasion resistance and low surface energy by solution polymerization of dihydroxy compds. with OH-containing acrylic polyorganosiloxanes and carbonyl halides)

IT 110-86-1, Pyridine, reactions

RL: RGT (Reagent); RACT (Reactant or reagent)

(manufacture of aromatic polycarbonates as binders for electrophotog. photoconductors showing good abrasion resistance and low surface energy by solution polymerization of dihydroxy compds. with OH-containing acrylic polyorganosiloxanes and carbonyl halides)

L31 ANSWER 3 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2005:1176034 HCAPLUS Full-text

DOCUMENT NUMBER: 143:442130

TITLE: Anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment

INVENTOR(S): Aoki, Kenji; Fujita, Mitsuhiro; Hiraki, Tadayoshi

PATENT ASSIGNEE(S): Kansai Paint Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 15 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2005307161	A	20051104	JP 2004-359536	2004 1213
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CN 1673295	A	20050928	CN 2005-10053994	2005 0315
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PRIORITY APPLN. INFO.:			JP 2004-82735	A	2004 0322
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			JP 2004-359536	A	2004 1213
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ED Entered STN: 06 Nov 2005

AB Title coatings comprise (A) core-shell emulsion obtained by multi-step emulsion polymerization of polymerizable unsatd. monomers in the presence of water and emulsifiers, (B) acrylic resins, and (C) crosslinkers, wherein the core-shell emulsion contain 1-40% alkoxysilyl-containing monomer units and is prepared by (i) first radical emulsion polymerization of alkoxysilyl-containing radically polymerizable monomers, ≥ 1 radically polymerizable unsatd. monomer selected from UV-absorbing component-containing monomers, light stabilizing component-containing monomers, and fluoro-containing monomers, copolymerizable monomers, and optionally monomers having ≥ 2 radically polymerizable groups, and second emulsion polymerization of alkoxysilyl-containing radically polymerizable monomers, copolymerizable monomers, and optionally monomers having ≥ 2 radically polymerizable groups. Thus, Adeka Reasoap SE 10N 1, styrene 20, Bu

10/553,775-294324-EIC SEARCH

acrylate 17, 2-hydroxyethyl acrylate 2, 1,6-hexanediol diacrylate 5, KBM 503 4, and Ruva 93 2 parts were emulsion-polymerized, Adeka Reasoap SE 10N 1, styrene 15, Bu acrylate 13, 2-hydroxyethyl acrylate 4, 1,6-hexanediol diacrylate 3, and KBM 503 15 parts were added therein and polymerized to give 20%-solids core-shell copolymer with particle diameter 127 nm, 15 parts of which was mixed with 45 parts 60%-solids styrene-Me methacrylate-Bu acrylate-Et acrylate-2-hydroxyethyl acrylate-acrylic acid copolymer solution, 40 parts Nikalac MX 430, 0.4 equiv (based on OH group) triethylamine, and water, adjusted pH at 8.2 and solid content 10% to give an anionic ~~electrodeposition~~ coating, showing good stability, weather resistance, and dice mark concealment, pencil hardness (crosslinked) 4 H, and 60° gloss 16.

IT 868663-68-7P 868663-72-3P 868681-86-1P
 RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)

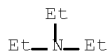
RN 868663-68-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate, formaldehyde, 1,6-hexanediyl di-2-propenoate, 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate, 2-propenoic acid, α -sulfo- ω -[1-[(nonylphenoxy)methyl]-2-(2-propenyloxy)ethoxy]poly(oxy-1,2-ethanediyl) ammonium salt, 1,3,5-triazine-2,4,6-triamine and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate, compd. with N,N-diethylethanamine (9CI)
 (CA INDEX NAME)

CM 1

CRN 121-44-8

CMF C6 H15 N



CM 2

CRN 868663-67-6

CMF (C18 H17 N3 O3 . C12 H18 O4 . C10 H20 O5 Si . C8 H8 . C7 H12 O2 . C5 H8 O3 . C5 H8 O2 . C5 H8 O2 . C3 H6 N6 . C3 H4 O2 . (C2 H4 O)n C21 H34 O6 S . C H2 O . H3 N)x

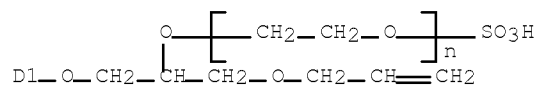
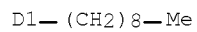
CCI PMS

CM 3

CRN 113405-85-9

CMF (C2 H4 O)n C21 H34 O6 S . H3 N

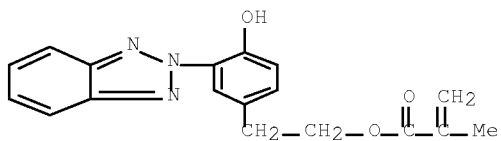
CCI IDS, PMS



CM 4

CRN 96478-09-0

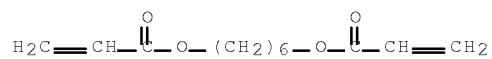
CMF C18 H17 N3 O3



CM 5

CRN 13048-33-4

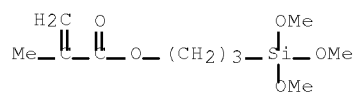
CMF C12 H18 O4



CM 6

CRN 2530-85-0

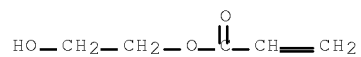
CMF C10 H20 O5 Si



CM 7

CRN 818-61-1

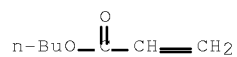
CMF C5 H8 O3



CM 8

CRN 141-32-2

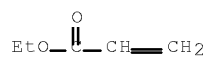
CMF C7 H12 O2



CM 9

CRN 140-88-5

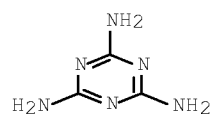
CMF C5 H8 O2



CM 10

CRN 108-78-1

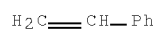
CMF C3 H6 N6



CM 11

CRN 100-42-5

CMF C8 H8



CM 12

CRN 80-62-6

10/553,775-294324-EIC SEARCH

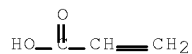
CMF C5 H8 O2



CM 13

CRN 79-10-7

CMF C3 H4 O2



CM 14

CRN 50-00-0

CMF C H2 O



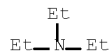
RN 868663-72-3 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
 with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
 formaldehyde, 1,6-hexanediyl di-2-propenoate, 2-hydroxyethyl
 2-propenoate, methyl 2-methyl-2-propenoate,
 1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate,
 2-propenoic acid, α -sulfo- ω -[1-[(nonylphenoxy)methyl]-
 2-(2-propenyloxy)ethoxy]poly(oxy-1,2-ethanediyl) ammonium salt,
 1,3,5-triazine-2,4,6-triamine and 3-(trimethoxysilyl)propyl
 2-methyl-2-propenoate, compd. with N,N-diethylethanamine (9CI)
 (CA INDEX NAME)

CM 1

CRN 121-44-8

CMF C6 H15 N



CM 2

CRN 868663-71-2

CMF (C18 H17 N3 O3 . C14 H25 N O2 . C12 H18 O4 . C10 H20 O5 Si .
 C8 H8 . C7 H12 O2 . C5 H8 O3 . C5 H8 O2 . C5 H8 O2 . C3 H6 N6

10/553,775-294324-EIC SEARCH

. C3 H4 O2 . (C2 H4 O)n C21 H34 O6 S . C H2 O . H3 N)x
CCI PMS

CM 3

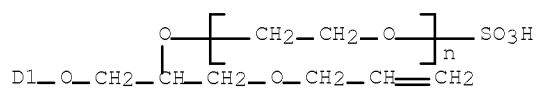
CRN 113405-85-9

CMF (C2 H4 O)n C21 H34 O6 S . H3 N

CCI IDS, PMS



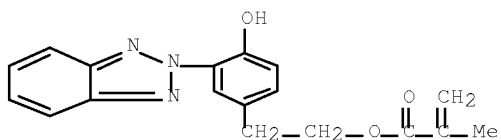
D1-(CH₂)₈-Me



CM 4

CRN 96478-09-0

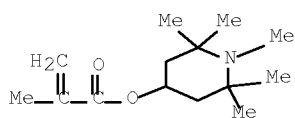
CMF C18 H17 N3 O3



CM 5

CRN 68548-08-3

CMF C14 H25 N O2

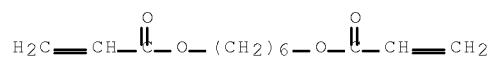


CM 6

CRN 13048-33-4

CMF C12 H18 O4

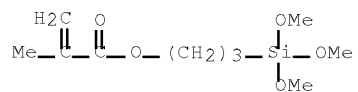
10/553,775-294324-EIC SEARCH



CM 7

CRN 2530-85-0

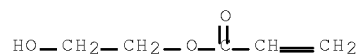
CMF C10 H20 O5 Si



CM 8

CRN 818-61-1

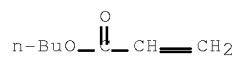
CMF C5 H8 O3



CM 9

CRN 141-32-2

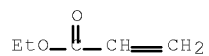
CMF C7 H12 O2



CM 10

CRN 140-88-5

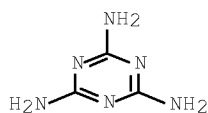
CMF C5 H8 O2



CM 11

CRN 108-78-1

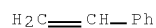
CMF C3 H6 N6



CM 12

CRN 100-42-5

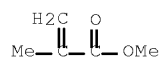
CMF C8 H8



CM 13

CRN 80-62-6

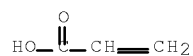
CMF C5 H8 O2



CM 14

CRN 79-10-7

CMF C3 H4 O2



CM 15

CRN 50-00-0

CMF C H2 O



RN 868681-86-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
 with butyl 2-propenoate, Duranate TPA-B 80, ethenylbenzene, ethyl
 2-propenoate, formaldehyde, 1,6-hexanediyl di-2-propenoate,
 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,

10/553,775-294324-EIC SEARCH

2-propenoic acid, α -sulfo- ω -[1-[(nonylphenoxy)methyl]-
2-(2-propenyloxy)ethoxy]poly(oxy-1,2-ethanediyl) ammonium salt,
1,3,5-triazine-2,4,6-triamine and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate, compd. with N,N-diethylethanamine (9CI)
(CA INDEX NAME)

CM 1

CRN 121-44-8

CMF C6 H15 N



CM 2

CRN 868681-85-0

CMF (C18 H17 N3 O3 . C12 H18 O4 . C10 H20 O5 Si . C8 H8 . C7 H12
O2 . C5 H8 O3 . C5 H8 O2 . C5 H8 O2 . C3 H6 N6 . C3 H4 O2 .
(C2 H4 O)n C21 H34 O6 S . C H2 O . H3 N . Unspecified)x

CCI PMS

CM 3

CRN 178359-56-3

CMF Unspecified

CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 4

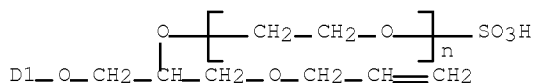
CRN 113405-85-9

CMF (C2 H4 O)n C21 H34 O6 S . H3 N

CCI IDS, PMS



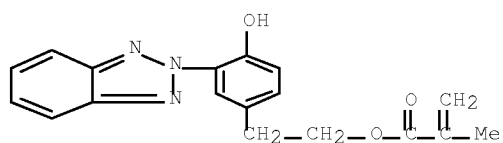
D1—(CH₂)₈—Me



CM 5

CRN 96478-09-0

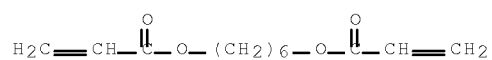
CMF C18 H17 N3 O3



CM 6

CRN 13048-33-4

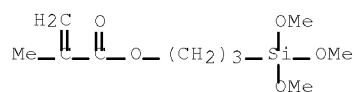
CMF C12 H18 O4



CM 7

CRN 2530-85-0

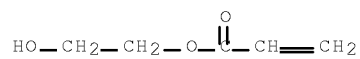
CMF C10 H20 O5 Si



CM 8

CRN 818-61-1

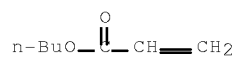
CMF C5 H8 O3



CM 9

CRN 141-32-2

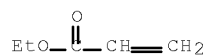
CMF C7 H12 O2



CM 10

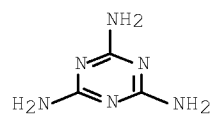
10/553,775-294324-EIC SEARCH

CRN 140-88-5
CMF C5 H8 O2



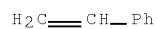
CM 11

CRN 108-78-1
CMF C3 H6 N6



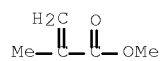
CM 12

CRN 100-42-5
CMF C8 H8



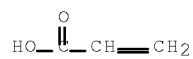
CM 13

CRN 80-62-6
CMF C5 H8 O2



CM 14

CRN 79-10-7
CMF C3 H4 O2



CM 15

10/553,775-294324-EIC SEARCH

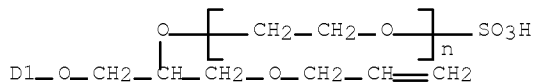
CRN 50-00-0
CMF C H2 O



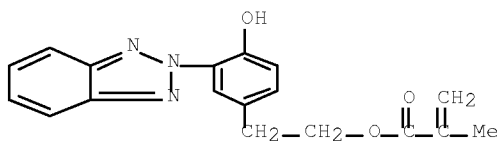
IT 868663-64-3P 868663-65-4P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(core-shell, prepolymer; anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)
RN 868663-64-3 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, 1,6-hexanediyl di-2-propenoate, 2-hydroxyethyl 2-propenoate,
 α -sulfo- ω -[1-[(nonylphenoxy)methyl]-2-(2-propenyloxy)ethoxy][poly(oxy-1,2-ethanediyl)] ammonium salt and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)
CM 1
CRN 113405-85-9
CMF (C2 H4 O)_n C21 H34 O6 S . H3 N
CCI IDS, PMS



D1-(CH₂)₈-Me



CM 2
CRN 96478-09-0
CMF C18 H17 N3 O3

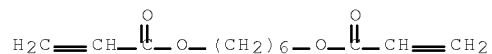


10/553,775-294324-EIC SEARCH

CM 3

CRN 13048-33-4

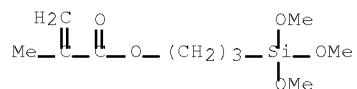
CMF C12 H18 O4



CM 4

CRN 2530-85-0

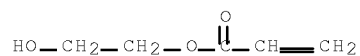
CMF C10 H20 O5 Si



CM 5

CRN 818-61-1

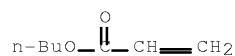
CMF C5 H8 O3



CM 6

CRN 141-32-2

CMF C7 H12 O2



RN 868663-65-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
 with butyl 2-propenoate, 1,6-hexanediyl di-2-propenoate,
 2-hydroxyethyl 2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyll
 2-methyl-2-propenoate, α -sulfo- ω -[1-
 [(nonylphenoxy)methyl]-2-(2-propenyloxy)ethoxy] [poly(oxy-1,2-
 ethanediyl)] ammonium salt and 3-(trimethoxysilyl)propyl
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

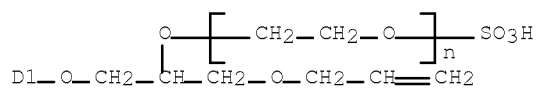
CM 1

10/553,775-294324-EIC SEARCH

CRN 113405-85-9
 CMF (C2 H4 O)_n C21 H34 O6 S . H3 N
 CCI IDS, PMS

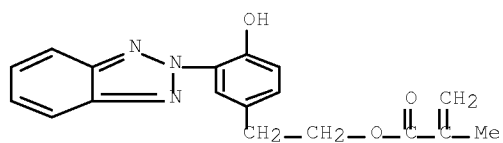


D1—(CH₂)₈—Me



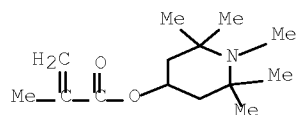
CM 2

CRN 96478-09-0
 CMF C18 H17 N3 O3



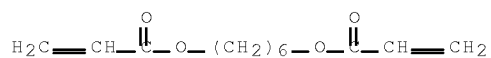
CM 3

CRN 68548-08-3
 CMF C14 H25 N O2



CM 4

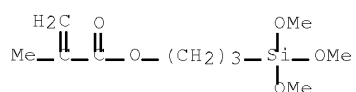
CRN 13048-33-4
 CMF C12 H18 O4



CM 5

CRN 2530-85-0

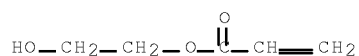
CMF C10 H20 O5 Si



CM 6

CRN 818-61-1

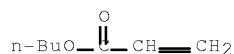
CMF C5 H8 O3



CM 7

CRN 141-32-2

CMF C7 H12 O2



IC ICM C09D151-00

ICS C08F275-00; C09D005-02; C09D005-32; C09D005-44; C09D133-00

CC 42-10 (Coatings, Inks, and Related Products)

ST anionic ~~electrodeposition~~ coating weather resistance
stability dice mark concealment; hydroxy contg acrylic
polyoxyalkylene core shell Nikalac copolymer coating

IT Polyoxyalkylenes, preparation

RL: IMF (Industrial manufacture); RCT (Reactant); PREP
(Preparation); RACT (Reactant or reagent)(acrylic, core-shell, prepolymer; anionic
~~electrodeposition~~ coatings with good weather
resistance, stability, and dice mark concealment)

IT Polyoxyalkylenes, preparation

RL: IMF (Industrial manufacture); RCT (Reactant); PREP
(Preparation); RACT (Reactant or reagent)(acrylic, fluorine-containing, core-shell, prepolymer; anionic
~~electrodeposition~~ coatings with good weather
resistance, stability, and dice mark concealment)

IT Aminoplasts

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical
or engineered material use); PREP (Preparation); USES (Uses)(acrylic, polyoxyalkylene-; anionic ~~electrodeposition~~
coatings with good weather resistance, stability, and dice mark
concealment)

10/553,775-294324-EIC SEARCH

- IT Polyoxyalkylenes, uses
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylic-aminoplast-, fluorine-containing; anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)
- IT Fluoropolymers, uses
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylic-aminoplast-polyoxyalkylene-; anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)
- IT Fluoropolymers, preparation
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(acrylic-polyoxyalkylene-, core-shell, prepolymer; anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)
- IT Aminoplasts
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylic-polyoxyalkylene-, fluorine-containing; anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)
- IT Coating materials
(~~electrodeposition~~; anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)
- IT Coating materials
(weather-resistant; anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)
- IT 868663-68-7P 868663-72-3P 868663-77-8P
868681-86-1P
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)
- IT 868663-70-1P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)
- IT 868663-64-3P 868663-65-4P 868663-66-5P
868681-84-9P, Adeka Reasoap SE 10N-butyl acrylate-Fancryl FA 711MM-1,6-hexanediol diacrylate-2-hydroxyethyl acrylate-KBM 503 copolymer
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(core-shell, prepolymer; anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)
- IT 105524-01-4P, Acrylic acid-butyl acrylate-ethyl acrylate-2-hydroxyethyl acrylate-methyl methacrylate-styrene copolymer triethylamine salt
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(prepolymer; anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)
- IT 7429-90-5D, Aluminum, oxidized
RL: TEM (Technical or engineered material use); USES (Uses)
(substrate; anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)

L31 ANSWER 4 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2004:1059254 HCAPLUS Full-text
DOCUMENT NUMBER: 142:45858

10/553,775-294324-EIC SEARCH

TITLE: Electrophotographic
photoconductor and process for its
manufacturing
INVENTOR(S): Rogge, Peter R.; Weidert, Edward
PATENT ASSIGNEE(S): Circular Technologies, USA
SOURCE: PCT Int. Appl., 30 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2004106051	A1	20041209	WO 2003-US17629	2003 0527

WO 2004106051 A8 20060323
W: US
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR,
HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR

PRIORITY APPLN. INFO.: WO 2003-US17629
2003
0527

ED Entered STN: 10 Dec 2004

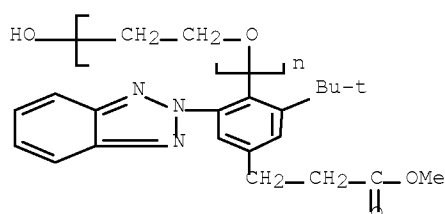
AB An electrophotog. photoconductor for use in electrophotog. applications is provided. The electrophotog. photoconductor is comprised of a monolithic elastic material layer comprised of at least a polyol, a polyisocyanate, and a hydroxyl-containing acrylate monomer, and addnl. optionally comprised of some combination of a conductive additive, an UV absorber, and a photoinitiator, that is deposited on an electroconductive substrate. The elastic material later is then exposed to UV light, thereby creating an elec. semi-conductive surface layer. An electrophotog. photoconductor prepared in this fashion has a hardness of 5-50 Shore A durometer, a surface resistivity of 10⁵-10¹² Ohms/cm² and a volume resistivity of 10⁴-10¹⁰ Ohms-cm.

IT 136457-10-8, Tinuvin 213

RL: TEM (Technical or engineered material use); USES (Uses)
(electrophotog. photoconductor and process
for its manufacturing)

RN 136457-10-8 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -[2-(2H-benzotriazol-2-yl)-6-(1,1-dimethylethyl)-4-(3-methoxy-3-oxopropyl)phenyl]- ω -hydroxy-
(CA INDEX NAME)



IC ICM B32B001-08

ICS B32B025-00; B32B031-28; C08F002-48; C08F002-50; C08J007-04;
G03G015-02

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and
Other Reprographic Processes)

ST electrophotog photoconductor manuf

10/553,775-294324-EIC SEARCH

IT Electrophotographic photoconductors (photoreceptors)
(electrophotog. photoconductor and process for its manufacturing)

IT 25736-86-1, Polyethylene glycol monomethacrylate
RL: TEM (Technical or engineered material use); USES (Uses)
(Sartomer CD 572; electrophotog. photoconductor and process for its manufacturing)

IT 50586-59-9, Curene 93
RL: TEM (Technical or engineered material use); USES (Uses)
(Voranol 234-630; electrophotog. photoconductor and process for its manufacturing)

IT 84593-42-0, Mondur CD 136457-10-8, Tinuvin 213
204019-31-8, Acclaim 6320 752252-67-8, SarCure SR 1129
752252-69-0, SarCure SR 1137
RL: TEM (Technical or engineered material use); USES (Uses)
(electrophotog. photoconductor and process for its manufacturing)

REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE
FOR THIS RECORD. ALL CITATIONS AVAILABLE
IN THE RE FORMAT

L31 ANSWER 5 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2004:996243 HCAPLUS Full-text
DOCUMENT NUMBER: 141:424846
TITLE: Benzotriazole unit-containing polymers for use
in optical devices
INVENTOR(S): Rogers, Jonathan; Craig, Michael Robert;
Schaefer, Thomas
PATENT ASSIGNEE(S): Ciba Specialty Chemicals Holding Inc., Switz.
SOURCE: PCT Int. Appl., 67 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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WO 2004099285	A2	20041118	WO 2004-EP50606	2004 0426

<--

WO 2004099285	A3	20051124		
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				
RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
EP 1620486	A2	20060201	EP 2004-741481	2004 0426

<--

CN 1784445	A	20060607	CN 2004-80012058	2004 0426
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR				

10/553,775-294324-EIC SEARCH

JP 2006526671 T 20061124 JP 2006-505574
2004
0426

US 20070043204 A1 20070222 US 2005-553775
2005
1020

PRIORITY APPLN. INFO.: EP 2003-405317 A
2003
0505

WO 2004-EP50606 W
2004
0426

ED Entered STN: 19 Nov 2004

AB The present invention relates to polymers comprising benzotriazole-containing repeating units. Optical devices such as electroluminescent or photovoltaic devices, made from the polymers of the present invention, can show significant advantages in color purity, device efficiency and/or operational lifetime. In addition, the polymers can have good solubility characteristics and relatively high glass transition temps., which facilitates their fabrication into coatings and films that are relatively thin, thermally stable, and relatively free of defects. Thus, stirring a solution of bis(1,5-cyclooctadiene)nickel 2.0 and 2,2'-bipyridyl 1.14 in PhMe (7.0 mL) at 80° for 1 h under Ar and darkness, adding 3-bromo-2-(3'-bromo-4'-methoxyphenyl)benzotriazole 0.23 and 2,7-dibromo-9,9-dihexylfluorene 1.50 g dissolved in PhMe (7 mL), purging with Ar, heating with a solution of a Ni complex at 80° for 17 h and working up gave a copolymer having benzotriazole repeating unit with Mw 650,000 and polydispersity 2.21.

IT 794518-77-7P 794518-81-3P 794518-84-6P
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(manufacture of benzotriazole unit-containing polymers for use in optical devices)

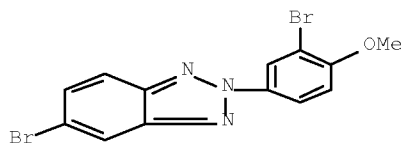
RN 794518-77-7 HCAPLUS

CN 2H-Benzotriazole, 5-bromo-2-(3-bromo-4-methoxyphenyl)-, polymer with 2,7-dibromo-9,9-dihexyl-9H-fluorene (9CI) (CA INDEX NAME)

CM 1

CRN 794518-76-6

CMF C13 H9 Br2 N3 O

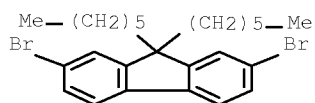


CM 2

CRN 189367-54-2

CMF C25 H32 Br2

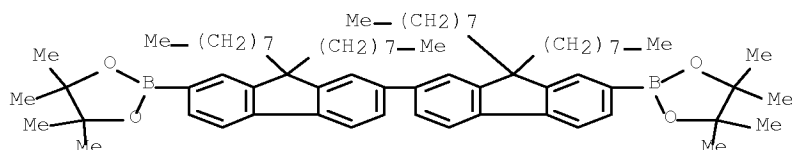
10/553,775-294324-EIC SEARCH



RN 794518-81-3 HCAPLUS
 CN 2H-Benzotriazole, 5-bromo-2-(6-bromo-2-methoxy-1-naphthalenyl)-, polymer with 2,2'-(9,9,9',9'-tetraoctyl[2,2'-bi-9H-fluorene]-7,7'-diyl)bis[4,4,5,5-tetramethyl-1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

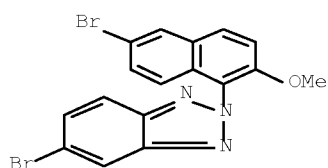
CM 1

CRN 794518-80-2
 CMF C70 H104 B2 O4



CM 2

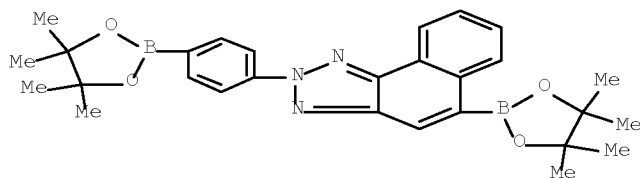
CRN 794518-79-9
 CMF C17 H11 Br2 N3 O



RN 794518-84-6 HCAPLUS
 CN 2H-Naphtho[1,2-d]triazole, 5-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-2-[4-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)phenyl]-, polymer with 1,4-dibromo-2,5-bis(octyloxy)benzene (9CI) (CA INDEX NAME)

CM 1

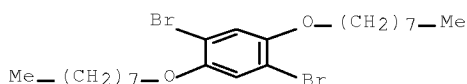
CRN 794518-83-5
 CMF C28 H33 B2 N3 O4



CM 2

CRN 156028-40-9

CMF C22 H36 Br2 O2



IC ICM C08G061-12

CC 37-3 (Plastics Manufacture and Processing)

Section cross-reference(s): 73, 74

ST optical device color purity soly benzotriazole
 polymer; coatability benzotriazole polymer coating film
 optical device; glass transition temp
 benzotriazole polymer optical device

IT Electroluminescent devices

Photoelectric devices

(manufacture of benzotriazole unit-containing polymers for use in
 optical devices)

IT 95-14-7DP, 1H-Benzotriazole, polymers 794518-77-7P
 794518-81-3P 794518-84-6P

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical
 or engineered material use); PREP (Preparation); USES (Uses)

(manufacture of benzotriazole unit-containing polymers for use in
 optical devices)

REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE
 FOR THIS RECORD. ALL CITATIONS AVAILABLE
 IN THE RE FORMAT

L31 ANSWER 6 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2004:616437 HCAPLUS [Full-text](#)

DOCUMENT NUMBER: 141:412461

TITLE: Migration of reactable UVAs and HALS in
 automotive plastic coatings

AUTHOR(S): Yaneff, Philip V.; Adamsons, Karlis; Cliff,
 Nancy; Kanouni, Mouhcine

CORPORATE SOURCE: DuPont Performance Coatings, Ajax, ON, L1S
 1R6, Can.

SOURCE: JCT Research (2004), 1(3), 201-212
 CODEN: JRCEB5; ISSN: 1547-0091

PUBLISHER: Federation of Societies for Coatings
 Technology

DOCUMENT TYPE: Journal

LANGUAGE: English

ED Entered STN: 02 Aug 2004

AB Loss of light stabilizers from automotive finishes can significantly reduce the
 durability of coatings on plastic substrates. Minimizing movement by retaining the
 stabilizers in the targeted layer can greatly improve coating longevity. This article

10/553,775-294324-EIC SEARCH

examines the migratory patterns of a series of traditional UVA and HALS additives in fully formulated 1K silane crosslinked coatings applied over both plastic and steel substrates, comparing their migratory patterns to that of reactable light stabilizers containing hydroxyl functionality. Anal. of the coating layers with the various UVAs and HALS revealed that functionalization of the light stabilizer with reactable hydroxy groups can prevent migration into the plastic; whereas nonreactable light stabilizers migrate into lower coating system layers and even into the plastic substrate. The greatest extent of migration does not occur during initial cure of the wet coating, but during exposure. Significant depletion of the nonreactable light stabilizers from the topcoat occurs as early as 1500 h of Xenon boro/boro exposure.

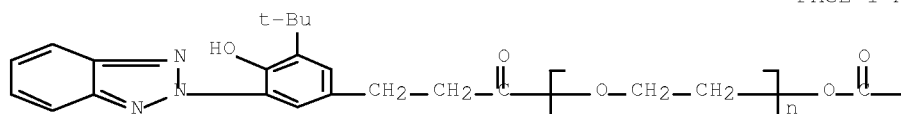
IT 104810-47-1 104810-48-2

RL: MOA (Modifier or additive use); PRP (Properties); USES (Uses)
(stabilizer; migration of reactive UV and hindered amine light stabilizers in automotive plastic coatings)

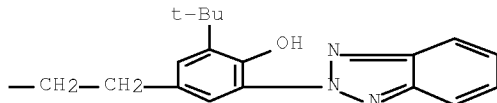
RN 104810-47-1 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]- ω -[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropoxy]- (CA INDEX NAME)

PAGE 1-A

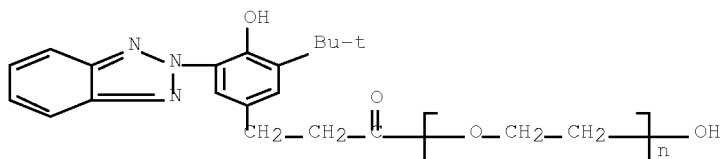


PAGE 1-B



RN 104810-48-2 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]- ω -hydroxy- (CA INDEX NAME)



CC 42-5 (Coatings, Inks, and Related Products)

IT Automobiles

Coating materials

Diffusion

ESR (electron spin resonance)

Light stabilizers

Oxidation, photochemical

UV absorption

10/553,775-294324-EIC SEARCH

UV stabilizers

(migration of reactive UV and hindered amine light stabilizers in automotive plastic coatings)

IT 73936-91-1 104810-47-1 104810-48-2

122586-52-1 137759-38-7 150686-79-6 178905-31-2

RL: MOA (Modifier or additive use); PRP (Properties); USES (Uses)

(stabilizer; migration of reactive UV and hindered amine light stabilizers in automotive plastic coatings)

REFERENCE COUNT: 12 THERE ARE 12 CITED REFERENCES AVAILABLE
FOR THIS RECORD. ALL CITATIONS AVAILABLE
IN THE RE FORMAT

L31 ANSWER 7 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2003:947956 HCAPLUS Full-text

DOCUMENT NUMBER: 140:11343

TITLE: Polymer electrolytes easily undergoing
photocrosslinking and electrochromic devices
therewith

INVENTOR(S): Nishikitani, Yoshinori; Asano, Takeshi; Ikai, Keizo

PATENT ASSIGNEE(S): Nippon Oil Corporation, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 16 pp.

CODEN: JKXXAF

DOCUMENT TYPE: ~~Patent~~

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	
JP 2003346553	A	20031205	JP 2002-150533	2002 0524
			<--	
JP 4166505	B2	20081015		
PRIORITY APPLN. INFO.:			JP 2002-150533	2002 0524

<--

ED Entered STN: 05 Dec 2003

AB The electrolytes, showing high ion conductivity and good dimensional accuracy, comprise photocured products of liquid mixts. containing polymers from R1R2C:CR3(CO2R4)nR5 [R1-R3 = H, C1-5 alkyl; R4 = C1-10 alkylene, C6-12 arylene, (CH2CHRO)r (R = H, C1-5 alkyl; r = 1-20); R5 = H, C1-10 alkyl, C6-12 aryl, C1-10 alkoxy; n = 0, 2], R'1R'3C:CR'2CO2CH2CH:CH2 (R'1-R'3 = H, C1-5 alkyl), and optional (UV-absorbing) comonomers, solvents, support electrolytes, and photopolymn. initiators.

IT ~~828684-62-8~~ 828684-62-8, Allyl methacrylate-methyl methacrylate-Ruva

93 copolymer, tetrabutylammonium complexes,

tetrafluoroborate-containing

RL: DEV (Device component use); IMF (Industrial manufacture); TEM
(Technical or engineered material use); PREP (Preparation); USES
(Uses)

(crosslinked; photocrosslinkable polymer electrolytes showing min. curing shrinkage for electrochromic devices)

RN 628684-62-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,

2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer

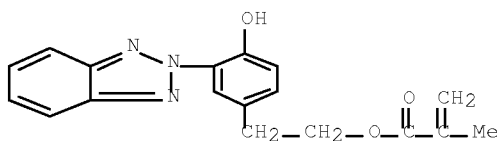
with methyl 2-methyl-2-propenoate and 2-propenyl

2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

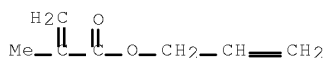
CRN 96478-09-0

CMF C18 H17 N3 O3



CM 2

CRN 96-05-9
CMF C7 H10 O2



CM 3

CRN 80-62-6
CMF C5 H8 O2



IC ICM H01B001-06
ICS C08F002-44; C08F220-10; C08F220-40; C08F299-00
CC 76-2 (Electric Phenomena)
Section cross-reference(s): 38
IT Electrochromic devices
Polymer electrolytes
(~~photocrosslinkable~~ polymer electrolytes showing min. curing shrinkage for electrochromic devices)
IT 7439-93-2DP, Lithium, methacrylate polymer complexes, perchlorate-containing 26715-19-5DP, Allyl methacrylate-methyl methacrylate copolymer, tetrabutylammonium complexes, tetrafluoroborate-containing ~~628684-62-8DP~~, Allyl methacrylate-methyl methacrylate-Ruva 93 copolymer, tetrabutylammonium complexes, tetrafluoroborate-containing
RL: DEV (Device component use); IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(crosslinked; photocrosslinkable polymer electrolytes showing min. curing shrinkage for electrochromic devices)

L31 ANSWER 8 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2003:586727 HCAPLUS Full-text
DOCUMENT NUMBER: 139:136074
TITLE: Pigment sensitized
photoelectrochemical cell
INVENTOR(S): Noda, Nobuhisa; Nakamura, Junichi
PATENT ASSIGNEE(S): Nippon Shokubai Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 15 pp.
CODEN: JKXXAF
DOCUMENT TYPE: ~~Patent~~

10/553,775-294324-EIC SEARCH

LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003217690	A	20030731	JP 2002-10691	2002 0118

PRIORITY APPLN. INFO.: JP 2002-10691
 2002
 0118

ED Entered STN: 31 Jul 2003

AB The photoelectrochem. cell has a UV shielding layer on its light incident side, where the layer is a formed from a composition containing a copolymer of a monomer having UV absorbing groups, a monomer having C_≥4 alkyl groups, and/or a monomer having UV stabilizing groups; or a composition containing a polymer of a monomer having C_≥4 alkyl groups and/or a monomer having UV stabilizing groups mixed with a UV absorbing additive.

IT 287736-69-0 569367-49-3 569367-51-7
 569367-53-9 569367-55-1

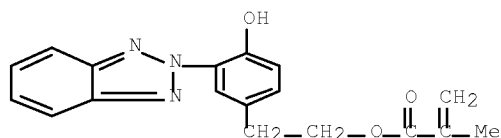
RL: DEV (Device component use); USES (Uses)
 (Uv shielding coatings for pigment sensitized
 photoelectrochem. cells)

RN 287736-69-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
 with 2-hydroxyethyl 2-methyl-2-propenoate and methyl
 2-methyl-2-propenoate (CA INDEX NAME)

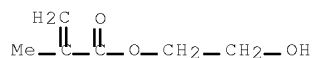
CM 1

CRN 96478-09-0
 CMF C18 H17 N3 O3



CM 2

CRN 868-77-9
 CMF C6 H10 O3



CM 3

CRN 80-62-6

10/553,775-294324-EIC SEARCH

CMF C5 H8 O2



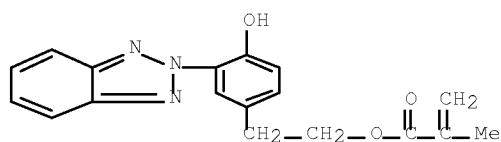
RN 569367-49-3 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with cyclohexyl 2-methyl-2-propenoate, 2-ethylhexyl 2-propenoate,
2-hydroxyethyl 2-methyl-2-propenoate and methyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 96478-09-0

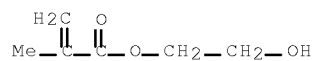
CMF C18 H17 N3 O3



CM 2

CRN 868-77-9

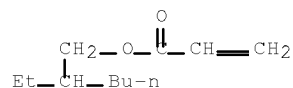
CMF C6 H10 O3



CM 3

CRN 103-11-7

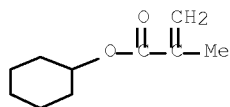
CMF C11 H20 O2



CM 4

CRN 101-43-9

CMF C10 H16 O2



CM 5

CRN 80-62-6
CMF C5 H8 O2

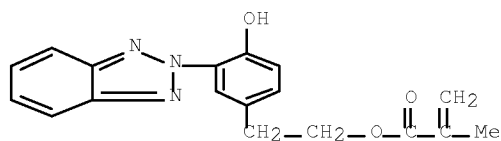


RN 569367-51-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with cyclohexyl 2-methyl-2-propenoate, 2-ethylhexyl 2-propenoate,
2-hydroxyethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate
and 1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate
(9CI) (CA INDEX NAME)

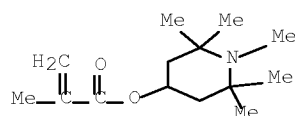
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 2

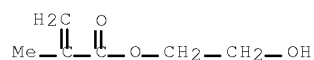
CRN 68548-08-3
CMF C14 H25 N O2



CM 3

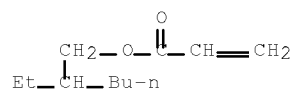
CRN 868-77-9
CMF C6 H10 O3

10/553,775-294324-EIC SEARCH



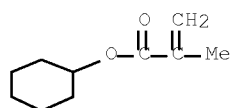
CM 4

CRN 103-11-7
CMF C11 H20 O2



CM 5

CRN 101-43-9
CMF C10 H16 O2



CM 6

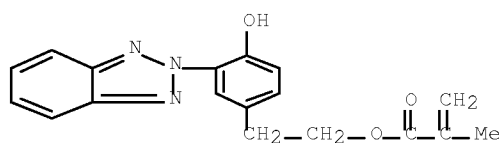
CRN 80-62-6
CMF C5 H8 O2



RN 569367-53-9 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with cyclohexyl 2-methyl-2-propenoate, 2-ethylhexyl 2-propenoate,
methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyl
2-methyl-2-propenoate and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

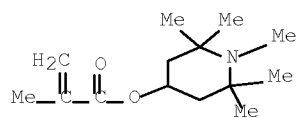
CRN 96478-09-0
CMF C18 H17 N3 O3



CM 2

CRN 68548-08-3

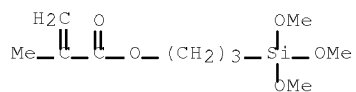
CMF C14 H25 N O2



CM 3

CRN 2530-85-0

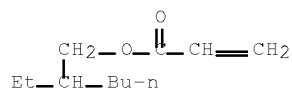
CMF C10 H20 O5 Si



CM 4

CRN 103-11-7

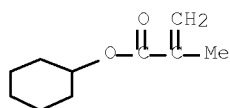
CMF C11 H20 O2



CM 5

CRN 101-43-9

CMF C10 H16 O2



10/553,775-294324-EIC SEARCH

CM 6

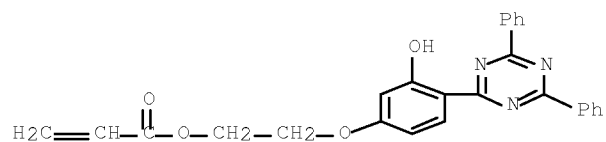
CRN 80-62-6
CMF C5 H8 O2



RN 569367-55-1 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with cyclohexyl 2-methyl-2-propenoate,
2-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-hydroxyphenoxy]ethyl
2-propenoate, 2-ethylhexyl 2-propenoate, 2-hydroxyethyl
2-methyl-2-propenoate, methyl 2-methyl-2-propenoate and
1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

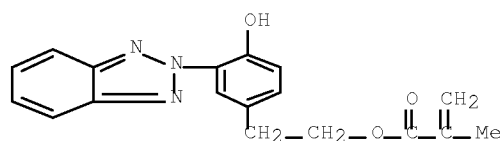
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CRN 176225-24-4
CMF C26 H21 N3 O4



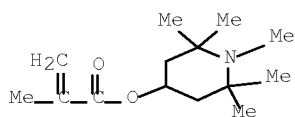
CM 2

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 3

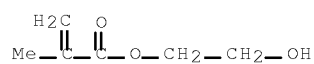
CRN 68548-08-3
CMF C14 H25 N O2



CM 4

CRN 868-77-9

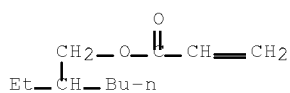
CMF C6 H10 O3



CM 5

CRN 103-11-7

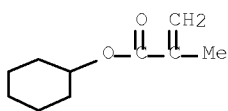
CMF C11 H20 O2



CM 6

CRN 101-43-9

CMF C10 H16 O2



CM 7

CRN 80-62-6

CMF C5 H8 O2



IC ICM H01M014-00
ICS H01L031-04

10/553,775-294324-EIC SEARCH

CC 52-2 (Electrochemical, Radiational, and Thermal Energy Technology)
 ST pigment sensitized photoelectrochem cell UV shielding
 polymer layer
 IT Photoelectrochemical cells
 UV shields
 (Uv shielding coatings for pigment sensitized
 photoelectrochem. cells)
 IT 26355-01-1 28549-51-1 287736-69-0 569367-47-1
 569367-49-3 569367-51-7 569367-53-9
 569367-55-1 569367-57-3
 RL: DEV (Device component use); USES (Uses)
 (Uv shielding coatings for pigment sensitized
 photoelectrochem. cells)

L31 ANSWER 9 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2003:520420 HCAPLUS Full-text
 DOCUMENT NUMBER: 139:86337
 TITLE: Antisoiling, weather-resistant waterproof
 sheets
 INVENTOR(S): Suzuki, Kenji
 PATENT ASSIGNEE(S): Hiraoka and Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 28 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	
JP 2003191386	A	20030708	JP 2002-93052	2002 0328
			<--	
PRIORITY APPLN. INFO.:			JP 2001-95879	A 2001 0329
			<--	
			JP 2001-318365	A 2001 1016
			<--	

ED Entered STN: 09 Jul 2003

AB The sheets, useful for medium to large-scale tents, etc., consist of a base sheet comprising a base fabric and polymer layer(s) containing natural rubber, synthetic rubber, and/or synthetic resins formed on at least one side of the base fabric, and hydrophilic coating layer(s) containing organosilicates and/or their condensates formed on the polymer layer(s). Thus, a polyester fabric was coated with a composition containing self-emulsifiable acrylic resin (Nipol SX 1706) 70, primary amino group-containing acrylic resin (Polymert NK-CK 200) 30, light stabilizer (Tinofast RSC) 0.2, UV absorber (Tinuvin 213) 0.2, TiO₂ 3, and 5-chlorobenzotriazole 0.1 part on the both sides and dried to give a base sheet, which was coated with an aqueous MeOH solution of Me silicate partial hydrolytic condensation product (MKC Silicate MS 56) 100, γ -glycidoxypropyltrimethoxysilane 10, and organometallic chelating agent 0.3 part on the both sides and dried to give a product showing long-lasting antisoiling properties during outdoor exposure.

IT 153175-43-0, Puva 30M

RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
 (additive migration-proofing layer; antisoiling,
 weather-resistant waterproof sheets coated with silicates)

RN 153175-43-0 HCAPLUS

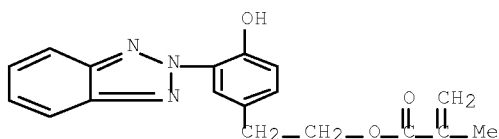
CN 2-Propenoic acid, 2-methyl-,
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
 with methyl 2-methyl-2-propenoate (CA INDEX NAME)

10/553,775-294324-EIC SEARCH

CM 1

CRN 96478-09-0

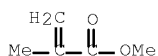
CMF C18 H17 N3 O3



CM 2

CRN 80-62-6

CMF C5 H8 O2



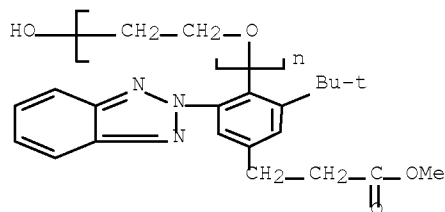
IT 136457-10-8, Tinuvin 213

RL: MOA (Modifier or additive use); USES (Uses)

(base fabric coating containing; antisoiling, weather-resistant waterproof sheets coated with silicates)

RN 136457-10-8 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -[2-(2H-benzotriazol-2-yl)-6-(1,1-dimethylethyl)-4-(3-methoxy-3-oxopropyl)phenyl]- ω -hydroxy-
(CA INDEX NAME)



IC ICM B32B027-00

ICS C09K003-00

CC 38-3 (Plastics Fabrication and Uses)

Section cross-reference(s): 40

IT 9002-89-5, PVA 117 9002-98-6D, Polyethylenimine, graft polymers with acrylic resins 9011-14-7, Methyl methacrylate resin 25068-38-6, Epikote 828 25684-76-8, Kynar 7201 64735-01-9, Elastron 37 153175-43-0, Puva 30M

159131-89-2, Polyment NK 380 364053-83-8, Sony Bond SC 474

RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)

(additive migration-proofing layer; antisoiling, weather-resistant waterproof sheets coated with silicates)

10/553,775-294324-EIC SEARCH

IT 91-76-9, Benzoguanamine 3319-31-1, Tris-2-ethylhexyl trimellitate 27178-16-1, Diisodecyl adipate 28553-12-0, Diisononyl phthalate 57583-54-7, Fyrolflex RDP 136457-10-8, Tinuvin 213 204143-67-9, Tinofast RSC 461642-21-7, NK Assist OX 473900-22-0, Epostar GP 50
 RL: MOA (Modifier or additive use); USES (Uses)
 (base fabric coating containing; antisoiling, weather-resistant waterproof sheets coated with silicates)

L31 ANSWER 10 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2003:271851 HCAPLUS Full-text

DOCUMENT NUMBER: 138:289107

TITLE: Fluororesin powder coating compositions with weather resistance

INVENTOR(S): Kasahara, Kiyoshi; Yamauchi, Suguru; Unoki, Masao

PATENT ASSIGNEE(S): Asahi Glass Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 8 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
JP 2003105250	A	20030409	JP 2001-298287	2001 0927

PRIORITY APPLN. INFO.: <-- JP 2001-298287 2001 0927

ED Entered STN: 09 Apr 2003

AB Title compns. contain fluororesins and benzotriazole vinyl compound-based UV-absorbing resins. A powdered composition containing Bu methacrylate-2-hydroxyethyl methacrylate-Me methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy-2-hydroxypropoxycarbonyl)ethylphenyl]-2H-benzotriazole copolymer, cyclohexyl vinyl ether-chlorotrifluoroethylene-4-hydroxybutyl vinyl ether copolymer, and ct B 1530 was electrodeposited on a white urethane base composition-coated plate and cured at 180° for 20 min to form a film showing 60° gloss 100 with 99% retention after 2,000 h under weatherometer and good adhesion to white base coat.

IT 505023-79-00, Cyclohexyl vinyl ether-chlorotrifluoroethylene-4-hydroxybutyl vinyl ether-butyl methacrylate-2-hydroxyethyl methacrylate-methyl methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy)-2-hydroxypropoxycarbonyl)ethylphenyl]-2H-benzotriazole-Vestagon B 1530 copolymer
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (cured; powdered fluororesin coatings containing benzotriazole-containing acrylic resins for weather resistance)

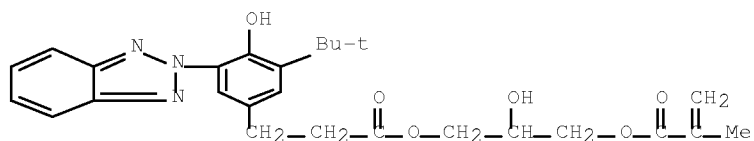
RN 505023-79-0 HCAPLUS

CN Benzenepropanoic acid, 3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxy-, 2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl ester, polymer with butyl 2-methyl-2-propenoate, chlorotrifluoroethene, 4-(ethenyloxy)-1-butanol, (ethenyloxy)cyclohexane, 2-hydroxyethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate and Vestagon B 1530 (9CI) (CA INDEX NAME)

CM 1

CRN 135590-53-3

CMF C26 H31 N3 O6



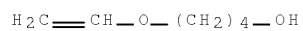
CM 2

CRN 81647-82-7
 CMF Unspecified
 CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

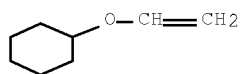
CM 3

CRN 17832-28-9
 CMF C6 H12 O2



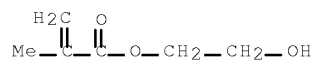
CM 4

CRN 2182-55-0
 CMF C8 H14 O



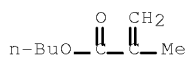
CM 5

CRN 868-77-9
 CMF C6 H10 O3



CM 6

CRN 97-88-1
 CMF C8 H14 O2



CM 7

CRN 80-62-6
CMF C5 H8 O2



CM 8

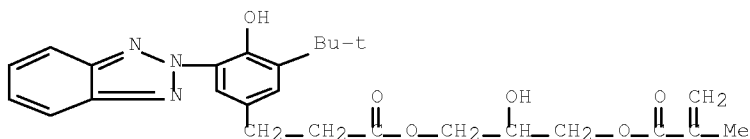
CRN 79-38-9
CMF C2 Cl F3



IT 505023-82-5P, Butyl methacrylate-2-hydroxyethyl methacrylate-methyl methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy)-2-hydroxypropoxycarbonyl]ethylphenyl]-2H-benzotriazole copolymer
 RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (powdered fluororesin coatings containing benzotriazole-containing acrylic resins for weather resistance)
 RN 505023-82-5 HCAPLUS
 CN Benzenepropanoic acid, 3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxy-, 2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl ester, polymer with butyl 2-methyl-2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

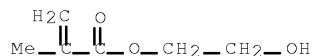
CM 1

CRN 135590-53-3
CMF C26 H31 N3 O6

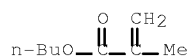


10/553,775-294324-EIC SEARCH

CM 2

CRN 868-77-9
CMF C6 H10 O3

CM 3

CRN 97-88-1
CMF C8 H14 O2

CM 4

CRN 80-62-6
CMF C5 H8 O2

IT 505023-80-3P, Cyclohexyl vinyl ether-chlorotrifluoroethylene-4-hydroxybutyl vinyl ether-isobutyl vinyl ether-butyl methacrylate-2-hydroxyethyl methacrylate-methyl methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy)-2-hydroxypropoxycarbonyl]ethylphenyl]-2H-benzotriazole-Vestagon B 1530 copolymer

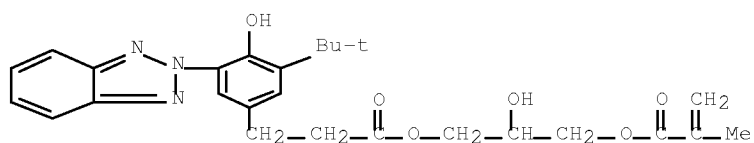
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(powdered fluororesin coatings containing benzotriazole-containing acrylic resins for weather resistance)

RN 505023-80-3 HCAPLUS

CN Benzenepropanoic acid, 3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxy-, 2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl ester, polymer with butyl 2-methyl-2-propenoate, chlorotrifluoroethene, 4-(ethenyloxy)-1-butanol, (ethenyloxy)cyclohexane, 1-(ethenyloxy)-2-methylpropane, 2-hydroxyethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate and Vestagon B 1530 (9CI) (CA INDEX NAME)

CM 1

CRN 135590-53-3
CMF C26 H31 N3 O6



CM 2

CRN 81647-82-7

CMF Unspecified

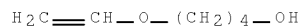
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 3

CRN 17832-28-9

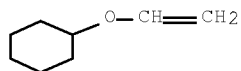
CMF C6 H12 O2



CM 4

CRN 2182-55-0

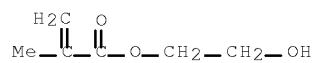
CMF C8 H14 O



CM 5

CRN 868-77-9

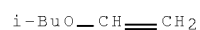
CMF C6 H10 O3



CM 6

CRN 109-53-5

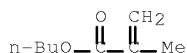
CMF C6 H12 O



10/553,775-294324-EIC SEARCH

CM 7

CRN 97-88-1
CMF C8 H14 O2



CM 8

CRN 80-62-6
CMF C5 H8 O2



CM 9

CRN 79-38-9
CMF C2 Cl F3



IC ICM C09D127-12
ICS C09D005-03; C09D133-14; C09D133-24; C09D157-12
CC 42-10 (Coatings, Inks, and Related Products)
IT 505023-79-0P, Cyclohexyl vinyl ether-chlorotrifluoroethylene-4-hydroxybutyl vinyl ether-butyl methacrylate-2-hydroxyethyl methacrylate-methyl methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy)-2-hydroxypropoxycarbonyl]ethylphenyl]-2H-benzotriazole-Vestagon B 1530 copolymer
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(cured; powdered fluororesin coatings containing benzotriazole-containing acrylic resins for weather resistance)
IT 29697-44-7P, Ethylene-propene-tetrafluoroethylene copolymer
505023-81-4P, Butyl methacrylate-tert-butyl methacrylate-2-hydroxyethyl methacrylate-methyl methacrylate copolymer 505023-82-5P, Butyl methacrylate-2-hydroxyethyl methacrylate-methyl methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy)-2-hydroxypropoxycarbonyl]ethylphenyl]-2H-benzotriazole copolymer
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(powdered fluororesin coatings containing benzotriazole-containing acrylic

10/553,775-294324-EIC SEARCH

resins for weather resistance)
 IT ~~505023-80-38~~, Cyclohexyl vinyl
 ether-chlorotrifluoroethylene-4-hydroxybutyl vinyl ether-isobutyl
 vinyl ether-butyl methacrylate-2-hydroxyethyl methacrylate-methyl
 methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy)-
 2-hydroxypropoxycarbonyl)ethylphenyl]-2H-benzotriazole-Vestagon B
 1530 copolymer
 RL: IMF (Industrial manufacture); TEM (Technical or engineered
 material use); PREP (Preparation); USES (Uses)
 (powdered fluororesin coatings containing benzotriazole-containing acrylic
 resins for weather resistance)

L31 ANSWER 11 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2003:118356 HCAPLUS Full-text

DOCUMENT NUMBER: 138:178010

TITLE: Ultraviolet stabilizing materials having a
 solubilizing moiety for use in electrochromic
 devices

INVENTOR(S): Giri, Punam; Kloeppner, Leroy J.; Baumann,
 Kelvin L.; Lompfrey, Jeffrey R.; Guarr, Thomas
 F.

PATENT ASSIGNEE(S): USA

SOURCE: U.S. Pat. Appl. Publ., 13 pp., Cont.-in-part
 of U. S. 6,445,486.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 5

PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
US 20030030883	A1	20030213	US 2002-211485	2002 0802
			<--	
US 6614578	B2	20030902		
US 6262832	B1	20010717	US 1999-454043	1999 1203
			<--	
US 6445486	B1	20020903	US 2000-724118	2000 1128
			<--	
WO 2004013688	A1	20040212	WO 2003-US23608	2003 0729
			<--	
W: AT, AU, BG, BR, CA, CH, CN, CZ, DE, DK, ES, FI, GB, GE, HU, ID, IL, IN, JP, KR, MX, NO, NZ, PL, PT, RO, RU, SE, SG, SK, TR, UA, YU, ZA				
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR				
AU 2003261284	A1	20040223	AU 2003-261284	2003 0729
			<--	
EP 1540413	A1	20050615	EP 2003-766942	2003 0729
			<--	
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
PRIORITY APPLN. INFO.:			US 1999-454043	A2

10/553,775-294324-EIC SEARCH

1999

1203

<--
US 2000-724118 A2

2000

1128

<--
US 2002-211485 A

2002

0802

<--
WO 2003-US23608 W

2003

0729

<--

OTHER SOURCE(S): MARPAT 138:178010

ED Entered STN: 14 Feb 2003

AB An electrochromic medium for use in electrochromic devices is described which comprises ≥ 1 solvent; an ~~anodic~~ material; a ~~cathodic~~ material, where both of the ~~anodic~~ and ~~cathodic~~ materials are electroactive and ≥ 1 of the ~~anodic~~ and ~~cathodic~~ materials is electrochromic; and an UV stabilizing material, where the UV stabilizing material includes a solubilizing moiety which serves to increase solubility of the UV stabilizing material relative to the same without the solubilizing moiety. Electrochromic devices are discussed which comprise a first substantially transparent substrate having an elec. conductive material; a second substrate having an elec. conductive material; and an electrochromic medium contained within a chamber positioned between the first and second substrates which comprises ≥ 1 solvent; an ~~anodic~~ material; a ~~cathodic~~ material, where both of the ~~anodic~~ and ~~cathodic~~ materials are electroactive and ≥ 1 of the ~~anodic~~ and ~~cathodic~~ materials is electrochromic; and an UV stabilizing material, where the UV stabilizing material includes a solubilizing moiety which serves to increase solubility of the UV stabilizing material relative to the same without the solubilizing moiety. Electrochromic media and devices in which the UV stabilizing material is a Ph benzotriazole derivative including a solubilizing moiety are also discussed.

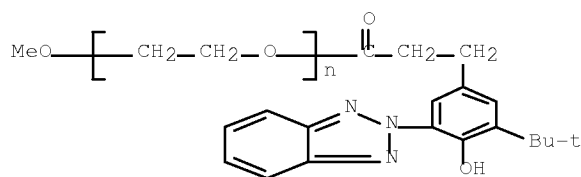
IT 497068-80-1P

RL: DEV (Device component use); PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(UV stabilizing materials having solubilizing moiety for use in electrochromic devices)

RN 497068-80-1 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]-~~o~~-methoxy-(9CI) (CA INDEX NAME)



IC ICM G02F001-15

INCL 359265000

CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)

Section cross-reference(s): 22, 68, 74, 76

IT Coating materials

(~~reflective~~, substrate of electrochromic device plated with; UV stabilizing materials having solubilizing moiety for use in electrochromic devices)

10/553,775-294324-EIC SEARCH

IT 84267-86-7P 497068-76-5P 497068-79-8P ~~497068-80-1P~~
 RL: DEV (Device component use); PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (UV stabilizing materials having solubilizing moiety for use in electrochromic devices)

IT 7440-16-6, Rhodium, uses 7440-16-6D, Rhodium, alloy 7440-18-8, Ruthenium, uses 7440-18-8D, Ruthenium, alloy 7440-22-4, Silver, uses 7440-22-4D, Silver, alloy 7440-47-3, Chromium, uses 7440-47-3D, Chromium, alloy
 RL: TEM (Technical or engineered material use); USES (Uses)
 (substrate of electrochromic device plated with ~~reflective~~; UV stabilizing materials having solubilizing moiety for use in electrochromic devices)

L31 ANSWER 12 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2003:111338 HCAPLUS Full-text

DOCUMENT NUMBER: 138:178317

TITLE: ~~Optical~~ film containing benzophenone and/or benzotriazole UV absorber for excellent color reproducibility, polarizing plate and ~~optical~~ imaging display

INVENTOR(S): Michihata, Isamu; Shimizu, Kunio; Saito, Koichi

PATENT ASSIGNEE(S): Konica Co., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 18 pp.

CODEN: JKXXAF

DOCUMENT TYPE: ~~Patent~~

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2003043259	A	20030213	JP 2001-233464	2001 0801
			<--	
JP 2008304930	A	20081218	JP 2008-184714	2008 0716
			<--	
PRIORITY APPLN. INFO.:			JP 2001-233464	A3 2001 0801
			<--	

ED Entered STN: 13 Feb 2003

AB The ~~optical~~ film contains a benzophenone and/or benzotriazole UV absorber, and has a spectral transmittance 50-95% at 390 nm and a spectral transmittance ≤5% at 350 nm. The ~~optical~~ film is based on a cellulose ester, and has a film thickness 20-65 μm. The polarizing plate and the ~~optical~~ imaging device such as LCD and EL devices are also claimed.

IT ~~153175-43-0~~, PUVA-30M

RL: DEV (Device component use); USES (Uses)
 (~~optical~~ film containing benzophenone and/or benzotriazole UV absorber for polarizing plate and ~~optical~~ imaging display)

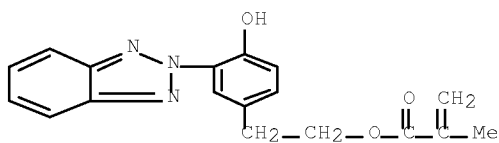
RN 153175-43-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
 with methyl 2-methyl-2-propenoate (CA INDEX NAME)

CM 1

CRN 96478-09-0

CMF C18 H17 N3 O3



CM 2

CRN 80-62-6

CMF C5 H8 O2



IC ICM G02B005-30
 ICS C08J005-18; C08K003-36; C08K005-07; C08K005-3475; C08L001-10;
 C08L101-00; G02B005-22; G02F001-1335; G09F009-00

CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and
 Other Reprographic Processes)
 Section cross-reference(s): 25, 28, 41, 73

ST optical film benzophenone benzotriazole UV absorber; liq
 crystal display electroluminescence device

IT Electroluminescent devices
 Liquid crystal displays
 (optical film containing benzophenone and/or
 benzotriazole UV absorber for)

IT Optical films
 Polarizers
 UV stabilizers
 (optical film containing benzophenone and/or
 benzotriazole UV absorber for polarizing plate and
 optical imaging display)

IT 9004-34-6, Cellulose, uses
 RL: DEV (Device component use); USES (Uses)
 (ester, support; optical film containing benzophenone
 and/or benzotriazole UV absorber for polarizing plate and
 optical imaging display)

IT 131-57-7 23328-53-2 38080-43-2 153175-43-0, PUVA-30M
 RL: DEV (Device component use); USES (Uses)
 (optical film containing benzophenone and/or
 benzotriazole UV absorber for polarizing plate and
 optical imaging display)

L31 ANSWER 13 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2002:848332 HCAPLUS Full-text
 DOCUMENT NUMBER: 137:343669
 TITLE: Organic electroluminescent devices
 INVENTOR(S): Kato, Hiroshi
 PATENT ASSIGNEE(S): Ricoh Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 10 pp.
 CODEN: JKXXAF

DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

10/553,775-294324-EIC SEARCH

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002324664	A	20021108	JP 2001-131017	2001 0427
PRIORITY APPLN. INFO.:			<-- JP 2001-131017	2001 0427
			<--	

ED Entered STN: 08 Nov 2002

AB The devices comprise: a glass substrate; a polymer layer containing a pendant-type UV absorber; an ITO 1st electrode; a hole transport, a phosphor, an electron transport and a metal 2nd electrode.

IT 153175-43-0, PUVA-30M
RL: DEV (Device component use); USES (Uses)
(organic electroluminescent devices)

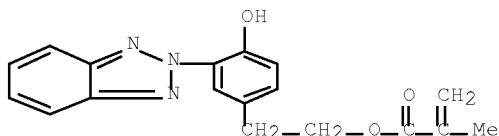
RN 153175-43-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with methyl 2-methyl-2-propenoate (CA INDEX NAME)

CM 1

CRN 96478-09-0

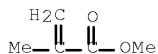
CMF C18 H17 N3 O3



CM 2

CRN 80-62-6

CMF C5 H8 O2



IC ICM H05B033-04
ICS H05B033-14; H05B033-22

CC 73-5 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)

IT Anodes
Cathodes
Electrodes
Electron transport
Hole transport
Phosphors
Seals (parts)
UV stabilizers
(organic electroluminescent devices)

IT 50926-11-9, ITO 76185-65-4 80223-29-6 134917-82-1

10/553,775-294324-EIC SEARCH

153175-43-0, PUVA-30M 157357-76-1

RL: DEV (Device component use); USES (Uses)
(organic electroluminescent devices)

L31 ANSWER 14 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2002:606627 HCAPLUS Full-text

DOCUMENT NUMBER: 137:161224

TITLE: Low ~~reflectance~~ laminate and its production

INVENTOR(S): Murakami, Takashi; Takiyama, Nobuyuki; Fukuda, Kazuhiro

PATENT ASSIGNEE(S): Konica Co., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 23 pp.

CODEN: JKXXAF

DOCUMENT TYPE: ~~Patent~~

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2002228803	A	20020814	JP 2001-21573	

2001

0130

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PRIORITY APPLN. INFO.:

JP 2001-21573

2001

0130

<--

ED Entered STN: 14 Aug 2002

AB The invention refers to a low ~~reflection~~ laminate, suitable for use in cathode ray tubes, plasma display panels, solar cells, liquid crystal displays, etc., wherein a substrate is placed between two ~~electrodes~~, one of which is a roll ~~electrode~~ with surface roughness $R_{max} < 10 \mu m$ and the other is coated with an inorg. material, and the substrate is coated with a fluorine, silicon or titanium thin film using plasma discharge treatment in order to produce a laminate with minimal ~~reflectivity~~ and minimal contamination from the plasma discharge process.

IT 153175-43-0, PUVA-30M

RL: DEV (Device component use); USES (Uses)

(low ~~reflectance~~ laminate and production)

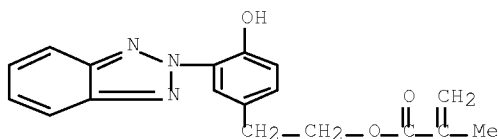
RN 153175-43-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with methyl 2-methyl-2-propenoate (CA INDEX NAME)

CM 1

CRN 96478-09-0

CMF C18 H17 N3 O3



CM 2

CRN 80-62-6

CMF C5 H8 O2

10/553,775-294324-EIC SEARCH



IC ICM G02B001-11
 ICS B32B027-00; B32B027-30; C08J007-00; C23C016-40; G02B001-10;
 C08L001-00
 CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related
 Properties)
 ST low ~~reflectance~~ laminate plasma discharge treatment
 antireflection film
 IT Antireflective films
 Laminated materials
 Optical ~~reflection~~
 Plasma
 (low ~~reflectance~~ laminate and production)
 IT 84-72-0, Ethyl phthalyl ethyl glycolate 115-86-6, Triphenyl
 phosphate 3896-11-5, Tinuvin 326 7440-21-3, Silicon, uses
 7440-32-6, Titanium, uses 7631-86-9, Silica, uses 7782-41-4,
 Fluorine, uses 9012-09-3, Triacetyl cellulose 23328-53-2,
 Tinuvin 171 67653-78-5, Dipentaerythritol hexaacrylate
 homopolymer 83044-89-7, Tinuvin 109 153175-43-0,
 PUVA-30M 200734-67-4, KE-604
 RL: DEV (Device component use); USES (Uses)
 (low ~~reflectance~~ laminate and production)

L31 ANSWER 15 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2002:107451 HCAPLUS Full-text

DOCUMENT NUMBER: 136:169112

TITLE: Colored resin emulsion, ink for ink-jet
 printing, electrocoating fluid and color
 filter

INVENTOR(S): Ishii, Masahiro; Shichiri, Tokushige; Oguchi,
 Yoshiyuki; Toyoshima, Katsunori; Ueda,
 Michihisa

PATENT ASSIGNEE(S): Sekisui Chemical Co. Ltd., Japan

SOURCE: PCT Int. Appl., 140 pp.

CODEN: PIXXD2

DOCUMENT TYPE: ~~Patent~~

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2002010280	A1	20020207	WO 2001-JP6518	2001 0730

<--

JP 2002105272	A	20020410	JP 2000-312154	2000 1012
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JP 2002356602	A	20021213	JP 2001-229429	2001 0730
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PRIORITY APPLN. INFO.: JP 2000-229324 A

10/553,775-294324-EIC SEARCH

2000
0728

<--
JP 2000-242820 A
2000
0810

<--
JP 2000-267377 A
2000
0904

<--
JP 2000-340679 A
2000
1108

<--
JP 2001-789 A
2001
0105

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JP 2001-28322 A
2001
0205

<--
JP 2001-99913 A
2001
0330

<--

ED Entered STN: 10 Feb 2002

AB The present invention relates to a colored resin emulsion which comprises an aqueous medium and, dispersed in the medium, colorant-incorporating resin particles comprising a colorant and a vinyl resin which is prepared by polymerizing a mixed monomer comprising 100 parts by weight of a hydrophobic vinyl monomer, 1 to 30 parts by weight of a vinyl monomer having an anionic or cationic group and 1 to 55 parts by weight of a vinyl monomer having a nonionic group; and an ink for ink-jet printing, an electrocoating fluid and a color filter using the colored resin emulsion. The colored resin emulsion exhibits excellent stability, weatherability and resistance to light. Thus, N-butoxymethylacrylamide 100, hydroxyethyl methacrylate 11.8, methacrylic acid 5.9 parts were polymerized in 341.0 parts Et acetate containing 11.8 parts V 65, 23.5 parts Orasol Red G was added to give a colored vinyl type resin solution, which was stirred with NH3 aqueous solution to give a colored resin emulsion with average particle size 76 nm. A ink-jet printing ink comprised the resulting emulsion (20%-solids) 50, glycerin 20, and water 30 parts.

IT ~~395681-56-8P~~ ~~395681-58-0P~~

RL: IMF (Industrial manufacture); POF (Polymer in formulation);
TEM (Technical or engineered material use); PREP (Preparation);
USES (Uses)

(colored resin emulsions for ink-jet printing inks,
electrocoating fluids and color filters)

RN 395681-56-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl
2-methyl-2-propenoate, N-(butoxymethyl)-2-propenamide,
2-hydroxyethyl 2-methyl-2-propenoate and methyl
2-methyl-2-propenoate, ammonium salt (9CI) (CA INDEX NAME)

CM 1

CRN 395681-55-7

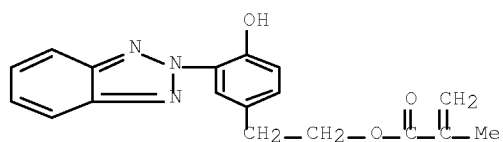
CMF (C18 H17 N3 O3 . C8 H15 N O2 . C6 H10 O3 . C5 H8 O2 . C4 H6
O2)x

CCI PMS

CM 2

CRN 96478-09-0

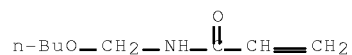
CMF C18 H17 N3 O3



CM 3

CRN 1852-16-0

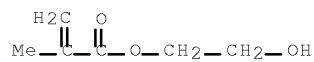
CMF C8 H15 N O2



CM 4

CRN 868-77-9

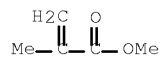
CMF C6 H10 O3



CM 5

CRN 80-62-6

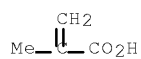
CMF C5 H8 O2



CM 6

CRN 79-41-4

CMF C4 H6 O2



RN 395681-58-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl

10/553,775-294324-EIC SEARCH

2-methyl-2-propenoate, N-butoxy-2-propenamide, 2-hydroxyethyl
2-methyl-2-propenoate and methyl 2-methyl-2-propenoate, ammonium
salt (9CI) (CA INDEX NAME)

CM 1

CRN 395681-57-9

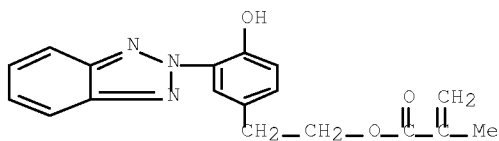
CMF (C18 H17 N3 O3 . C7 H13 N O2 . C6 H10 O3 . C5 H8 O2 . C4 H6
O2) x

CCI PMS

CM 2

CRN 96478-09-0

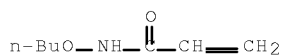
CMF C18 H17 N3 O3



CM 3

CRN 4203-85-4

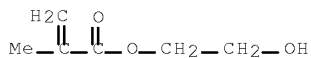
CMF C7 H13 N O2



CM 4

CRN 868-77-9

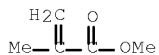
CMF C6 H10 O3



CM 5

CRN 80-62-6

CMF C5 H8 O2

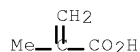


10/553,775-294324-EIC SEARCH

CM 6

CRN 79-41-4

CMF C4 H6 O2



IC ICM C08L057-00
ICS C08J003-03; C09D011-00; C08J003-24; B41M005-00; G02B005-20;
G02B005-22
CC 42-12 (Coatings, Inks, and Related Products)
Section cross-reference(s): 37, 38, 73
IT Coloring materials
Electrodeposits
Optical filters
Pigments, nonbiological
(colored resin emulsions for ink-jet printing inks,
electrocoating fluids and color filters)
IT 208838-83-9P 395681-50-2P 395681-52-4P 395681-54-6P
~~395681-56-8P~~ ~~395681-58-0P~~ 395681-60-4P
395681-62-6P 395681-64-8P 395681-65-9P 395681-66-0P
395681-68-2P 395681-69-3P 395681-71-7P 395681-73-9P
395681-74-0P 395681-75-1P 395681-77-3P 395681-79-5P
395681-80-8P 395681-82-0P 395681-84-2P 395681-86-4P
395681-88-6P 395681-90-0P 395681-92-2P 395681-94-4P
395681-96-6P
RL: IMF (Industrial manufacture); POF (Polymer in formulation);
TEM (Technical or engineered material use); PREP (Preparation);
USES (Uses)
(colored resin emulsions for ink-jet printing inks,
electrocoating fluids and color filters)
REFERENCE COUNT: 9 THERE ARE 9 CITED REFERENCES AVAILABLE
FOR THIS RECORD. ALL CITATIONS AVAILABLE
IN THE RE FORMAT

L31 ANSWER 16 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2002:98759 HCAPLUS Full-text
DOCUMENT NUMBER: 136:152807
TITLE: Weather-resistant anionic
electrodeposition coating materials
INVENTOR(S): Mizoguch, Yoshitaka; Aoki, Kenji
PATENT ASSIGNEE(S): Kansai Paint Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2002038084	A	20020206	JP 2000-220236	2000 0721
			<--	
PRIORITY APPLN. INFO.:			JP 2000-220236	2000 0721
			<--	

10/553,775-294324-EIC SEARCH

ED Entered STN: 06 Feb 2002

AB Coating materials contain acrylic copolymers having acid value 20-200 mg KOH/g and OH value 20-200 mg KOH/g, amino resin hardeners, blocked polyisocyanate hardeners, UV absorbers, and light stabilizers. Thus, a coating material (8% solids) on anodically oxidized Al contained acrylic acid-Bu acrylate-Et acrylate-2-hydroxyethyl acrylate-2-(2'-hydroxy-5'-methacryloxyethylphenyl)-2H- benzotriazole-4-methacryloyloxy-1,2,2,6,6-pentamethylpiperidine-Me methacrylate-styrene copolymer triethylamine salt 7 (as copolymer), Cymel 300 2, Duranate 24A90CX 1, p-toluenesulfonic acid 0.05 kg, water, and triethylamine (to pH 8.0).

IT 394251-89-8DP, reaction products with blocked polyisocyanates and melamine resins 394251-92-4DP, reaction products with blocked polyisocyanates and melamine resins 394251-94-6DP, reaction products with blocked polyisocyanates and melamine resins 394251-96-8DP, reaction products with blocked polyisocyanates and melamine resins
 RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

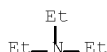
RN 394251-89-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate, 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate and 2-propenoic acid, compd. with N,N-diethylethanamine (9CI) (CA INDEX NAME)

CM 1

CRN 121-44-8

CMF C6 H15 N



CM 2

CRN 394251-88-8

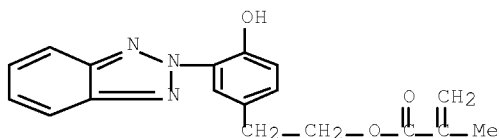
CMF (C18 H17 N3 O3 . C14 H25 N O2 . C8 H8 . C7 H12 O2 . C5 H8 O3 . C5 H8 O2 . C5 H8 O2 . C3 H4 O2)x

CCI PMS

CM 3

CRN 96478-09-0

CMF C18 H17 N3 O3

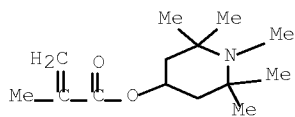


10/553,775-294324-EIC SEARCH

CM 4

CRN 68548-08-3

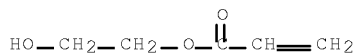
CMF C14 H25 N O2



CM 5

CRN 818-61-1

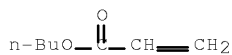
CMF C5 H8 O3



CM 6

CRN 141-32-2

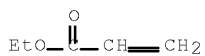
CMF C7 H12 O2



CM 7

CRN 140-88-5

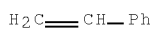
CMF C5 H8 O2



CM 8

CRN 100-42-5

CMF C8 H8



10/553,775-294324-EIC SEARCH

CM 9

CRN 80-62-6

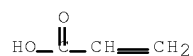
CMF C5 H8 O2



CM 10

CRN 79-10-7

CMF C3 H4 O2



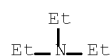
RN 394251-92-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
 with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
 2-propenoic acid and 2,2,6,6-tetramethyl-4-piperidinyl
 2-methyl-2-propenoate, compd. with N,N-diethylethanamine (9CI)
 (CA INDEX NAME)

CM 1

CRN 121-44-8

CMF C6 H15 N



CM 2

CRN 394251-91-3

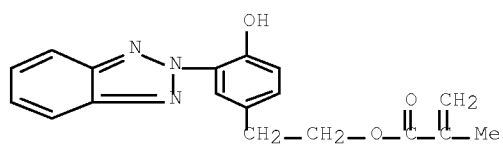
CMF (C18 H17 N3 O3 . C13 H23 N O2 . C8 H8 . C7 H12 O2 . C5 H8 O3
 . C5 H8 O2 . C5 H8 O2 . C3 H4 O2)x

CCI PMS

CM 3

CRN 96478-09-0

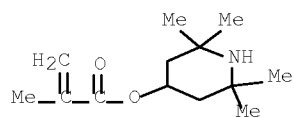
CMF C18 H17 N3 O3



CM 4

CRN 31582-45-3

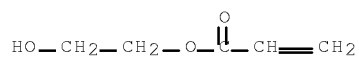
CMF C13 H23 N O2



CM 5

CRN 818-61-1

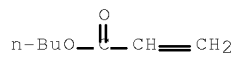
CMF C5 H8 O3



CM 6

CRN 141-32-2

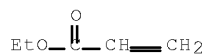
CMF C7 H12 O2



CM 7

CRN 140-88-5

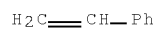
CMF C5 H8 O2



CM 8

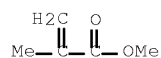
10/553,775-294324-EIC SEARCH

CRN 100-42-5
CMF C8 H8



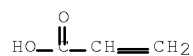
CM 9

CRN 80-62-6
CMF C5 H8 O2



CM 10

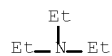
CRN 79-10-7
CMF C3 H4 O2



RN 394251-94-6 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate,
2-propenoic acid and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate, compd. with N,N-diethylethanamine (9CI)
(CA INDEX NAME)

CM 1

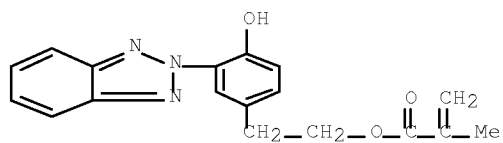
CRN 121-44-8
CMF C6 H15 N



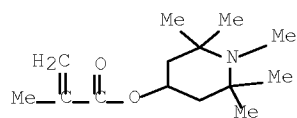
CM 2

CRN 328404-57-5
CMF (C18 H17 N3 O3 . C14 H25 N O2 . C10 H20 O5 Si . C8 H8 . C7
H12 O2 . C5 H8 O3 . C5 H8 O2 . C5 H8 O2 . C3 H4 O2)x
CCI PMS

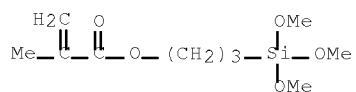
CRN 96478-09-0
CMF C18 H17 N3 O3



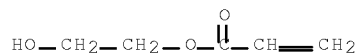
CRN 68548-08-3
CMF C14 H25 N O2



CRN 2530-85-0
CMF C10 H20 O5 Si

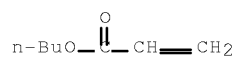


CRN 818-61-1
CMF C5 H8 O3



CRN 141-32-2
CMF C7 H12 O2

10/553,775-294324-EIC SEARCH



CM 8

CRN 140-88-5

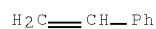
CMF C5 H8 O2



CM 9

CRN 100-42-5

CMF C8 H8



CM 10

CRN 80-62-6

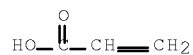
CMF C5 H8 O2



CM 11

CRN 79-10-7

CMF C3 H4 O2



RN 394251-96-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
2-propenoic acid, 2,2,6,6-tetramethyl-4-piperidinyl
2-methyl-2-propenoate and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate, compd. with N,N-diethylethanamine (9CI)

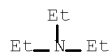
10/553,775-294324-EIC SEARCH

(CA INDEX NAME)

CM 1

CRN 121-44-8

CMF C6 H15 N



CM 2

CRN 394251-95-7

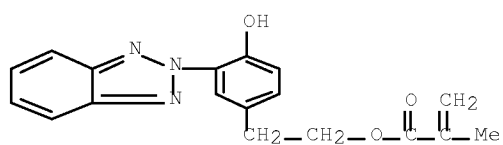
CMF (C18 H17 N3 O3 . C13 H23 N O2 . C10 H20 O5 Si . C8 H8 . C7 H12 O2 . C5 H8 O3 . C5 H8 O2 . C5 H8 O2 . C3 H4 O2) x

CCI PMS

CM 3

CRN 96478-09-0

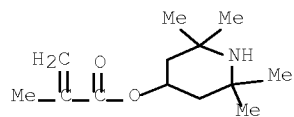
CMF C18 H17 N3 O3



CM 4

CRN 31582-45-3

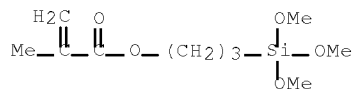
CMF C13 H23 N O2



CM 5

CRN 2530-85-0

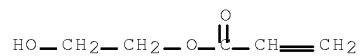
CMF C10 H20 O5 Si



CM 6

CRN 818-61-1

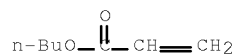
CMF C5 H8 O3



CM 7

CRN 141-32-2

CMF C7 H12 O2



CM 8

CRN 140-88-5

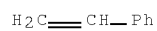
CMF C5 H8 O2



CM 9

CRN 100-42-5

CMF C8 H8



CM 10

CRN 80-62-6

CMF C5 H8 O2

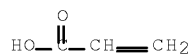


10/553,775-294324-EIC SEARCH

CM 11

CRN 79-10-7

CMF C3 H4 O2



IT 328404-57-5P 394251-88-8P 394251-91-3P
394251-95-7P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(weather-resistant anionic ~~electrodeposition~~ coating materials containing acrylic resins and melamine resins and light stabilizers)

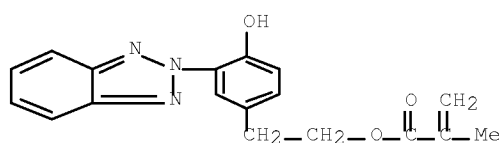
RN 328404-57-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate, 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate, 2-propenoic acid and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 96478-09-0

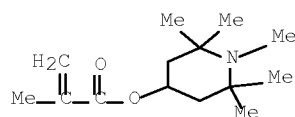
CMF C18 H17 N3 O3



CM 2

CRN 68548-08-3

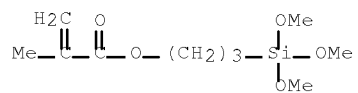
CMF C14 H25 N O2



CM 3

CRN 2530-85-0

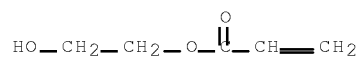
CMF C10 H20 O5 Si



CM 4

CRN 818-61-1

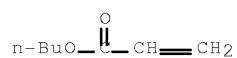
CMF C5 H8 O3



CM 5

CRN 141-32-2

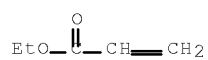
CMF C7 H12 O2



CM 6

CRN 140-88-5

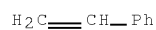
CMF C5 H8 O2



CM 7

CRN 100-42-5

CMF C8 H8



CM 8

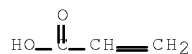
CRN 80-62-6

CMF C5 H8 O2



CM 9

CRN 79-10-7
CMF C3 H4 O2

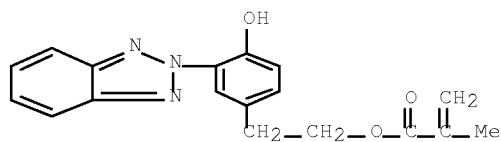


RN 394251-88-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate and
2-propenoic acid (9CI) (CA INDEX NAME)

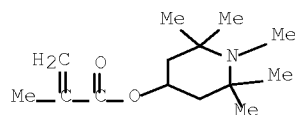
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



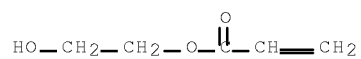
CM 2

CRN 68548-08-3
CMF C14 H25 N O2



CM 3

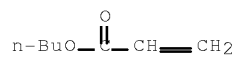
CRN 818-61-1
CMF C5 H8 O3



CM 4

CRN 141-32-2

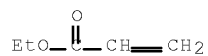
CMF C7 H12 O2



CM 5

CRN 140-88-5

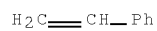
CMF C5 H8 O2



CM 6

CRN 100-42-5

CMF C8 H8



CM 7

CRN 80-62-6

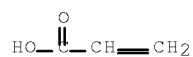
CMF C5 H8 O2



CM 8

CRN 79-10-7

CMF C3 H4 O2

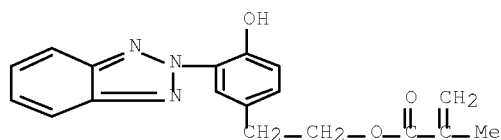


RN 394251-91-3 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-,
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
 with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
 2-propenoic acid and 2,2,6,6-tetramethyl-4-piperidiny1
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 96478-09-0

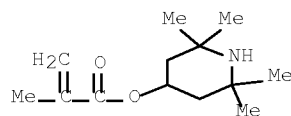
CMF C18 H17 N3 O3



CM 2

CRN 31582-45-3

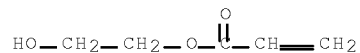
CMF C13 H23 N O2



CM 3

CRN 818-61-1

CMF C5 H8 O3

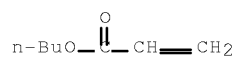


CM 4

CRN 141-32-2

CMF C7 H12 O2

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CM 5

CRN 140-88-5

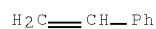
CMF C5 H8 O2



CM 6

CRN 100-42-5

CMF C8 H8



CM 7

CRN 80-62-6

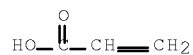
CMF C5 H8 O2



CM 8

CRN 79-10-7

CMF C3 H4 O2



RN 394251-95-7 HCAPLUS

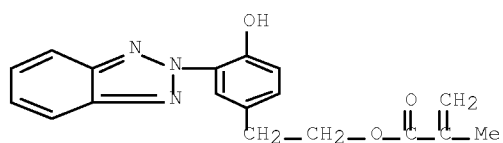
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
2-propenoic acid, 2,2,6,6-tetramethyl-4-piperidinyl
2-methyl-2-propenoate and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

10/553,775-294324-EIC SEARCH

CM 1

CRN 96478-09-0

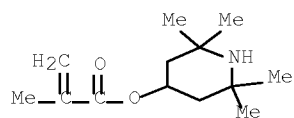
CMF C18 H17 N3 O3



CM 2

CRN 31582-45-3

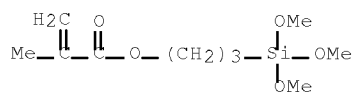
CMF C13 H23 N O2



CM 3

CRN 2530-85-0

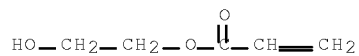
CMF C10 H20 O5 Si



CM 4

CRN 818-61-1

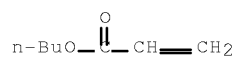
CMF C5 H8 O3



CM 5

CRN 141-32-2

CMF C7 H12 O2



CM 6

CRN 140-88-5

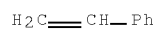
CMF C5 H8 O2



CM 7

CRN 100-42-5

CMF C8 H8



CM 8

CRN 80-62-6

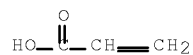
CMF C5 H8 O2



CM 9

CRN 79-10-7

CMF C3 H4 O2



IC ICM C09D175-04
 ICS C09D005-44; C09D133-00; C09D161-20
 CC 42-7 (Coatings, Inks, and Related Products)
 Section cross-reference(s): 56
 ST weather resistant anionic ~~electrodeposition~~ coating
 material; acrylic melamine ~~electrodeposition~~ coating
 light stabilizer; UV absorber acrylic melamine
~~electrodeposition~~ coating

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IT Electrodeposits
(anionic; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

IT Amines, uses
RL: MOA (Modifier or additive use); USES (Uses)
(hindered; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

IT Vinyl compounds, uses
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polymers; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

IT Polymerization
(radical; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

IT Aminoplasts
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(reaction products with acrylic resins and blocked polyisocyanates, Cymel 300 and Nikalac MX 430; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

IT Aminoplasts
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(reaction products with acrylic resins and blocked polyisocyanates; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

IT Crosslinking agents
Crosslinking catalysts
UV stabilizers
(weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

IT Coating materials
(weather-resistant; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

IT 9003-08-1DP, Cymel 300, reaction products with acrylic resins and blocked polyisocyanates
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(Cymel 300 and Nikalac MX 430; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

IT 104-15-4, p-Toluenesulfonic acid, uses
RL: CAT (Catalyst use); USES (Uses)
(weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

IT 822-06-0DP, Hexamethylene diisocyanate, derivs., reaction products with acrylic resins and melamine resins 73928-87-7DP, Duranate 24A90CX, reaction products with acrylic resins and melamine resins 394251-89-9DP, reaction products with blocked polyisocyanates and melamine resins 394251-92-4DP, reaction products with blocked polyisocyanates and melamine resins 394251-94-6DP, reaction products with blocked polyisocyanates and melamine resins 394251-96-8DP,

10/553,775-294324-EIC SEARCH

reaction products with blocked polyisocyanates and melamine resins
 RL: IMF (Industrial manufacture); POF (Polymer in formulation);
 PRP (Properties); TEM (Technical or engineered material use); PREP
 (Preparation); USES (Uses)
 (weather-resistant anionic electrodeposition coating
 materials containing acrylic resins and melamine resins and light
 stabilizers)

IT 328404-57-5P 394251-88-8P 394251-91-3P
 394251-95-7P

RL: IMF (Industrial manufacture); TEM (Technical or engineered
 material use); PREP (Preparation); USES (Uses)
 (weather-resistant anionic electrodeposition coating
 materials containing acrylic resins and melamine resins and light
 stabilizers)

L31 ANSWER 17 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2001:864997 HCAPLUS Full-text

DOCUMENT NUMBER: 136:14033

TITLE: Electrically conductive pastes and
 optical semiconductor devices
 manufactured by using them with excellent UV
 and weather resistance

INVENTOR(S): Shizuki, Hironori

PATENT ASSIGNEE(S): Toshiba Chemical Corp., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2001332124	A	20011130	JP 2000-149863	2000 0522

PRIORITY APPLN. INFO.: <-- JP 2000-149863 2000
 0522

<--

ED Entered STN: 30 Nov 2001

AB The pastes, useful for bonding blue LED chips to lead frames, contain organic binders,
 solvents and/or monomers, Ag-containing elec. conductive powders, and 0.1-10% (based on
 resin solids content) compds. having ≥1 benzotriazole structures and methacryloyl or
 hydroxyethyl groups. The compds. may be copolymd. with the monomers in advance. The
 powders may contain 5-20% TiO₂.

IT 153175-43-0, 2-(2'-Hydroxy-5'-methacryloxyethylphenyl)-2H-
 benzotriazole-methyl methacrylate copolymer

RL: MOA (Modifier or additive use); USES (Uses)

(UV absorber; elec. conductive pastes containing benzotriazole
 compds. for optical semiconductor devices
 with good UV and weather resistance)

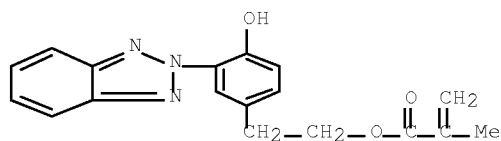
RN 153175-43-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
 with methyl 2-methyl-2-propenoate (CA INDEX NAME)

CM 1

CRN 96478-09-0

CMF C18 H17 N3 O3



CM 2

CRN 80-62-6
CMF C5 H8 O2

IC ICM H01B001-22
ICS C08K003-08; C08K003-22; C08K005-00; C08K005-3472; C08L101-00;
C09J004-06; H01L021-52; H05K003-32; C09J009-02; C09J011-04;
C09J011-06; C09J201-00; C08L033-14

CC 76-3 (Electric Phenomena)
Section cross-reference(s): 38, 73

ST elec conductive paste silver weather resistance; UV resistance
epoxy paste optical semiconductor; benzotriazole UV
absorber titania paste LED

IT Epoxy resins, uses
RL: PNU (Preparation, unclassified); TEM (Technical or engineered
material use); PREP (Preparation); USES (Uses)
(crosslinked, binder; elec. conductive pastes containing
benzotriazole compds. for optical semiconductor
devices with good UV and weather resistance)

IT Electrically conductive pastes
Electroluminescent devices
Optoelectronic semiconductor devices
UV stabilizers
(elec. conductive pastes containing benzotriazole compds. for
optical semiconductor devices with good UV
and weather resistance)

IT Phenolic resins, uses
RL: PNU (Preparation, unclassified); TEM (Technical or engineered
material use); PREP (Preparation); USES (Uses)
(epoxy, binder; elec. conductive pastes containing benzotriazole
compds. for optical semiconductor devices
with good UV and weather resistance)

IT Epoxy resins, uses
RL: PNU (Preparation, unclassified); TEM (Technical or engineered
material use); PREP (Preparation); USES (Uses)
(phenolic, binder; elec. conductive pastes containing benzotriazole
compds. for optical semiconductor devices
with good UV and weather resistance)

IT 153175-43-0, 2-(2'-Hydroxy-5'-methacryloxyethylphenyl)-2H-
benzotriazole-methyl methacrylate copolymer 196516-61-7
RL: MOA (Modifier or additive use); USES (Uses)
(UV absorber; elec. conductive pastes containing benzotriazole
compds. for optical semiconductor devices
with good UV and weather resistance)

IT 373599-19-0P, Celloxide 2021-GT 302-PG 207S-YL 983U copolymer
376366-31-3P, BRG 558-EOCN 103S-Epikote 1007 copolymer
RL: PNU (Preparation, unclassified); TEM (Technical or engineered
material use); PREP (Preparation); USES (Uses)

10/553,775-294324-EIC SEARCH

(binder; elec. conductive pastes containing benzotriazole compds.
for optical semiconductor devices with good
UV and weather resistance)

IT 7440-22-4, Silver, uses

RL: TEM (Technical or engineered material use); USES (Uses)
(elec. conductive pastes containing benzotriazole compds. for
optical semiconductor devices with good UV
and weather resistance)

IT 13463-67-7, Titanium oxide, uses

RL: TEM (Technical or engineered material use); USES (Uses)
(rutile-type; elec. conductive pastes containing benzotriazole
compds. for optical semiconductor devices
with good UV and weather resistance)

L31 ANSWER 18 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2001:563988 HCAPLUS Full-text

DOCUMENT NUMBER: 135:159968

TITLE: Electrochromic component

INVENTOR(S): Asano, Takeshi; Oshima, Shinji; Nishikitani,
Yoshinori

PATENT ASSIGNEE(S): Nisseki Mitsubishi Oil Corporation, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 22 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	
JP 2001209078	A	20010803	JP 2000-16929	2000 0126
			<--	
WO 2001055784	A1	20010802	WO 2001-JP455	2001 0124
			<--	
W: US				
RW: DE, FR, GB				
US 20030072071	A1	20030417	US 2002-205982	2002 0726
			<--	
US 6728022	B2	20040427		
PRIORITY APPLN. INFO.:			JP 2000-16929	A 2000 0126
			<--	
			WO 2001-JP455	A1 2001 0124
			<--	

ED Entered STN: 03 Aug 2001

AB The invention refers to a electrochromic device comprising an electrochromic polymer
and an organic compound with bipyridinium ion as an ~~cathodic~~ electrochromic structure,
and a metallocene as a ~~anodic~~ electrochromic structure, wherein the organic compound
may react with the polymer.

IT 352427-38-4

RL: DEV (Device component use); USES (Uses)
(electrochromic component)

RN 352427-38-4 HCAPLUS

CN 1-Propanone, 2-hydroxy-2-methyl-1-[4-(1-methylethyl)phenyl]-,
polymer with 2-(2H-benzotriazol-2-yl)-4-(1,1-dimethylethyl)phenol
and α -(2-methyl-1-oxo-2-propenyl)- ω -methoxypoly(oxy-

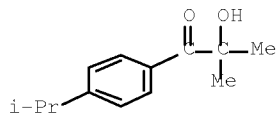
10/553,775-294324-EIC SEARCH

1,2-ethanediyl) (9CI) (CA INDEX NAME)

CM 1

CRN 69673-85-4

CMF C13 H18 O2

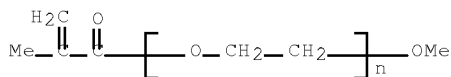


CM 2

CRN 26915-72-0

CMF (C2 H4 O)n C5 H8 O2

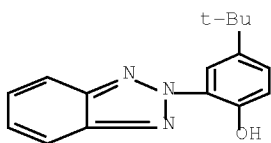
CCI PMS



CM 3

CRN 3147-76-0

CMF C16 H17 N3 O



IC ICM G02F001-15

ICS B60R001-04; C08F008-30; C08F008-42; C09K009-02

CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)

IT 1332-29-2, Tin oxide 2440-22-4,
2-(5-Methyl-2-hydroxyphenyl)benzotriazole 7440-05-3, Palladium,
uses 16731-68-3, 2-Undecylimidazole 50926-11-9, ITO
352427-34-0 352427-35-1 352427-37-3 352427-38-4
352427-39-5 352427-40-8 352427-41-9 352427-43-1
352430-76-3

RL: DEV (Device component use); USES (Uses)
(electrochromic component)

L31 ANSWER 19 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2001:324518 HCAPLUS Full-text

DOCUMENT NUMBER: 134:341657

TITLE: Water-soluble electrodeposition
coating compositions with good weather

10/553,775-294324-EIC SEARCH

INVENTOR(S): resistance
 Obata, Katsuya; Kishida, Katsuhiko
 PATENT ASSIGNEE(S): Honey Kasei K. K., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

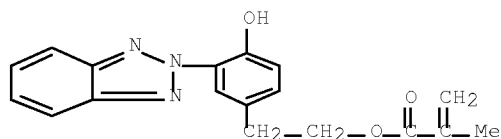
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001123107	A	20010508	JP 1999-338316	1999 1025

PRIORITY APPLN. INFO.: <--
 JP 1999-338316
 1999
 1025

ED Entered STN: 08 May 2001
 AB The compns. contain (A) 100 parts (meth)acrylic polymers prepared from UV-absorbing vinyl monomers 1-20, radical-scavenging vinyl monomers 1-20, F-containing vinyl monomers 1-15, CO₂H-containing vinyl monomers 3-15, OH-containing vinyl monomers 5-30, and (meth)acrylates 0-89 parts and (B) 10-100 parts amino resins. Thus, an aqueous solution containing 6:15:10:18:26:10:10:5 acrylic acid-2-hydroxyethyl acrylate-styrene-Bu acrylate-Me methacrylate-RUVA 93 [2-(2'-hydroxy-5'-methacryloxyethylphenyl)-2H-benzotriazole]-1,2,2,6,6-pentamethyl-4-piperidyl methacrylate-Famac (2-perfluorooctylethyl methacrylate) copolymer, Cymel 235 (melamine resin), and dimethylaminoethanol was ~~electrodeposited~~ on an Al plate to give a coating showing gloss 85% and gloss retention 100% after 3 cycles of accelerated weathering tests.
 IT 338405-66-6P, Acrylic acid-butyl acrylate-2-hydroxyethyl acrylate-methyl methacrylate-1,2,2,6,6-pentamethyl-4-piperidyl methacrylate-2-perfluorooctylethyl methacrylate-RUVA 93-styrene copolymer
 RL: IMF (Industrial manufacture); POF (Polymer in formulation);
 RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent);
 USES (Uses)
 (water-thinned ~~electrodeposition~~ coatings with good weather resistance)
 RN 338405-66-6 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-,
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, ethenylbenzene, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-methyl-2-propenoate, 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate and 2-propenoic acid (9CI) (CA INDEX NAME)

CM 1

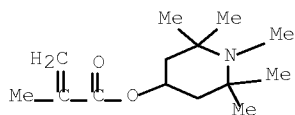
CRN 96478-09-0
 CMF C18 H17 N3 O3



10/553,775-294324-EIC SEARCH

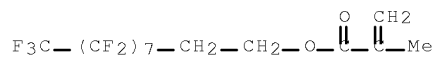
CM 2

CRN 68548-08-3
CMF C14 H25 N O2



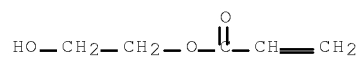
CM 3

CRN 1996-88-9
CMF C14 H9 F17 O2



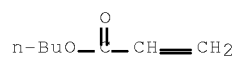
CM 4

CRN 818-61-1
CMF C5 H8 O3



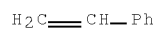
CM 5

CRN 141-32-2
CMF C7 H12 O2



CM 6

CRN 100-42-5
CMF C8 H8



10/553,775-294324-EIC SEARCH

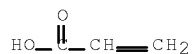
CM 7

CRN 80-62-6
CMF C5 H8 O2



CM 8

CRN 79-10-7
CMF C3 H4 O2



IT 338405-70-2F

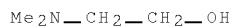
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(water-thinned ~~electrodeposition~~ coatings with good weather resistance)

RN 338405-70-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, ethenylbenzene, formaldehyde, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-methyl-2-propenoate, 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate, 2-propenoic acid and 1,3,5-triazine-2,4,6-triamine, compd. with 2-(dimethylamino)ethanol (9CI) (CA INDEX NAME)

CM 1

CRN 108-01-0
CMF C4 H11 N O

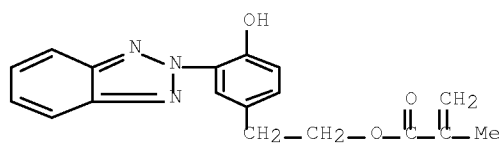


CM 2

CRN 338405-69-9
CMF (C18 H17 N3 O3 . C14 H25 N O2 . C14 H9 F17 O2 . C8 H8 . C7 H12 O2 . C5 H8 O3 . C5 H8 O2 . C3 H6 N6 . C3 H4 O2 . C H2 O)x
CCI PMS

CM 3

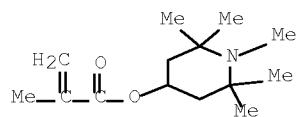
CRN 96478-09-0
CMF C18 H17 N3 O3



CM 4

CRN 68548-08-3

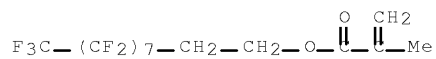
CMF C14 H25 N O2



CM 5

CRN 1996-88-9

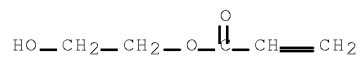
CMF C14 H9 F17 O2



CM 6

CRN 818-61-1

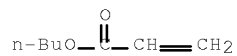
CMF C5 H8 O3



CM 7

CRN 141-32-2

CMF C7 H12 O2

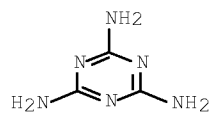


10/553,775-294324-EIC SEARCH

CM 8

CRN 108-78-1

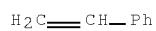
CMF C3 H6 N6



CM 9

CRN 100-42-5

CMF C8 H8



CM 10

CRN 80-62-6

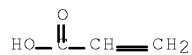
CMF C5 H8 O2



CM 11

CRN 79-10-7

CMF C3 H4 O2



CM 12

CRN 50-00-0

CMF C H2 O



IC ICM C09D157-08

10/553,775-294324-EIC SEARCH

ICS C09D005-44; C09D157-10; C09D161-20
 CC 42-7 (Coatings, Inks, and Related Products)
 ST ~~electrodeposition~~ acrylic coating aminoplast crosslinked
 weatherability; melamine resin crosslinked acrylic
~~electrodeposition~~ coating; methylaminoethanol salt acrylic
 polymer aminoplast ~~electrodeposit~~
 IT Aminoplasts
 RL: POF (Polymer in formulation); RCT (Reactant); RACT (Reactant
 or reagent); USES (Uses)
 (crosslinking agents; water-thinned ~~electrodeposition~~
 coatings with good weather resistance)
 IT Coating materials
 (water-soluble; water-thinned ~~electrodeposition~~ coatings
 with good weather resistance)
 IT ~~Electrodeposits~~
 (water-thinned ~~electrodeposition~~ coatings with good
 weather resistance)
 IT Coating materials
 (weather-resistant; water-thinned ~~electrodeposition~~
 coatings with good weather resistance)
 IT 338405-66-6F, Acrylic acid-butyl acrylate-2-hydroxyethyl
 acrylate-methyl methacrylate-1,2,2,6,6-pentamethyl-4-piperidyl
 methacrylate-2-perfluorooctylethyl methacrylate-RUVA 93-styrene
 copolymer
 RL: IMF (Industrial manufacture); POF (Polymer in formulation);
 RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent);
 USES (Uses)
 (water-thinned ~~electrodeposition~~ coatings with good
 weather resistance)
 IT 338405-70-2F
 RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical
 or engineered material use); PREP (Preparation); USES (Uses)
 (water-thinned ~~electrodeposition~~ coatings with good
 weather resistance)

L31 ANSWER 20 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2001:174226 HCAPLUS Full-text
 DOCUMENT NUMBER: 134:209402
 TITLE: Acrylic polymer-based anionic
~~electrodeposition~~ compositions
 INVENTOR(S): Yokoyama, Tetsuya; Kamikado, Koji; Hirano,
 Koji; Mizoguchi, Yoshitaka
 PATENT ASSIGNEE(S): Kansai Paint Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: ~~Patent~~
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	
JP 2001064568	A	20010313	JP 1999-238166	1999 0825

PRIORITY APPLN. INFO.: <--
 JP 1999-238166
 1999
 0825
 <--

ED Entered STN: 14 Mar 2001

AB The title compns., giving coated products with good appearance and weather resistance,
 comprise (a) water-dispersible vinyl copolymers having alkoxy silyl groups on the side
 chains (e.g., acrylic acid-Bu acrylate-Et acrylate-2-hydroxyethyl acrylate- γ -
 methacryloxypropyltrimethoxysilane-Me methacrylate-styrene copolymer) or having alkoxy

10/553,775-294324-EIC SEARCH

silyl monomers containing benzotriazole- and/or hindered amino-containing acrylic monomers (e.g., acrylic acid-Bu acrylate-Et acrylate-FA 711MM-2-hydroxyethyl acrylate-γ-methacryloxypropyltrimethoxysilane-Me methacrylate-RUVA 93-styrene copolymer) with acid-value 15-150 mg-KOH/g and OH-value 30-200 mg-KOH/g 40-84, (b) vinyl copolymers containing benzotriazole- and/or hindered amino-containing acrylic monomers with acid-value <14 mg-KOH/g (e.g., Bu acrylate-Bu methacrylate-2-ethylhexyl methacrylate-FA 711MM-2-hydroxyethyl methacrylate-RUVA 93 copolymer) 0.1-20, and (c) crosslinking agents (e.g., melamine resin) 15-50%, providing SP value of (b) is 0.3-1.5 smaller than that of (a).

IT 328404-57-5 328404-59-7 328404-61-1
328404-63-3

RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(acrylic polymer-based anionic electrodeposition compns.)

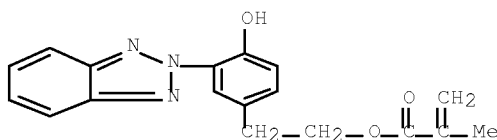
RN 328404-57-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate,
2-propenoic acid and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 96478-09-0

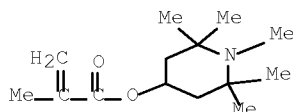
CMF C18 H17 N3 O3



CM 2

CRN 68548-08-3

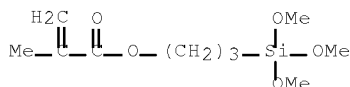
CMF C14 H25 N O2



CM 3

CRN 2530-85-0

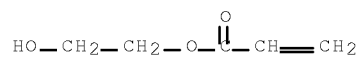
CMF C10 H20 O5 Si



CM 4

CRN 818-61-1

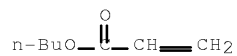
CMF C5 H8 O3



CM 5

CRN 141-32-2

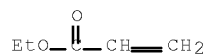
CMF C7 H12 O2



CM 6

CRN 140-88-5

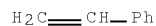
CMF C5 H8 O2



CM 7

CRN 100-42-5

CMF C8 H8



CM 8

CRN 80-62-6

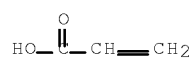
CMF C5 H8 O2



10/553,775-294324-EIC SEARCH

CM 9

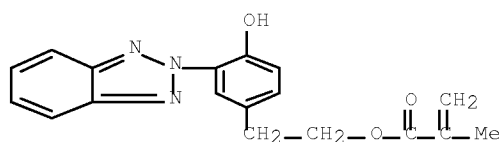
CRN 79-10-7
CMF C3 H4 O2



RN 328404-59-7 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-methyl-2-propenoate, butyl 2-propenoate, 2-ethylhexyl
2-methyl-2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate and
1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

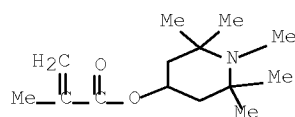
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



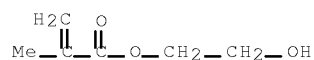
CM 2

CRN 68548-08-3
CMF C14 H25 N O2



CM 3

CRN 868-77-9
CMF C6 H10 O3

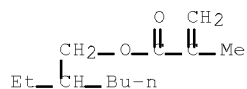


10/553,775-294324-EIC SEARCH

CM 4

CRN 688-84-6

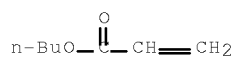
CMF C12 H22 O2



CM 5

CRN 141-32-2

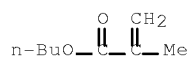
CMF C7 H12 O2



CM 6

CRN 97-88-1

CMF C8 H14 O2



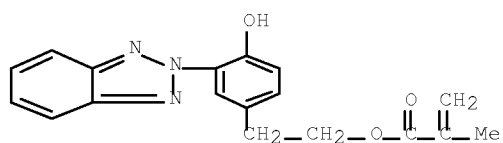
RN 328404-61-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
 with butyl 2-methyl-2-propenoate, butyl 2-propenoate, 2-ethylhexyl
 2-methyl-2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate,
 methyl 2-methyl-2-propenoate and
 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate (9CI)
 (CA INDEX NAME)

CM 1

CRN 96478-09-0

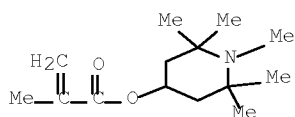
CMF C18 H17 N3 O3



10/553,775-294324-EIC SEARCH

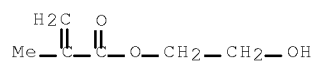
CM 2

CRN 68548-08-3
CMF C14 H25 N O2



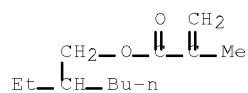
CM 3

CRN 868-77-9
CMF C6 H10 O3



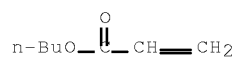
CM 4

CRN 688-84-6
CMF C12 H22 O2



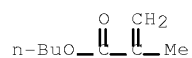
CM 5

CRN 141-32-2
CMF C7 H12 O2



CM 6

CRN 97-88-1
CMF C8 H14 O2



10/553,775-294324-EIC SEARCH

CM 7

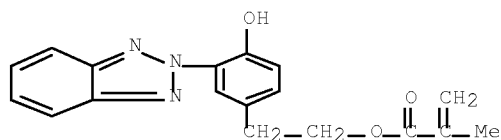
CRN 80-62-6
CMF C5 H8 O2



RN 328404-63-3 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-methyl-2-propenoate, butyl 2-propenoate, 2-ethylhexyl
2-methyl-2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate and
methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

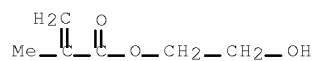
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



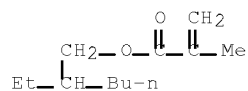
CM 2

CRN 868-77-9
CMF C6 H10 O3



CM 3

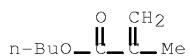
CRN 688-84-6
CMF C12 H22 O2



CM 4

CRN 141-32-2
CMF C7 H12 O2

CM 5

CRN 97-88-1
CMF C8 H14 O2

CM 6

CRN 80-62-6
CMF C5 H8 O2

IC ICM C09D133-00
ICS C09D005-44; C09D139-04; C09D161-28; C09D175-04
CC 42-7 (Coatings, Inks, and Related Products)
Section cross-reference(s): 76
ST acrylic polymer anionic electrodeposition weather
resistance; appearance acrylic polymer anionic
electrodeposition; benzotriazole acrylic polymer anionic
electrodeposition; hindered amino acrylic polymer anionic
electrodeposition
IT Electrodeposition
(acrylic polymer-based anionic electrodeposition
compns.)
IT Aminoplasts
RL: MOA (Modifier or additive use); USES (Uses)
(crosslinking agents; acrylic polymer-based anionic
electrodeposition compns.)
IT Crosslinking agents
(melamine resin; acrylic polymer-based anionic
electrodeposition compns.)
IT Coating materials
(weather-resistant; acrylic polymer-based anionic
electrodeposition compns.)
IT 92598-34-0 328404-57-5 328404-59-7
328404-61-1 328404-63-3
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical
or engineered material use); USES (Uses)
(acrylic polymer-based anionic electrodeposition

10/553,775-294324-EIC SEARCH

compns.)
 IT 9003-08-1, Melamine resin
 RL: MOA (Modifier or additive use); USES (Uses)
 (crosslinking agents; acrylic polymer-based anionic
 electrodeposition compns.)

L31 ANSWER 21 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2000:181094 HCAPLUS Full-text

DOCUMENT NUMBER: 132:209229

TITLE: Aqueous acrylic electrodeposition
 coating compositions with storage stability
 and weather resistance

INVENTOR(S): Sauchi, Yasuyuki; Ishii, Hiroaki; Kayamori,
 Satoshi

PATENT ASSIGNEE(S): Toa Gosei Chemical Industry Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 8 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	
JP 2000080310	A	20000321	JP 1998-265762	1998 0904

PRIORITY APPLN. INFO.: <--
 JP 1998-265762
 1998
 0904

ED Entered STN: 21 Mar 2000

AB Title compns., useful for Al substrates, contain aminoplasts and (partially)
 neutralized acrylic polymers prepared from alkyl (meth)acrylates, COOH-containing vinyl
 compds., OH-containing vinyl compds., UV-absorbing vinyl compds. and other monomers.
 An aqueous composition containing acrylic acid-styrene-Bu acrylate-2-hydroxyethyl
 acrylate-methacrylic acid-Me methacrylate-RUVA 93 copolymer, Cymel 235, organic Al
 compds., and dimethylethanolamine showed good storage stability at room temperature for
 3 days and was electrodeposited on an Al plate to form a film with gloss retention
 82.4% after 4,000 h under sunshine weatherometer.

IT 260389-73-99, Acrylic acid-butyl acrylate-2-hydroxyethyl
 acrylate-methacrylic acid-methyl methacrylate-RUVA 93-styrene
 copolymer dimethylethanolamine salt

RL: IMF (Industrial manufacture); POF (Polymer in formulation);

TEM (Technical or engineered material use); PREP (Preparation);

USES (Uses)

(UV-absorbing acrylic resin-based aqueous electrodeposition
 coatings with storage stability and weather resistance)

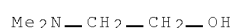
RN 260389-73-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl
 2-methyl-2-propenoate, butyl 2-propenoate, ethenylbenzene,
 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate and
 2-propenoic acid, compd. with 2-(dimethylamino)ethanol (9CI) (CA
 INDEX NAME)

CM 1

CRN 108-01-0

CMF C4 H11 N O



10/553,775-294324-EIC SEARCH

CM 2

CRN 260389-72-8

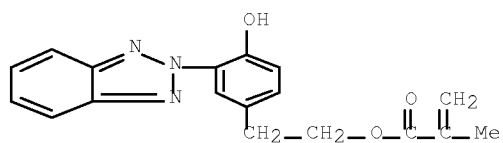
CMF (C18 H17 N3 O3 . C8 H8 . C7 H12 O2 . C5 H8 O3 . C5 H8 O2 . C4 H6 O2 . C3 H4 O2) x

CCI PMS

CM 3

CRN 96478-09-0

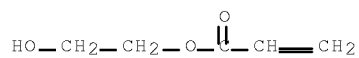
CMF C18 H17 N3 O3



CM 4

CRN 818-61-1

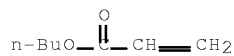
CMF C5 H8 O3



CM 5

CRN 141-32-2

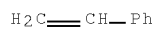
CMF C7 H12 O2



CM 6

CRN 100-42-5

CMF C8 H8



10/553,775-294324-EIC SEARCH

CM 7

CRN 80-62-6

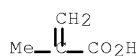
CMF C5 H8 O2



CM 8

CRN 79-41-4

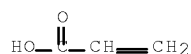
CMF C4 H6 O2



CM 9

CRN 79-10-7

CMF C3 H4 O2



- IC ICM C09D005-44
ICS C09D133-06; C09D133-14; C09D139-04; C09D161-20
- CC 42-7 (Coatings, Inks, and Related Products)
Section cross-reference(s): 56
- ST aq acrylic ~~electrodeposition~~ coating storage stability;
weather resistance aq acrylic ~~electrodeposition~~ coating;
UV absorbing methacrylate polymer aq ~~electrodeposition~~
coating
- IT ~~Electrodeposits~~
(UV-absorbing acrylic resin-based aqueous ~~electrodeposition~~
coatings with storage stability and weather resistance)
- IT Acrylic polymers, uses
RL: IMF (Industrial manufacture); POF (Polymer in formulation);
TEM (Technical or engineered material use); PREP (Preparation);
USES (Uses)
(UV-absorbing acrylic resin-based aqueous ~~electrodeposition~~
coatings with storage stability and weather resistance)
- IT Aminoplasts
RL: POF (Polymer in formulation); TEM (Technical or engineered
material use); USES (Uses)
(UV-absorbing acrylic resin-based aqueous ~~electrodeposition~~
coatings with storage stability and weather resistance)
- IT Windows
(frames, Al-made, as substrates; UV-absorbing acrylic
resin-based aqueous ~~electrodeposition~~ coatings with
storage stability and weather resistance)
- IT 250389-73-32, Acrylic acid-butyl acrylate-2-hydroxyethyl
acrylate-methacrylic acid-methyl methacrylate-RUVA 93-styrene

10/553,775-294324-EIC SEARCH

copolymer dimethylethanolamine salt

RL: IMF (Industrial manufacture); POF (Polymer in formulation);

TEM (Technical or engineered material use); PREP (Preparation);

USES (Uses)

(UV-absorbing acrylic resin-based aqueous ~~electrodeposition~~
coatings with storage stability and weather resistance)

IT 9003-08-1, Cymel 235

RL: POF (Polymer in formulation); TEM (Technical or engineered
material use); USES (Uses)(UV-absorbing acrylic resin-based aqueous ~~electrodeposition~~
coatings with storage stability and weather resistance)

IT 7429-90-5, Aluminum, miscellaneous

RL: MSC (Miscellaneous)

(substrates; UV-absorbing acrylic resin-based aqueous
~~electrodeposition~~ coatings with storage stability and
weather resistance)

L31 ANSWER 22 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 1998:685250 HCAPLUS Full-text

DOCUMENT NUMBER: 130:8862

TITLE: ~~Electrophotographic~~
~~photoreceptor~~ containing aromatic
polycarbonate and electrophotographic
apparatusINVENTOR(S): Takekawa, Ichiro; Nukata, Hidemi; Nakamura,
Hiroshi; Miyamoto, Masakiko

PATENT ASSIGNEE(S): Fuji Xerox Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 27 pp.

CODEN: JKXXAF

DOCUMENT TYPE: ~~Patent~~

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 10282690	A	19981023	JP 1997-88379	

1997

0407

PRIORITY APPLN. INFO.:

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JP 1997-88379

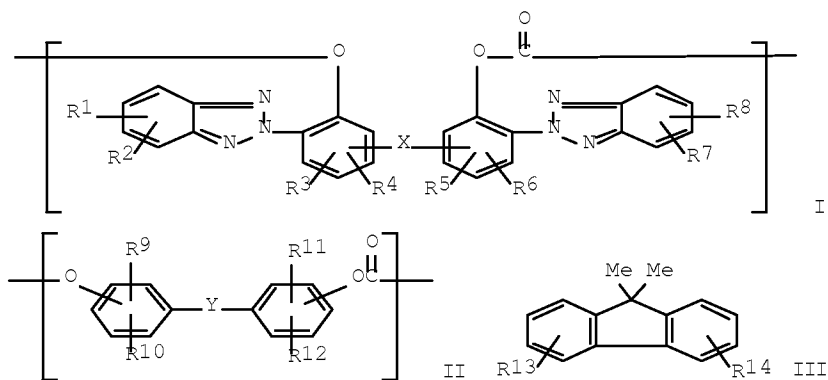
1997

0407

OTHER SOURCE(S): MARPAT 130:8862

ED Entered STN: 29 Oct 1998

GI



AB The title photoreceptor comprises a conductive support coated with a photosensitive layer containing a polycarbonate copolymer resin having repeating units I and II [R1-12 = H, halo, C1-5 alkyl, C6-12 aryl, C2-5 alkenyl, C1-5 alkoxy, C7-17 aralkyl (these groups may be substituted by C1-5 alkyl, C1-5 alkenyl, C1-5 alkoxy, halo, or dimethylpolysiloxy group); X = O(CH2O)a, (CH2O)aCO2(CH2)bOCO(CH2)c, (CH2)a, (CH2)aCO(CH2)bCO(CH2)c, OCOCH:CHC6H4-p-CH:CHCO2, CH2CONHC6H4CONHCH2 (a, b, c = 0-20); Y = (CR13R14)c(CH2)d(CR15R16)e, S, SO2, O, (CH2)f(SiR13R14O)gSiR13R14(CH2)f, III, CR13R14C6H4CR15R16, 1,1-cyclohexyl, CMe2; R13-16 = H, halo, C1-5 alkyl, C6-12 aryl, C2-5 alkenyl, C1-5 alkoxy, C7-17 aralkyl (these groups may be substituted by C1-5 alkyl, C1-5 alkenyl, C1-5 alkoxy, halo, or dimethylpolysiloxy group); c, e, f = 0-20; d, g = 1-100] and a triphenylamine compound. An electrophotog. apparatus using the photoreceptor is also claimed. The photoreceptor shows high abrasion resistance and durability in repeated use and provides high quality images without fog and black spot.

IT 192209-77-1 215809-90-8 215810-06-3

RL: DEV (Device component use); USES (Uses)

(electrophotog. apparatus having photoreceptor containing polycarbonate and triphenylamine)

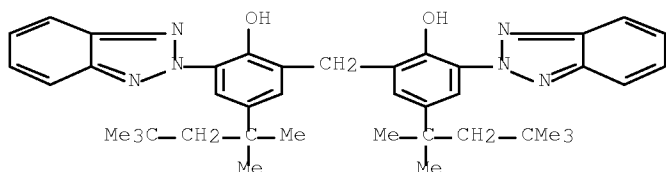
RN 192209-77-1 HCAPLUS

CN Carbonic acid, polymer with
2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-(1,1,3,3-tetramethylbutyl)phenol] and 4,4'-(1-methylethylidene)bis[phenol]
(9CI) (CA INDEX NAME)

CM 1

CRN 103597-45-1

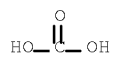
CMF C41 H50 N6 O2



CM 2

CRN 463-79-6

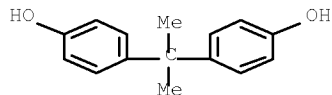
CMF C H2 O3



CM 3

CRN 80-05-7

CMF C15 H16 O2



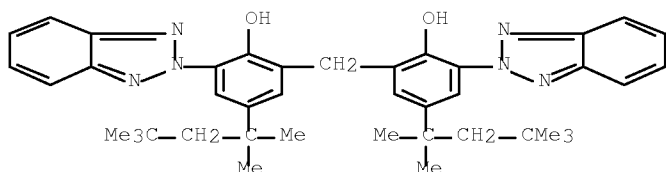
RN 215809-90-8 HCAPLUS

CN Carbonic acid, polymer with 4,4'-cyclohexylidenebis[phenol] and 2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-(1,1,3,3-tetramethylbutyl)phenol] (9CI) (CA INDEX NAME)

CM 1

CRN 103597-45-1

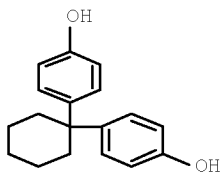
CMF C41 H50 N6 O2



CM 2

CRN 843-55-0

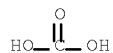
CMF C18 H20 O2



CM 3

CRN 463-79-6

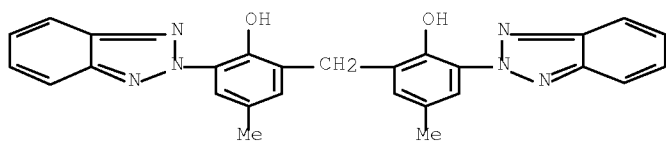
CMF C H2 O3



RN 215810-06-3 HCAPLUS
 CN Carbonic acid, polymer with
 2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-methylphenol] and
 4,4'-(1-methylethylidene)bis[phenol] (9CI) (CA INDEX NAME)

CM 1

CRN 30653-05-5
 CMF C27 H22 N6 O2



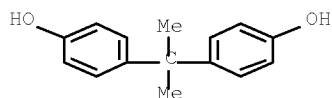
CM 2

CRN 463-79-6
 CMF C H2 O3



CM 3

CRN 80-05-7
 CMF C15 H16 O2



IC ICM G03G005-05
 ICS C08G064-12; C08K005-17; C08L069-00; G03G005-06
 CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and
 Other Reprographic Processes)
 ST arom polycarbonate phenylamine electrophotog
 photoreceptor app
 IT Electrophotographic apparatus
 Electrophotographic photoconductors (
 photoreceptors)

10/553,775-294324-EIC SEARCH

(electrophotog. apparatus having photoreceptor containing polycarbonate and triphenylamine)

IT 65181-78-4, N,N'-Diphenyl-N,N'-bis(3-methylphenyl)-(1,1'-biphenyl)-4,4'-diamine 105465-13-2 111153-52-7 165320-08-1

RL: DEV (Device component use); USES (Uses)

(charge transporter; electrophotog. apparatus having photoreceptor containing polycarbonate and triphenylamine)

IT 192209-77-1 215809-90-8 215810-06-3

RL: DEV (Device component use); USES (Uses)

(electrophotog. apparatus having photoreceptor containing polycarbonate and triphenylamine)

L31 ANSWER 23 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 1998:402375 HCAPLUS Full-text

DOCUMENT NUMBER: 129:96382

ORIGINAL REFERENCE NO.: 129:19872h,19873a

TITLE: UV-protected syndiotactic polystyrene overlay films

INVENTOR(S): Ojeda, Jaime R.

PATENT ASSIGNEE(S): Minnesota Mining and Manufacturing Co., USA

SOURCE: PCT Int. Appl., 35 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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WO 9825763	A1	19980618	WO 1997-US6992	

1997

0425

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W: AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GE, GH, HU, IL, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ, TM, TR, TT, UA, UG, UZ, VN, YU

RW: GH, KE, LS, MW, SD, SZ, UG, AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG

US 5981076	A	19991109	US 1996-761912	
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1996

1209

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CA 2274774	C	19980618	CA 1997-2274774	
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1997

0425

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CA 2274774	A1	19980618		
AU 9729926	A	19980703	AU 1997-29926	

1997

0425

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EP 942830	A1	19990922	EP 1997-924524	
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1997

0425

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EP 942830	B1	20030625		
R: DE, FR, GB, IT				
CN 1244156	A	20000209	CN 1997-181241	

1997

0425

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CN 1096939	C	20021225		
JP 2001505835	T	20010508	JP 1998-526610	

10/553,775-294324-EIC SEARCH

1997
0425

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JP 4060371 B2 20080312
US 6120901 A 20000919 US 1998-989651998
0618

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KR 2000057453 A 20000915 KR 1999-705086

1999
0608

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JP 2007045158 A 20070222 JP 2006-242850

2006
0907

PRIORITY APPLN. INFO.:

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US 1996-761912 A

1996
1209

<--

JP 1998-526610 A3

1997
0425

<--

WO 1997-US6992 W

1997
0425

<--

ED Entered STN: 01 Jul 1998

AB The film, having good dimensional stability, comprises a 1st layer comprising syndiotactic polystyrene and a 2nd layer comprising a UV-blocking material, optionally, PMMA, and optionally, a bonding and a 3rd layer disposed between the 1st and 2nd layers. Thus, coating Sorbalite OU (UV-ray resistant aqueous polyurethane) containing Triton TX 100 latex solution (solid content 15.6%) on a syndiotactic p-methylstyrene-styrene copolymer film gave a coated film with good UV-ray resistance.

IT 209329-55-5 209329-56-6

RL: PRP (Properties); TEM (Technical or engineered material use);
USES (Uses)

(UV-blocking material; UV-protected syndiotactic polystyrene
overlay films)

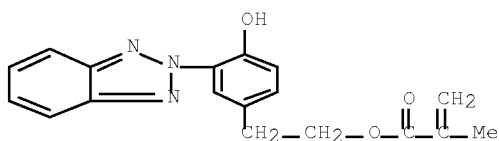
RN 209329-55-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with methyl 2-methyl-2-propenoate, 2-propenoic acid and
3-(trimethoxysilyl)propyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 96478-09-0

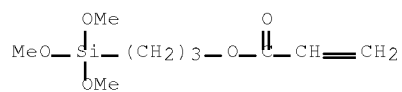
CMF C18 H17 N3 O3



CM 2

CRN 4369-14-6

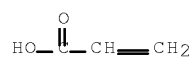
CMF C9 H18 O5 Si



CM 3

CRN 80-62-6
CMF C5 H8 O2

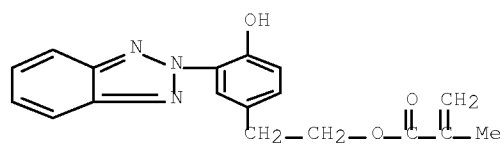
CM 4

CRN 79-10-7
CMF C3 H4 O2

RN 209329-56-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with 2-propenoic acid and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

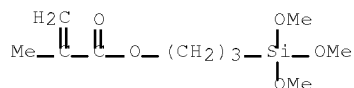
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3

CM 2

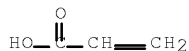
CRN 2530-85-0
CMF C10 H20 O5 Si

10/553,775-294324-EIC SEARCH



CM 3

CRN 79-10-7
CMF C3 H4 O2



IC ICM B32B027-28
ICS B32B027-18; C08K003-22; C08K005-132; C08K005-3475
CC 38-3 (Plastics Fabrication and Uses)
IT ~~Electrode~~ reaction
(photochem.; UV-protected syndiotactic polystyrene overlay films)
IT 79-10-7D, 2-Propenoic acid, polymers, uses 9002-84-0, PTFE 9011-14-7, PMMA 9017-68-9, Acrylic acid-isooctyl acrylate copolymer 57460-65-8, Ethyl acrylate-isopropenyloxazoline-methyl methacrylate copolymer 209329-55-5 209329-56-6 209534-17-8, Sorbalite OU
RL: PRP (Properties); TEM (Technical or engineered material use);
USES (Uses)
(UV-blocking material; UV-protected syndiotactic polystyrene overlay films)
REFERENCE COUNT: 12 THERE ARE 12 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L31 ANSWER 24 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 1998:352206 HCAPLUS Full-text
DOCUMENT NUMBER: 129:82813
ORIGINAL REFERENCE NO.: 129:17079a
TITLE: ~~Electrodeposition~~ coating compositions having excellent resistance to corrosion, hot water, and weather
INVENTOR(S): Tanimoto, Motoki; Inoue, Tsuyoshi
PATENT ASSIGNEE(S): Nippon Paint Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF
DOCUMENT TYPE: ~~Patent~~
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 10147734	A	19980602	JP 1996-306665	1996 1118

PRIORITY APPLN. INFO.: <-- JP 1996-306665 1996
1118
<--

10/553,775-294324-EIC SEARCH

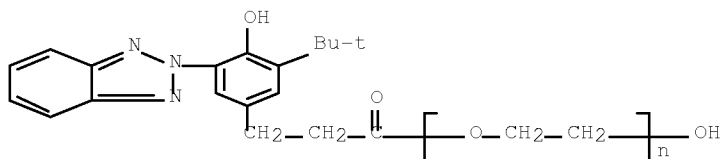
ED Entered STN: 10 Jun 1998

AB The coating compns. contain (A) low mol.-weight polyols having primary OH and prepared by reacting (i) cycloaliph. epoxy resins with mol. weight 400-3000 and epoxy equiv 200-1500 with (ii) monocarboxylic acids, preferably benzoic acid (I), dimethylolpropionic acid, dimethylolbutanoic acid, or glycolic acid, and further reacting the remaining OH with (iii) ε-caprolactone (II) and (B) crosslinking agents. The coatings may contain (C) ionic polymer polyols with mol. weight 3000-200,000 and OH value 15-120 and (D) 0.5-10 parts (per A + B 100 parts) UV absorbers as optional components. The coatings are especially suitable for automobiles. Thus, 207.1 parts a polyol (solid 75%, prepared from Sun-Tohto ST 3000, bisphenol A, I, and II at ratio 921.6:228.0:237.9:399.0), 820.4 parts 170.0:90.0:250.0:317.0:37.0:136.0:92.6 glycidyl methacrylate-2-hydroxyethyl methacrylate-styrene-Et methacrylate-Bu acrylate-Bu methacrylate copolymer N-methylethanolamine salt (solid 70.7%), 392.9 parts a crosslinking agent (prepared from IPDI, 2-ethylhexanol, and trimethylolpropane at ratio 371.4:218.0:75.0), 20.0 parts Tinuvin 1130, 10.0 parts ADK Stab LA 62 were mixed, neutralized with 19.1 parts glacial AcOH, thinned with 1391.6 parts H2O, and further mixed with 130.4 parts pigment paste and 2484.5 parts H2O to give a .apprx.20%-solids cationic ~~electrodeposition~~ coating.

IT 104810-48-2, Tinuvin 1130
 RL: MOA (Modifier or additive use); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
 (water-thinned epoxy compns. for automobile ~~electrodeposition~~ coatings with corrosion, hot water and weather resistance)

RN 104810-48-2 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α-[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]-ω-hydroxy-
 (CA INDEX NAME)



IC ICM C09D005-44
 ICS C09D005-44; C09D005-32; C09D007-12; C09D133-02; C09D133-06;
 C09D167-04; C09D175-04

CC 42-9 (Coatings, Inks, and Related Products)

ST anticorrosive ~~electrodeposition~~ coating epoxy resin;
 storage stable epoxy resin ~~electrodeposition~~ coating;
 water resistance epoxy resin ~~electrodeposition~~ coating;
 cycloaliph epoxy resin monocarboxylic acid polyether; caprolactone
 cycloaliph epoxy resin polyether; hydrogenated bisphenol A epoxy
 resin coating; automobile coating epoxy resin anticorrosive
~~electrodeposition~~

IT Coating materials
 Coating materials
 (anticorrosive, water-thinned; water-thinned epoxy compns. for
 automobile ~~electrodeposition~~ coatings with corrosion,
 hot water and weather resistance)

IT Polyurethanes, uses
 RL: IMF (Industrial manufacture); MOA (Modifier or additive use);
 PRP (Properties); TEM (Technical or engineered material use); PREP
 (Preparation); USES (Uses)
 (crosslinking agent; water-thinned epoxy compns. for automobile
~~electrodeposition~~ coatings with corrosion, hot water
 and weather resistance)

IT Aminoplasts
 RL: MOA (Modifier or additive use); PRP (Properties); TEM

10/553,775-294324-EIC SEARCH

(Technical or engineered material use); USES (Uses)
 (crosslinking agent; water-thinned epoxy compns. for automobile
~~electrodeposition~~ coatings with corrosion, hot water
 and weather resistance)

IT Polyesters, uses
 Polyesters, uses
 RL: IMF (Industrial manufacture); POF (Polymer in formulation);
 PRP (Properties); TEM (Technical or engineered material use); PREP
 (Preparation); USES (Uses)
 (epoxy; water-thinned epoxy compns. for automobile
~~electrodeposition~~ coatings with corrosion, hot water
 and weather resistance)

IT Epoxy resins, uses
 Epoxy resins, uses
 RL: IMF (Industrial manufacture); POF (Polymer in formulation);
 PRP (Properties); TEM (Technical or engineered material use); PREP
 (Preparation); USES (Uses)
 (polyester-; water-thinned epoxy compns. for automobile
~~electrodeposition~~ coatings with corrosion, hot water
 and weather resistance)

IT Coating materials
 Coating materials
 (water-resistant, water-thinned; water-thinned epoxy compns.
 for automobile ~~electrodeposition~~ coatings with
 corrosion, hot water and weather resistance)

IT ~~Electrodeposits~~
 UV stabilizers
 (water-thinned epoxy compns. for automobile
~~electrodeposition~~ coatings with corrosion, hot water
 and weather resistance)

IT Coating materials
 Coating materials
 (water-thinned, weather-resistant; water-thinned epoxy compns.
 for automobile ~~electrodeposition~~ coatings with
 corrosion, hot water and weather resistance)

IT 77-99-6DP, reaction products with 2-ethylhexanol and IPDI
 104-76-7DP, 2-Ethylhexanol, reaction products with IPDI and
 trimethylolpropane 4098-71-9DP, reaction products with
 2-ethylhexanol and trimethylolpropane
 RL: IMF (Industrial manufacture); MOA (Modifier or additive use);
 PRP (Properties); TEM (Technical or engineered material use); PREP
 (Preparation); USES (Uses)
 (crosslinking agent; water-thinned epoxy compns. for automobile
~~electrodeposition~~ coatings with corrosion, hot water
 and weather resistance)

IT 9003-08-1, Cymel 235 118232-50-1, Coatax WE 804
 RL: MOA (Modifier or additive use); PRP (Properties); TEM
 (Technical or engineered material use); USES (Uses)
 (crosslinking agent; water-thinned epoxy compns. for automobile
~~electrodeposition~~ coatings with corrosion, hot water
 and weather resistance)

IT 208987-38-6P, Butyl acrylate-butyl methacrylate-ethyl
 methacrylate-glycidyl methacrylate-2-hydroxyethyl
 methacrylate-styrene copolymer, N-methylethanolamine salt
 208987-40-0P 208987-41-1P 208987-42-2P, Acrylamide-acrylic
 acid-butyl acrylate-butyl methacrylate-ethyl
 methacrylate-2-hydroxyethyl methacrylate-methacrylic acid-styrene
 copolymer 209113-45-1P 209113-46-2P 209225-21-8P
 RL: IMF (Industrial manufacture); POF (Polymer in formulation);
 PRP (Properties); TEM (Technical or engineered material use); PREP
 (Preparation); USES (Uses)
 (water-thinned epoxy compns. for automobile
~~electrodeposition~~ coatings with corrosion, hot water
 and weather resistance)

IT 104810-48-2, Tinuvin 1130 107119-91-5, ADK Stab LA 62
 RL: MOA (Modifier or additive use); PRP (Properties); TEM
 (Technical or engineered material use); USES (Uses)

10/553,775-294324-EIC SEARCH

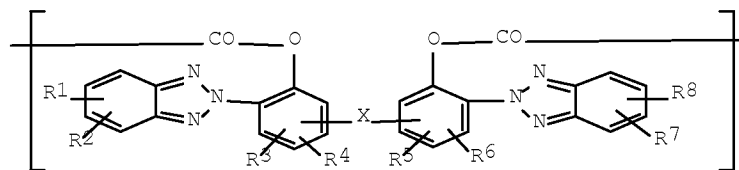
(water-thinned epoxy compns. for automobile
electrodeposition coatings with corrosion, hot water
and weather resistance)

L31 ANSWER 25 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 1997:139984 HCAPLUS Full-text
DOCUMENT NUMBER: 126:164198
ORIGINAL REFERENCE NO.: 126:31615a,31618a
TITLE: Copolycarbonate suitable for
electrophotographic
photoreceptor binder and its
preparation
INVENTOR(S): Ogawa, Noryoshi; Tajima, Jun
PATENT ASSIGNEE(S): Mitsubishi Gas Chemical Co., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

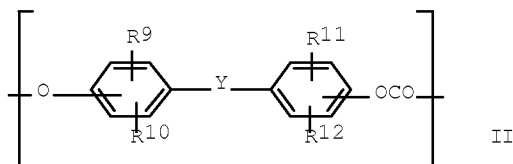
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 08311193	A	19961126	JP 1995-122710	1995 0522
JP 3460754	B2	20031027	JP 1995-122710	1995 0522

PRIORITY APPLN. INFO.: <--<--

ED Entered STN: 03 Mar 1997
GI



I



II

AB The title copolycarbonate has structural repeating units 1-60 mol.% I (R1-8 = H, F, Cl, Br, I, C1-5 alkyl, C6-12 aryl, C2-5 alkenyl, C1-5 alkoxy, C7-17 aralkyl; X = specified connection group) and II (R9-12 = H, F, Cl, Br, I, C1-5 alkyl, C6-12 aryl, C2-5 alkenyl, C1-5 alkoxy, C7-17 aralkyl; Y = specified connection group), wherein the copolycarbonate has a limiting viscosity of 0.30-2.00 dL/g. The copolycarbonate is prepared by polymerizing bisphenol derivs. and a carbonic compound. The electrophotog. photoreceptor utilizing the copolycarbonate shows excellent durability.

IT 135099-46-6P 135355-00-9P 159043-45-5P
159878-40-7P 186521-18-6P

10/553,775-294324-EIC SEARCH

RL: DEV (Device component use); PNU (Preparation, unclassified);
PREP (Preparation); USES (Uses)
(copolycarbonate suitable for electrophotog.
photoreceptor binder)

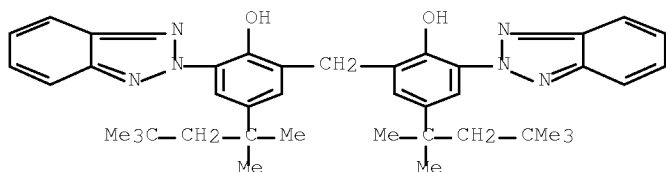
RN 135099-46-6 HCAPLUS

CN Carbonic dichloride, polymer with
2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-(1,1,3,3-
tetramethylbutyl)phenol] and 4,4'-(1-methylethylidene)bis[phenol]
(9CI) (CA INDEX NAME)

CM 1

CRN 103597-45-1

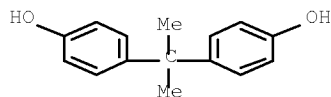
CMF C41 H50 N6 O2



CM 2

CRN 80-05-7

CMF C15 H16 O2



CM 3

CRN 75-44-5

CMF C C12 O



RN 135355-00-9 HCAPLUS

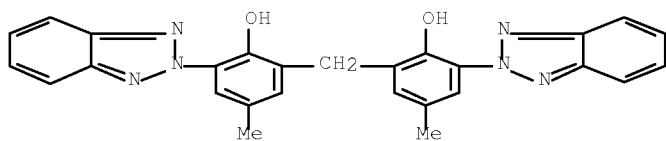
CN Carbonic dichloride, polymer with
2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-methylphenol] and
4,4'-(1-methylethylidene)bis[phenol] (9CI) (CA INDEX NAME)

CM 1

CRN 30653-05-5

CMF C27 H22 N6 O2

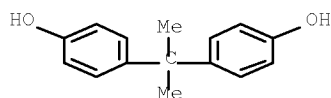
10/553,775-294324-EIC SEARCH



CM 2

CRN 80-05-7

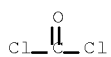
CMF C15 H16 O2



CM 3

CRN 75-44-5

CMF C C12 O



RN 159043-45-5 HCAPLUS

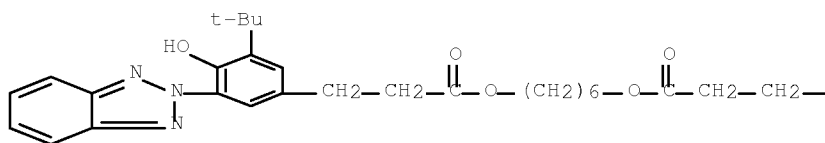
CN Benzenepropanoic acid, 3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxy-, 1,6-hexanediyl ester, polymer with carbonic dichloride and 4,4'-(1-methylethylidene)bis[phenol] (9CI)
(CA INDEX NAME)

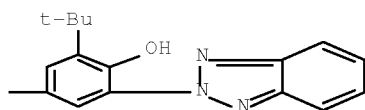
CM 1

CRN 84268-08-6

CMF C44 H52 N6 O6

PAGE 1-A

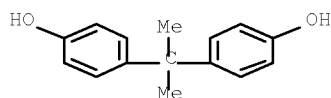




CM 2

CRN 80-05-7

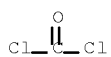
CMF C15 H16 O2



CM 3

CRN 75-44-5

CMF C C12 O



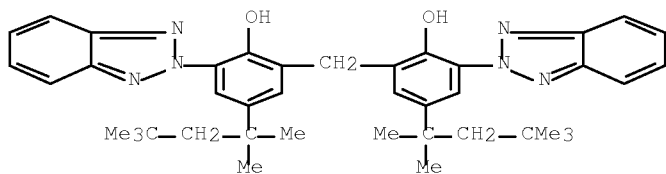
RN 159878-40-7 HCAPLUS

CN Carbonic dichloride, polymer with 4,4'-cyclohexylidenebis[phenol]
and 2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-(1,1,3,3-
tetramethylbutyl)phenol] (9CI) (CA INDEX NAME)

CM 1

CRN 103597-45-1

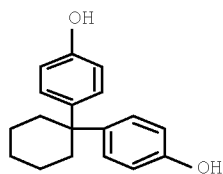
CMF C41 H50 N6 O2



CM 2

CRN 843-55-0

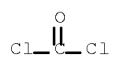
CMF C18 H20 O2



CM 3

CRN 75-44-5

CMF C C12 O



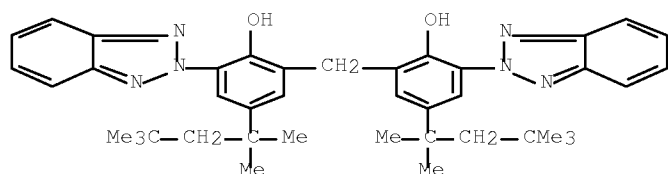
RN 186521-18-6 HCAPLUS

CN Carbonic dichloride, polymer with
 2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-(1,1,3,3-tetramethylbutyl)phenol] and
 4,4'-(1-methylethylidene)bis[2-methylphenol] (9CI) (CA INDEX NAME)

CM 1

CRN 103597-45-1

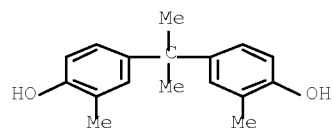
CMF C41 H50 N6 O2



CM 2

CRN 79-97-0

CMF C17 H20 O2

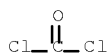


10/553,775-294324-EIC SEARCH

CM 3

CRN 75-44-5

CMF C C12 O



IC ICM C08G064-12
ICS C08G064-24; C08G064-30; C09D169-00; G03G005-05

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35

ST copolycarbonate polycarbonate electrophotog
photoreceptor binder

IT Electrophotographic photoconductors
(photoreceptors)
(binders; copolycarbonate suitable for electrophotog.
photoreceptor binder and its preparation)

IT Polycarbonates, preparation
RL: DEV (Device component use); PNU (Preparation, unclassified);
PREP (Preparation); USES (Uses)
(copolycarbonate suitable for electrophotog.
photoreceptor binder)

IT 135099-46-6P 135355-00-9P 159043-45-5P
159878-40-7P 186521-18-6P
RL: DEV (Device component use); PNU (Preparation, unclassified);
PREP (Preparation); USES (Uses)
(copolycarbonate suitable for electrophotog.
photoreceptor binder)

L31 ANSWER 26 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 1995:833360 HCAPLUS Full-text

DOCUMENT NUMBER: 123:343570

ORIGINAL REFERENCE NO.: 123:61615a,61618a

TITLE: Anticorrosive weather- and hot water-resistant
cationic electrodeposition coating
compositions

INVENTOR(S): Tanimoto, Motoi; Tatsumi, Jinichi; Inoe,
Tsuyoshi

PATENT ASSIGNEE(S): Nippon Paint Co Ltd, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 07166112	A	19950627	JP 1993-310751	1993 1210

PRIORITY APPLN. INFO.: <--
JP 1993-310751
1993
1210

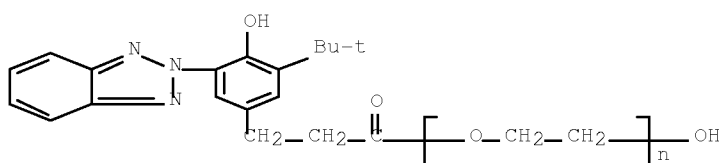
ED Entered STN: 05 Oct 1995

AB The title compns. contain acrylic resins having OH groups, tertiary amino groups, ester groups, and CO₂H groups on side chains, 50.0-90.0, crosslinking agents 10.0-50.0, UV

light absorbers 0.4-10.0, and hindered amine-type light stabilizers 0.2-5.0%. Thus, a coating was obtained from acrylic resin [prepared from styrene-glycidyl methacrylate-2-hydroxyethyl methacrylate-Bu acrylate-Et methacrylate-Bu methacrylate-2-(methylamino)ethanol copolymer and 2.2 parts Rikacid HH-A] 700.0, crosslinking agent (prepared from IPDI, 2-ethylhexanol and trimethylolpropane) 300.0, Tinuvin 1130 (UV absorber) 20.0, ADK Stab LA-62 (hindered amine) 10.0, pigment paste 63.3 parts (as solid), AcOH, and H₂O.

RL: MOA (Modifier or additive use); PRP (Properties); TEM
(Technical or engineered material use); USES (Uses)
(UV absorber; anticorrosive weather- and hot water-resistant
cationic electrodeposition coating compns.)

CN Poly(oxy-1,2-ethanediyl), α -[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]- ω -hydroxy-
(CA INDEX NAME)



IT 77-99-6DP, Trimethylolpropane, reaction products with 2-ethylhexanol and IPDI, copolymers with functional group-containing acrylic resins 80-62-6DP, Methyl methacrylate, reaction products with functional group-containing (meth)acrylates, copolymers with

10/553,775-294324-EIC SEARCH

blocked polyisocyanates 85-42-7DP, Rikacid HH-A, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 97-63-2DP, Ethyl methacrylate, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 97-88-1DP, Butyl methacrylate, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 100-42-5DP, Styrene, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 104-76-7DP, 2-Ethylhexanol, reaction products with IPDI and trimethylolpropane, copolymers with functional group-containing acrylic resins 106-91-2DP, Glycidyl methacrylate, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 109-83-1DP, 2-(Methylamino)ethanol, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 141-32-2DP, Butyl acrylate, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 868-77-9DP, 2-Hydroxyethyl methacrylate, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 4098-71-9DP, IPDI, reaction products with 2-ethylhexanol and trimethylolpropane, copolymers with functional group-containing acrylic resins 68548-08-3DP, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 85099-10-1DP, Placel FM 1, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates

RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(anticorrosive weather- and hot water-resistant cationic ~~electrodeposition~~ coating compns.)

IT 107119-91-5, ADK Stab LA 62

RL: MOA (Modifier or additive use); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(light stabilizer; anticorrosive weather- and hot water-resistant cationic ~~electrodeposition~~ coating compns.)

L31 ANSWER 27 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 1994:325861 HCAPLUS Full-text

DOCUMENT NUMBER: 120:325861

ORIGINAL REFERENCE NO.: 120:57317a,57320a

TITLE: Cationic ~~electrodeposition~~ coating compositions

INVENTOR(S): Imai, Toshio; Shimomura, Kiichi; Tanaka, Takashi

PATENT ASSIGNEE(S): Nippon Oils & Fats Co Ltd, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.

CODEN: JKXXAF

DOCUMENT TYPE: ~~Patent~~

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
JP 05320546	A	19931203	JP 1992-160409	1992 0527

PRIORITY APPLN. INFO.: <--
JP 1992-160409

1992
0527

<--

10/553,775-294324-EIC SEARCH

ED Entered STN: 25 Jun 1994

AB Title compns., effective for preventing UV-induced delamination when used as undercoats, comprise resins (as solid) 100, hydrophobic UV absorbers 0.2-10, and hindered amines 0.2-8 parts. Thus, a coating containing epoxy resin-amine reaction products 886, 2-[2-hydroxy-3,5-di(1,1-dimethylbenzyl)phenyl]benzotriazole 19, and bis(1-octyloxy-2,2,6,6-tetramethyl-4-piperidyl) sebacate 12 parts, and a pigment paste were applied electrophoretically and cured to form a 20 μm -thick film, which was coated with an acrylic-melamine topcoat with cross-cut adhesion 100/100 initially and also after 500-h accelerated weathering test.

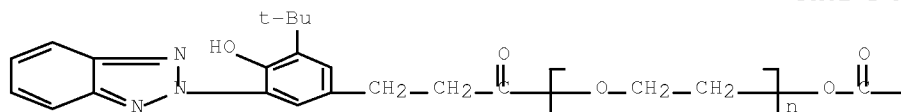
IT 104810-47-1 104810-48-2

RL: USES (Uses)
(UV absorber, cationic ~~electrodeposition~~ undercoats containing hindered amines and, resistant to UV-induced delamination from topcoats)

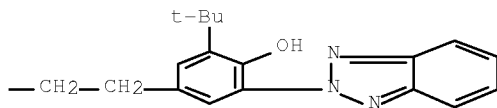
RN 104810-47-1 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]- ω -[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropoxy]- (CA INDEX NAME)

PAGE 1-A

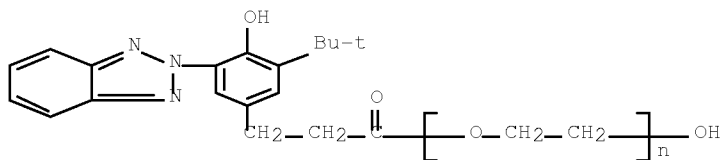


PAGE 1-B



RN 104810-48-2 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]- ω -hydroxy- (CA INDEX NAME)



IC ICM C09D005-44

CC 42-7 (Coatings, Inks, and Related Products)

ST cationic ~~electrodeposition~~ undercoat delamination prevention; UV absorber cationic ~~electrodeposition~~ undercoat; hindered amine cationic ~~electrodeposition~~ undercoat

IT ~~Electrodeposits~~ and Electroplates
(cationic, containing hydrophobic UV absorbers and hindered amines,

10/553,775-294324-EIC SEARCH

undercoats, resistant to UV-induced delamination from topcoats)

IT Light stabilizers
(UV, cationic ~~electrodeposition~~ undercoats containing hindered amines and, resistant to UV-induced delamination from topcoats)

IT Amines, uses
RL: USES (Uses)
(hindered, cationic ~~electrodeposition~~ undercoats containing UV absorbers and, resistant to UV-induced delamination from topcoats)

IT 70321-86-7 104810-47-1 104810-48-2
RL: USES (Uses)
(UV absorber, cationic ~~electrodeposition~~ undercoats containing hindered amines and, resistant to UV-induced delamination from topcoats)

IT 63843-89-0 122586-52-1
RL: USES (Uses)
(cationic ~~electrodeposition~~ undercoats containing UV absorbers and, resistant to UV-induced delamination from topcoats)

L31 ANSWER 28 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 1992:265242 HCAPLUS Full-text

DOCUMENT NUMBER: 116:265242

ORIGINAL REFERENCE NO.: 116:44799a,44802a

TITLE: Voltage-activated opaque-transparent-changing sheet materials

INVENTOR(S): Matsuda, Minoru; Yamakido, Masayoshi; Ito, Hidemi; Iwata, Koichi; Nakagawa, Sumihito

PATENT ASSIGNEE(S): Takiron Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
JP 03255423	A	19911114	JP 1990-339056	1990 1130
			<--	
PRIORITY APPLN. INFO.:			JP 1990-5368	A1 1990 0112
			<--	
			JP 1990-21850	A1 1990 0130
			<--	

ED Entered STN: 27 Jun 1992

AB The material comprises (1) a 1st transparent ~~electrode~~, (2) a liquid crystal dispersed in a cured epoxy resin, (3) a 2nd transparent ~~electrode~~. Optionally, the liquid crystal contains a UV absorber and/or a radical-capturing compound; a resin layer containing a UV absorber is formed between (1) and (2) and/or (2) and (3); the liquid crystal consists of a derivative of salicylate, benzophenone, benzotriazole, benzoate, hydroquinone, cyanoacrylate, thiodipropionic acid, hindered phenol, hindered amine; and the epoxy is cured using trimethylolpropane-tris-(β -thiopropionate) as a hardener. The material exhibits a reversible transparent-opaque change by on-off of the applied voltage and is suited for use in blinds, partitions, windows, and domes.

IT 141655-67-6

RL: USES (Uses)

(liquid crystal, voltage-activated light-shading sheet containing)

RN 141655-67-6 HCAPLUS

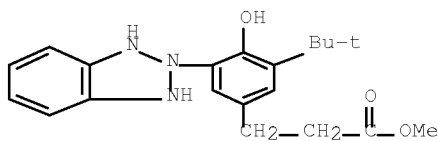
10/553,775-294324-EIC SEARCH

CN Benzenepropanoic acid, 3-(1,3-dihydro-2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxy-, methyl ester, polymer with 1,2-ethanediol (9CI) (CA INDEX NAME)

CM 1

CRN 141655-66-5

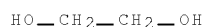
CMF C20 H25 N3 O3



CM 2

CRN 107-21-1

CMF C2 H6 O2



IC ICM G02F001-1333

ICS C09K019-54; E06B009-24; G02F001-137

CC 73-12 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)

IT 82151-62-0, E 43 (Liquid crystal) 141655-66-5

RL: USES (Uses)

(liquid crystal, voltage-activated light-shading sheet containing)

L31 ANSWER 29 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 1977:509437 HCAPLUS Full-text

DOCUMENT NUMBER: 87:109437

ORIGINAL REFERENCE NO.: 87:17287a,17290a

TITLE: Light-sensitive material for positively active photovarnish used in manufacturing printing plates

INVENTOR(S): Wallbillich, Guenter; Saenger, Dietrich; Bronstert, Bernd

PATENT ASSIGNEE(S): BASF A.-G., Fed. Rep. Ger.

SOURCE: Ger. Offen., 16 pp.

CODEN: GWXXBX

DOCUMENT TYPE: ~~Patent~~

LANGUAGE: German

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	
DE 2545957	A1	19770421	DE 1975-2545957	

1975
1014

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PRIORITY APPLN. INFO.: DE 1975-2545957

1975
1014

10/553,775-294324-EIC SEARCH

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ED Entered STN: 12 May 1984

AB Pos.-working quinone diazide type photoresists with improved light sensitivity are prepared Thus, 2,2',4,4'-tetrahydroxybenzophenone monoacetate 1 part dissolved in dioxane 10 parts was treated with 2 equivalent o-quinonediazidesulfonyl chloride. At 30°, a 1.5 molar excess Et3N was slowly added, and after 2 h the solution was filtered and poured into excess H2O and the yellow diazo compound (I) was collected. Then 70 parts I in 270 parts dioxane was treated with 210 parts Bisphenol A, 30 parts paraformaldehyde, and 4 parts p-toluenesulfonic acid. The reaction mixture was heated for 60 min at 60° and poured into a 4-fold excess MeOH containing 0.95 parts NaOH. A light-sensitive phenolic resin (II) with a mol. weight of 1880 was precipitated with H2O and collected. A solution containing II 200, Fanal blue B (C.I. 42595:2) 0.1% and EtCOMe-dioxane (3:1) 1800 was coated on a clean ~~anodized~~ Al plate. After drying the plate was exposed for 45 s with a 8000 W pulsed Xe lamp at 135-cm distance. The plate was developed in a 5% Na3PO4 solution for 30 s, followed by a H2O rinse and a dip in 1% H3PO4. After rinsing and drying the plate was used on a press to give 75,000 clean sharp prints.

IT ~~63956-53-6~~

RL: USES (Uses)

(photosensitive compns. containing, for lithog. plates)

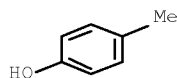
RN 63956-53-6 HCAPLUS

CN 1-Naphthalenesulfonic acid, 6-diazo-5,6-dihydro-5-oxo-, monoester with 4-(2H-benzotriazol-2-yl)-1,3-benzenediol, polymer with formaldehyde and 4-methylphenol (9CI) (CA INDEX NAME)

CM 1

CRN 106-44-5

CMF C7 H8 O



CM 2

CRN 50-00-0

CMF C H2 O



CM 3

CRN 63956-52-5

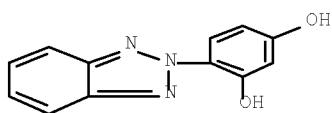
CMF C22 H13 N5 O5 S

CCI IDS

CM 4

CRN 22607-31-4

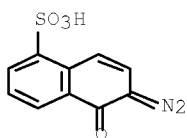
CMF C12 H9 N3 O2



CM 5

CRN 20546-03-6

CMF C10 H6 N2 O4 S



IC G03F007-10

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic Processes)

IT 63956-50-3 63956-54-7

RL: USES (Uses)

(photosensitive compns. containing, for lithog. plates)

10/553,775-294324-EIC SEARCH

FULL SEARCH HISTORY

=> => d his nofile

(FILE 'HOME' ENTERED AT 13:38:10 ON 18 MAY 2009)

FILE 'HCAPLUS' ENTERED AT 13:38:17 ON 18 MAY 2009

E US20070043204/PN

L1 1 SEA SPE=ON ABB=ON PLU=ON US20070043204/PN
SEL RN

FILE 'REGISTRY' ENTERED AT 13:39:02 ON 18 MAY 2009

L2 4 SEA SPE=ON ABB=ON PLU=ON (794518-77-7/BI OR
794518-81-3/BI OR 794518-84-6/BI OR 95-14-7/BI)
E N3C2/ES

FILE 'LREGISTRY' ENTERED AT 13:40:30 ON 18 MAY 2009

L3 STR

FILE 'REGISTRY' ENTERED AT 13:42:41 ON 18 MAY 2009

L4 SCR 2043
L5 50 SEA SSS SAM L3 AND L4
L6 2975 SEA SSS FUL L3 AND L4
SAV TEMP L6 FAN775REG/A
L7 3 SEA SPE=ON ABB=ON PLU=ON L2 AND L6

FILE 'HCAPLUS' ENTERED AT 13:44:57 ON 18 MAY 2009

L8 1 SEA SPE=ON ABB=ON PLU=ON L7
L9 1424 SEA SPE=ON ABB=ON PLU=ON L6
L10 1225078 SEA SPE=ON ABB=ON PLU=ON OPTIC?
L11 153 SEA SPE=ON ABB=ON PLU=ON L9 AND L10
L12 QUE SPE=ON ABB=ON PLU=ON DEVICE? OR CONTRIVANCE? OR
INVENTION? OR APPARAT? OR APP## OR IMPLEMENT? OR
INSTRUMENT? OR TOOL? OR UTENSIL? OR EQUIP?
L13 149242 SEA SPE=ON ABB=ON PLU=ON L10(2A)L12
L14 41 SEA SPE=ON ABB=ON PLU=ON L13 AND L11
D SCA L1
L15 86 SEA SPE=ON ABB=ON PLU=ON L9 AND ?LUMIN?
L16 7 SEA SPE=ON ABB=ON PLU=ON L14 AND L15
L17 1254 SEA SPE=ON ABB=ON PLU=ON (ANOD? OR CATHOD?)(2A)(REFL
ECT? OR TRANSMIS?)
L18 0 SEA SPE=ON ABB=ON PLU=ON L9 AND L17
L19 57 SEA SPE=ON ABB=ON PLU=ON L9 AND (REFLECT? OR
TRANSMIS?)
L20 18 SEA SPE=ON ABB=ON PLU=ON L9 AND (ANOD? OR CATHOD?
OR ELECTROD?)
L21 3 SEA SPE=ON ABB=ON PLU=ON L19 AND L20
L22 QUE SPE=ON ABB=ON PLU=ON (CHARG? OR HOLE# OR
ELECTRON# OR E)(2A)(TRANSPORT? OR MIGRAT? OR TRANSFER?
OR MOVE# OR MOVING# OR MOVEMENT? OR CARR?)
L23 5 SEA SPE=ON ABB=ON PLU=ON L9 AND L22
L24 28 SEA SPE=ON ABB=ON PLU=ON L16 OR L20 OR L21 OR L23
L25 QUE SPE=ON ABB=ON PLU=ON PY=<2004 NOT P/DT
L26 QUE SPE=ON ABB=ON PLU=ON (PY=<2004 OR PRY=<2004 OR
AY=<2004 OR MY=<2004 OR REVIEW/DT) AND P/DT
L27 24 SEA SPE=ON ABB=ON PLU=ON L24 AND (L25 OR L26)
L28 QUE SPE=ON ABB=ON PLU=ON PHOTOELECTR? OR PHOTO?(A)EL
ECTR?
L29 7 SEA SPE=ON ABB=ON PLU=ON L9 AND L28
L30 7 SEA SPE=ON ABB=ON PLU=ON L29 AND (L25 OR L26)
L31 29 SEA SPE=ON ABB=ON PLU=ON L27 OR L30
SAV TEMP L31 FAN775HCP/A
D QUE STAT L31
D L31 1-29 IBIB ED ABS HITSTR HITIND